# **EAST Search History**

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	106	((HFC-32 or difluoroethane or R-32 or (hydrofluorocarbon adj "32") or HFC32) and ("CF.sub.3I." or (trifluoromethyl adj iodide) or iodotrifluoromethane or monoiodotrifluoromethane or (perfluoromethyl adj iodide) or (TRIFLUOROMETHYL adj IODIDE) or IODOTRIFLUOROMETHANE or MONOIODOTRIFLUOROMETHANE or (PERFLUOROMETHYL adj IODIDE) or CF3I or TRIFLUOROIODOMETHANE or trifluoroiodomethane))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/03/02 13:08
<b>S2</b>	15	((HFC-32 or difluoroethane or R-32 or (hydrofluorocarbon adj "32") or HFC32) and ("CF.sub.3I." or (trifluoromethyl adj iodide) or iodotrifluoromethane or monoiodotrifluoromethane or (perfluoromethyl adj iodide) or (TRIFLUOROMETHYL adj IODIDE) or IODOTRIFLUOROMETHANE or MONOIODOTRIFLUOROMETHANE or (PERFLUOROMETHYL adj IODIDE) or CF3I or TRIFLUOROIODOMETHANE or trifluoroiodomethane))	USOCR; EPO; JPO; DERWENT	OR	OFF	2006/03/02 13:00
<b>S</b> 3	93	S1 and (@ad<="20040416" or @prad<="20040416")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/03/02 13:01
S4	21	(("20050233933") or ("20060033071") or ("20060019857") or ("20060022166") or ("20060043330") or ("20060025322") or ("6270689") or ("6649079") or ("20030178597") or ("20040256594") or ("20050233923") or ("6843930") or ("20040021124") or ("5562861") or ("5444102") or ("6526764") or ("20050230657") or ("5674451") or ("5611210") or ("5685915") or ("6875370")).PN.	US-PGPUB; USPAT	OR	OFF	2006/03/02 13:01
S5	14	S4 and (@ad<="20040416" or @prad<="20040416")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/03/02 13:07
S6	2	S4 and (@ad="20040416" or @prad="20040416")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/03/02 13:08
<b>S7</b>	0	S6 and ((HFC-32 or difluoroethane or R-32 or (hydrofluorocarbon adj "32") or HFC32) and ("CF.sub.3I." or (trifluoromethyl adj iodide) or iodotrifluoromethane or monoiodotrifluoromethane or (perfluoromethyl adj iodide) or (TRIFLUOROMETHYL adj IODIDE) or IODOTRIFLUOROMETHANE or MONOIODOTRIFLUOROMETHANE or (PERFLUOROMETHYL adj IODIDE) or CF3I or TRIFLUOROIODOMETHANE or trifluoroiodomethane)).clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/03/02 13:08

3/2/06 4:45:17 PM Page 1

Welcome to STN International! Enter x:x

LOGINID:ssspta1751gxw

PASSWORD:

TERMINAL (ENTER 1, 2, 3, OR ?):2

\* \* \* \* \* \* \* \* \* Welcome to STN International NEWS Web Page URLs for STN Seminar Schedule - N. America NEWS 2 "Ask CAS" for self-help around the clock NEWS 3 DEC 05 CASREACT(R) - Over 10 million reactions available NEWS 4 DEC 14 2006 MeSH terms loaded in MEDLINE/LMEDLINE NEWS 5 DEC 14 2006 MeSH terms loaded for MEDLINE file segment of TOXCENTER NEWS 6 DEC 14 CA/CAplus to be enhanced with updated IPC codes NEWS 7 DEC 21 IPC search and display fields enhanced in CA/CAplus with the IPC reform DEC 23 New IPC8 SEARCH, DISPLAY, and SELECT fields in USPATFULL/ NEWS IPC 8 searching in IFIPAT, IFIUDB, and IFICDB NEWS 9 JAN 13 NEWS 10 JAN 13 New IPC 8 SEARCH, DISPLAY, and SELECT enhancements added to INPADOC NEWS 11 JAN 17 Pre-1988 INPI data added to MARPAT NEWS 12 JAN 17 IPC 8 in the WPI family of databases including WPIFV NEWS 13 JAN 30 Saved answer limit increased NEWS 14 JAN 31 Monthly current-awareness alert (SDI) frequency added to TULSA NEWS 15 FEB 21 STN AnaVist, Version 1.1, lets you share your STN AnaVist visualization results NEWS 16 FEB 22 Status of current WO (PCT) information on STN NEWS 17 FEB 22 The IPC thesaurus added to additional patent databases on STN NEWS 18 FEB 22 Updates in EPFULL; IPC 8 enhancements added NEWS 19 FEB 27 New STN AnaVist pricing effective March 1, 2006 NEWS 20 FEB 28 MEDLINE/LMEDLINE reload improves functionality NEWS 21 FEB 28 TOXCENTER reloaded with enhancements NEWS 22 FEB 28 REGISTRY/ZREGISTRY enhanced with more experimental spectral property data NEWS 23 MAR 01 INSPEC reloaded and enhanced NEWS EXPRESS FEBRUARY 15 CURRENT VERSION FOR WINDOWS IS V8.01a, CURRENT MACINTOSH VERSION IS V6.0c(ENG) AND V6.0Jc(JP), AND CURRENT DISCOVER FILE IS DATED 19 DECEMBER 2005. V8.0 AND V8.01 USERS CAN OBTAIN THE UPGRADE TO V8.01a AT http://download.cas.org/express/v8.0-Discover/ STN Operating Hours Plus Help Desk Availability NEWS HOURS NEWS INTER General Internet Information NEWS LOGIN Welcome Banner and News Items NEWS PHONE Direct Dial and Telecommunication Network Access to STN NEWS WWW CAS World Wide Web Site (general information)

Enter NEWS followed by the item number or name to see news on that specific topic.

All use of STN is subject to the provisions of the STN Customer agreement. Please note that this agreement limits use to scientific research. Use for software development or design or implementation of commercial gateways or other similar uses is prohibited and may result in loss of user privileges and other penalties.

=> s difluoroethane/cn

THIS COMMAND NOT AVAILABLE IN THE CURRENT FILE
Some commands only work in certain files. For example, the EXPAND

command can only be used to look at the index in a file which has an index. Enter "HELP COMMANDS" at an arrow prompt (=>) for a list of

commands which can be used in this file.

=> file reg

COST IN U.S. DOLLARS

SINCE FILE TOTAL ENTRY SESSION

FULL ESTIMATED COST

ENTRY SESSION 0.21 0.21

FILE 'REGISTRY' ENTERED AT 11:33:07 ON 02 MAR 2006 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT. PLEASE SEE "HELP USAGETERMS" FOR DETAILS. COPYRIGHT (C) 2006 American Chemical Society (ACS)

Property values tagged with IC are from the ZIC/VINITI data file provided by InfoChem.

STRUCTURE FILE UPDATES: 1 MAR 2006 HIGHEST RN 875609-25-9 DICTIONARY FILE UPDATES: 1 MAR 2006 HIGHEST RN 875609-25-9

New CAS Information Use Policies, enter HELP USAGETERMS for details.

TSCA INFORMATION NOW CURRENT THROUGH January 6, 2006

Please note that search-term pricing does apply when conducting SmartSELECT searches.

\*\*\*\*\*\*\*\*\*\*\*\*\*\*\*\*\*\*\*

\*
\* The CA roles and document type information have been removed from \*
\* the IDE default display format and the ED field has been added, \*

\* effective March 20, 2005. A new display format, IDERL, is now

 $^st$  available and contains the CA role and document type information.  $^st$ 

Structure search iteration limits have been increased. See HELP SLIMITS

REGISTRY includes numerically searchable data for experimental and predicted properties as well as tags indicating availability of experimental property data in the original document. For information

http://www.cas.org/ONLINE/UG/regprops.html

on property searching in REGISTRY, refer to:

=> s difluoroethane/cn

for details.

L1 1 DIFLUOROETHANE/CN

=> s trifluoromethyl iodide/cn

L2 1 TRIFLUOROMETHYL IODIDE/CN

=> file caplus,uspatful COST IN U.S. DOLLARS

SINCE FILE TOTAL ENTRY SESSION 9.96 10.17

FULL ESTIMATED COST

FILE 'CAPLUS' ENTERED AT 11:33:34 ON 02 MAR 2006
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
COPYRIGHT (C) 2006 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPATFULL' ENTERED AT 11:33:34 ON 02 MAR 2006
CA INDEXING COPYRIGHT (C) 2006 AMERICAN CHEMICAL SOCIETY (ACS)

```
=> s l1 and l2
1.3
           0 L1 AND L2
=> s l1
L4
          214 L1
=> s 12
L5
         2027 L2
=> s 14 and 15
            0 L4 AND L5
1.6
=> file reg
COST IN U.S. DOLLARS
                                               SINCE FILE
                                                              TOTAL
                                                    ENTRY
                                                            SESSION
FULL ESTIMATED COST
                                                     1.97
                                                              12.14
FILE 'REGISTRY' ENTERED AT 11:34:05 ON 02 MAR 2006
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
COPYRIGHT (C) 2006 American Chemical Society (ACS)
Property values tagged with IC are from the ZIC/VINITI data file
provided by InfoChem.
STRUCTURE FILE UPDATES:
                          1 MAR 2006 HIGHEST RN 875609-25-9
DICTIONARY FILE UPDATES:
                          1 MAR 2006 HIGHEST RN 875609-25-9
New CAS Information Use Policies, enter HELP USAGETERMS for details.
TSCA INFORMATION NOW CURRENT THROUGH January 6, 2006
  Please note that search-term pricing does apply when
  conducting SmartSELECT searches.
********************
* The CA roles and document type information have been removed from *
* the IDE default display format and the ED field has been added,
* effective March 20, 2005. A new display format, IDERL, is now
* available and contains the CA role and document type information.
***********
Structure search iteration limits have been increased. See HELP SLIMITS
for details.
REGISTRY includes numerically searchable data for experimental and
predicted properties as well as tags indicating availability of
experimental property data in the original document. For information
on property searching in REGISTRY, refer to:
http://www.cas.org/ONLINE/UG/regprops.html
=> d his
     (FILE 'HOME' ENTERED AT 11:32:45 ON 02 MAR 2006)
    FILE 'REGISTRY' ENTERED AT 11:33:07 ON 02 MAR 2006
L1
             1 S DIFLUOROETHANE/CN
L2
             1 S TRIFLUOROMETHYL IODIDE/CN
    FILE 'CAPLUS, USPATFULL' ENTERED AT 11:33:34 ON 02 MAR 2006
             0 S L1 AND L2
L3
           214 S L1
L4
L5
          2027 S L2
             0 S L4 AND L5
L6
```

```
=> d l1
1.1
     ANSWER 1 OF 1 REGISTRY COPYRIGHT 2006 ACS on STN
     25497-28-3 REGISTRY
RN
ED
     Entered STN: 16 Nov 1984
CN
     Ethane, difluoro- (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)
OTHER NAMES:
     Difluoroethane
CN
     C2 H4 F2
MF
CI
     IDS, COM
LC
                  BIOSIS, CA, CAOLD, CAPLUS, CASREACT, CHEMLIST, CIN, DETHERM*,
     STN Files:
       ENCOMPLIT, ENCOMPLIT2, ENCOMPPAT, ENCOMPPAT2, IFICDB, IFIPAT, IFIUDB,
       NIOSHTIC, PDLCOM*, PIRA, PROMT, TOXCENTER, TULSA, USPAT2, USPATFULL, VTB
          (*File contains numerically searchable property data)
1/2 H<sub>3</sub>C-CH<sub>3</sub>
     D1-F
**PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT**
             164 REFERENCES IN FILE CA (1907 TO DATE)
             164 REFERENCES IN FILE CAPLUS (1907 TO DATE)
               3 REFERENCES IN FILE CAOLD (PRIOR TO 1967)
=> d 12
L2
     ANSWER 1 OF 1 REGISTRY COPYRIGHT 2006 ACS on STN
RN
     2314-97-8 REGISTRY
ED
     Entered STN: 16 Nov 1984
     Methane, trifluoroiodo- (6CI, 8CI, 9CI) (CA INDEX NAME)
OTHER NAMES:
CN
    Freon 13I1
CN
     Iodotrifluoromethane
CN
    Monoiodotrifluoromethane
CN
     Perfluoromethyl iodide
CN
    R 13I1
CN
     Trifluoroiodomethane
     Trifluoromethyl iodide
CN
FS
     3D CONCORD
DR
     263005-66-9
MF
     C F3 I
CI
LC
     STN Files:
                  BEILSTEIN*, BIOSIS, CA, CAOLD, CAPLUS, CASREACT, CHEMCATS,
       CHEMINFORMRX, CHEMLIST, CHEMSAFE, CIN, CSCHEM, CSNB, DETHERM*, DIPPR*,
       GMELIN*, IFICDB, IFIPAT, IFIUDB, MEDLINE, MSDS-OHS, PROMT, PS, RTECS*,
       SPECINFO, TOXCENTER, ULIDAT, USPAT2, USPATFULL, VTB
         (*File contains numerically searchable property data)
     Other Sources:
                      EINECS**, NDSL**, TSCA**
         (**Enter CHEMLIST File for up-to-date regulatory information)
```



```
1837 REFERENCES IN FILE CA (1907 TO DATE)
```

- 12 REFERENCES TO NON-SPECIFIC DERIVATIVES IN FILE CA
- 1839 REFERENCES IN FILE CAPLUS (1907 TO DATE)
  - 88 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

#### => d his

L1

1.3

(FILE 'HOME' ENTERED AT 11:32:45 ON 02 MAR 2006)

FILE 'REGISTRY' ENTERED AT 11:33:07 ON 02 MAR 2006

1 S DIFLUOROETHANE/CN

L2 1 S TRIFLUOROMETHYL IODIDE/CN

FILE 'CAPLUS, USPATFULL' ENTERED AT 11:33:34 ON 02 MAR 2006

0 S L1 AND L2

L4 214 S L1

L5 2027 S L2

L6 0 S L4 AND L5

FILE 'REGISTRY' ENTERED AT 11:34:05 ON 02 MAR 2006

## => d 14 ti,pi

YOU HAVE REQUESTED DATA FROM FILE 'CAPLUS, USPATFULL' - CONTINUE? (Y) /N:y

L4 ANSWER 1 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN

TI Making polyurethane and polyisocyanurate foams, mixtures of a hydrofluorocarbon and methyl formate as a blowing agent, polyol premix of reduced vapor pressure

	PATENT	NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	US 2005	277701	A1	20051215	IIC 2004 968400	20040615
FI				<del>_</del>		
			A1		WO 2005-US20929	20050614
	W :	AE, AG, AL	, AM, AT	, AU, AZ,	BA, BB, BG, BR, BW, BY,	BZ, CA, CH,
		CN, CO, CR	, CU, C2	, DE, DK,	DM, DZ, EC, EE, EG, ES,	FI, GB, GD,
		GE, GH, GM	, HR, HU	J, ID, IL,	IN, IS, JP, KE, KG, KM,	KP, KR, KZ,
		LC, LK, LR	, LS, LT	LU, LV,	MA, MD, MG, MK, MN, MW,	MX, MZ, NA,
		NG, NI, NO	, NZ, OM	I, PG, PH,	PL, PT, RO, RU, SC, SD,	SE, SG, SK,
		SL, SM, SY	, TJ, TM	I, TN, TR,	TT, TZ, UA, UG, US, UZ,	VC, VN, YU,
		ZA, ZM, ZW				
	RW:	AT, BE, BG	, CH, CY	CZ, DE,	DK, EE, ES, FI, FR, GB,	GR, HU, IE,
		IS, IT, LT	, LU, MC	NL, PL,	PT, RO, SE, SI, SK, TR,	BF, BJ, CF,
		CG, CI, CM	, GA, GN	r, GQ, GW,	ML, MR, NE, SN, TD, TG,	BW, GH, GM,
					SZ, TZ, UG, ZM, ZW, AM,	
		KZ, MD, RU	, TJ, TM			

#### => d 14 ti,pi 1-

YOU HAVE REQUESTED DATA FROM FILE 'CAPLUS, USPATFULL' - CONTINUE? (Y) /N:y

# YOU HAVE REQUESTED DATA FROM 214 ANSWERS - CONTINUE? Y/(N):y

- L4 ANSWER 1 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Making polyurethane and polyisocyanurate foams, mixtures of a hydrofluorocarbon and methyl formate as a blowing agent, polyol premix of reduced vapor pressure

	PATENT	NO.		KIN	D	DATE			APPL	ICAT	ION :	NO.		D.	ATE	
			-		-									-		
ΡI	US 2005	277701	•	<b>A1</b>		2005	1215	1	US 2	004-	8684	00		2	0040	615
	WO 2006			<b>A</b> 1		2006			WO 2						0050	
	₩:	AE, AG	, AL,	AM,	ΑT,	AU,	ΑZ,	BA,	BB,	BG,	BR,	BW,	BY,	BZ,	CA,	CH,
		CN, CO	, CR,	CU,	CZ,	DE,	DK,	DM,	DZ,	EC,	EE,	EG,	ES,	FI,	GB,	GD,
		GE, GH	, GM,	HR,	HU,	ID,	IL,	IN,	IS,	JP,	KE,	KG,	KM,	KP,	KR,	KZ,
		LC, LK	, LR,	LS,	LT,	LU,	LV,	MA,	MD,	MG,	MK,	MN,	MW,	MX,	MZ,	NA,

```
SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU,
            ZA, ZM, ZW
        RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE,
            IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG,
            KZ, MD, RU, TJ, TM
    ANSWER 2 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Procedure for processing hollow glassware, particularly a bottle
TI
                 KIND DATE APPLICATION NO.
    PATENT NO.
                              -----
                        ----
                                         AT 2003-941
                        A5
                              20040615
                                                                 20030617
    AT 200300941
ΡI
                         В
                               20050125
    AT 412341
    ANSWER 3 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Preparation method and equipment of difluorochloroethane
ΤI
                       KIND DATE APPLICATION NO.
                                                                DATE
    PATENT NO.
                              _____
                                          ______
    _____
                        ----
                                          CN 2004-10015778
                                                                20040109
                        Α
                               20041222
PΙ
    CN 1556083
    ANSWER 4 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Refrigerant composition with lubricant
TI
                       KIND DATE APPLICATION NO.
                                                               DATE
    PATENT NO.
                                         -----
     _____
                              _____
                        - - - -
                               20050512 WO 2004-US34724
                                                               20041020
    WO 2005042679
                        A1
ΡI
        W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH,
            CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD,
            GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC,
            LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI,
            NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY,
            TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW
        RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM,
            AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK,
            EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE,
            SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE,
            SN. TD. TG
                                          US 2004-969621
                                                                 20041020
    US 2005109977
                         A1
                               20050526
    ANSWER 5 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Closed cycle refrigeration system and mixed component refrigerant
ΤI
    PATENT NO. KIND DATE APPLICATION NO. DATE
                        ----
                              _____
                                          ______
                                                                 -----
                                          US 2003-694699
                               20050428
                                                                 20031028
ΡI
    US 2005086950
                        A1
    ANSWER 6 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Improvements in or relating to aerosol formulations comprising formoterol
TI
    fumarate dihydrate
                       KIND DATE APPLICATION NO.
    PATENT NO.
                                          ______
     ------
                       ----
                              -----
                                                                 _____
    WO 2005034927 A2
WO 2005034927 A3
                                          WO 2004-IB3465
                                                                 20041008
                               20050421
ΡI
                               20050602
    WO 2005034927
        W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH,
            CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD,
            GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC,
            LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI,
            NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY,
            TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW
        RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM,
            AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK,
            EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE,
            SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE,
            SN, TD, TG
    ANSWER 7 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Consolidation heat treating atmospheres for manufacture of sol-gel-derived
ΤI
    halogen-doped optical glass
                                          APPLICATION NO.
                                                                 DATE
                        KIND
                             DATE
    PATENT NO.
```

NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK,

```
A1
                               20041007
                                          US 2004-771176
PΙ
    US 2004194511
                        A1
                               20030807
                                          US 2002-62748
                                                                 20020201
    US 2003147605
    US 6928220
                        B2
                               20050809
                        A1
                                                                 20020807
                               20030807
                                          US 2002-215162
    US 2003147606
    ANSWER 8 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Polyol compositions containing polyether or polyester polyols and
TΙ
    polyisocyanate-based foams prepared therefrom
                                    APPLICATION NO.
                   KIND DATE
    PATENT NO.
    EP 1435366 A1 20040707 EP 2003-250046
                                                                20030103
ΡI
        R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
            IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK
                            20040729 CA 2003-2511811 20031223
                        AA
     CA 2511811
                              20040729
                                                                20031223
                        A1
                                         WO 2003-US41607
    WO 2004063243
        W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,
            CO, CR, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM,
            HR, HU, ID, IL, IN, IS, JP, KE, KG, KR, KZ, LC, LK, LR, LS, LT,
            LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT,
            RO, RU, SD, SE, SG, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, US,
            UZ, YU, ZA, ZM, ZW
        RW: BW, GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ,
            BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE,
            ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK,
            TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG
                               20051101 BR 2003-17211
                                                                20031223
    BR 2003017211
                        Α
    ANSWER 9 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Materials and methods for the conversion of hydrofluorocarbons to
ΤI
    fluoromonomers
    US 2004127757 A1 2004055
CA 2511887
                                         APPLICATION NO.
                                                                DATE
                                                                -----
                                          -----
                      A1 20040701 US 2002-331821 20021230
AA 20040722 CA 2003-2511887 20031230
ΡI
    CA 2511887 AA 20040722
WO 2004060842 A1 20040722
WO 2004060842 C1 20041021
                                         WO 2003-US41851
                                                                20031230
        W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,
            CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH,
            GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR,
            LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NI, NO, NZ, OM,
            PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN,
            TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW
        RW: BW, GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ,
            BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE,
            ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK,
            TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD,
                              20051005 EP 2003-815021
                        A1
            AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
            IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK
                                          US 2005-218055
    US 2005288536
                        A1
                              20051229
                                                                 20050831
    ANSWER 10 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Plasma device and procedure for anisotropic etching in of structures in a
ΤI
     substrate
    PATENT NO.
                      KIND DATE
                                        APPLICATION NO.
                       ----
    DE 10247913
                       A1
                              20040422 DE 2002-10247913 20021014
ΡI
                       A2 20040429
    WO 2004036627
                                        WO 2003-DE2971
                                                                 20030909
                            20040722
    WO 2004036627
                        A3
        W: JP, US
        RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE,
            IT, LU, MC, NL, PT, RO, SE, SI, SK, TR
                                         EP 2003-753277
                             20050720
    EP 1554747
                        A2
            AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
            IE, SI, FI, RO, CY, TR, BG, CZ, EE, HU, SK
    JP 2006503425
                         T2
                              20060126
                                         JP 2004-543938
                                                                20030909
```

----

--------------

L4

```
Procedure for the plasma anisotropic etching of a silicon substrate
ΤI
                              DATE
    PATENT NO.
                       KIND
                                         APPLICATION NO.
     -----
                       ----
                              -----
                                         ______
                                                                _____
                                        DE 2002-10246063
    DE 10246063
                              20040422
                                                               20021002
ΡI
                        A1
    ANSWER 12 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Method for plasma etching performance enhancement in semiconductor device
TI
    fabrication
                                        APPLICATION NO.
    PATENT NO.
                      KIND DATE
                                                               DATE
    US 2004072443 A1 20040415 US 2002-295601
                                                               20021114
PΙ
    US 6833325 B2 20041221

US 2004072430 A1 20040415 US 2003-674675 20030929

WO 2004034445 A2 20040422 WO 2003-US31712 20031006

WO 2004034445 A3 20040812

WO 2004034445 B1 20040930
        W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,
            CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH,
            GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR,
            LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NI, NO, NZ, OM,
            PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN,
            TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW
        RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY,
            KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES,
            FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR,
            BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG
                            20040504 AU 2003-282718 20031006
20050706 EP 2003-774602 20031006
    AU 2003282718
                       A1
    EP 1550153
                        A2
            AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
            IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK
                                         US 2004-946181
    US 2005037624
                        A1
                             20050217
                                                                20040920
L4
    ANSWER 13 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
ΤI
    Method for etching photolithographic reticles
    PATENT NO. KIND DATE APPLICATION NO. DATE
                                        -----
                       ----
                              -----
    JP 2004038154 A2 20040205 JP 2003-136222
                                                              20030514
PΙ
                                       US 2003-437729
    US 2004072081
                       A1
                             20040415
    ANSWER 14 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Safety tires having good durability and riding comfort
ΤI
    PATENT NO. KIND DATE APPLICATION NO.
                                         -----
                       ----
                              -----
PΙ
    JP 2003118311
                       A2
                              20030423 JP 2002-94474
                                                               20020329
    ANSWER 15 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
TT
    Silicon dioxide etching yield measurements with inductively coupled
    fluorocarbon plasmas
    ANSWER 16 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Speed-of-sound, ideal-gas heat capacity, and second acoustic virial
TI
    coefficient for mixing refrigerant difluoroethane (HFC152a) +
    difluoromethane (HCFC22)
    ANSWER 17 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Resistive plate chambers for muon detection at LHC
ΤI
    ANSWER 18 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Heat transfer fluids useable for cooling items, such as optical fibers
ΤI
    PATENT NO. KIND DATE APPLICATION NO. DATE
     -----
                       ----
                              -----
                                         ______
    WO 2002074709
                                                               20020314
PΙ
                       A1
                              20020926 WO 2002-EP3030
        W: AU, BR, CN, IN, JP
        RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL,
            PT, SE, TR
                        A1
                             20040102
                                        EP 2002-753572
    EP 1373153
        R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
            IE, FI, CY, TR
                              20040512 CN 2002-806445
                        Α
    CN 1496340
                                                                20020314
```

```
US 2004227125 A1
                                       US 2004-874079
                                                            20040622
                            20041118
    US 2005218371
                      A1
                            20051006
                                       US 2005-130331
                                                            20050517
    ANSWER 19 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Algorithmically Compressed Data and the Topological Conjecture for the
    Inner-Core Electrons
    ANSWER 20 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Substrate cleaning apparatus and method
ΤI
               KIND DATE APPLICATION NO.
                                                           DATE
    PATENT NO.
    US 2002072016 A1 20020613
US 6692903
                                       ______
                                                            -----
                                       US 2000-737373
                                                            20001213
    US 6692903 B2 20040217

WO 2002049078 A2 20020620 WO 2001-US48273

WO 2002049078 A3 20021024
                                                            20011210
        W: CN, JP, KR, SG
        RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL,
           PT, SE, TR
    ANSWER 21 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Hydrocarbon-based refrigerant mixture composition for replacing R-12 and
    R-22 refrigerants
                                                           DATE
    PATENT NO.
                      KIND DATE APPLICATION NO.
                     ----
                           -----
                                       _____
                                                            -----
    -----
                            20000705 KR 2000-17251
                                                            20000403
    KR 2000036953
                      Α
    ANSWER 22 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Formulations of mometasone and a bronchodilator for pulmonary
    administration
                                   APPLICATION NO.
                     KIND DATE
                                                           DATE
                                       -----
    -----
                    ----
                                                            -----
    WO 2002011711
                     A2 20020214 WO 2001-US24093 20010801
    WO 2002011711 A3 20030227
WO 2002011711 B1 20040422
        W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,
           CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH,
           GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR,
           LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, PL, PT,
           RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, UZ,
           VN, YU, ZA, ZW
        RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW, AM, AZ, BY, KG,
           KZ, MD, RU, TJ, TM, AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR,
           IE, IT, LU, MC, NL, PT, SE, TR, BF, BJ, CF, CG, CI, CM, GA, GN,
           GQ, GW, ML, MR, NE, SN, TD, TG
               AA 20020214
                                       CA 2001-2417973
    CA 2417973
                                                           20010801
                            20020218 AU 2001-78115
    AU 2001078115
                      A5
                      A1 20020620 US 2001-920340 20010801
A2 20030521 EP 2001-956079 20010801
                            20020620 US 2001-920340
    US 2002076382
    EP 1311294
           AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
           IE, SI, LT, LV, FI, RO, MK, CY, AL, TR
                                     US 2004-824711
    US 2004198708
                      A1
                           20041007
                                                           20040414
    ANSWER 23 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Detection of fluorine containing gas compounds
    PATENT NO. KIND DATE APPLICATION NO. DATE
                     _ _ _ _
                                       _____
    JP 2002022725
                            20020123 JP 2000-209708
                     A2
                                                           20000711
                     B2
    JP 3640601
                            20050420
    ANSWER 24 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Additivity of the Correlation Energy in Some 3D Organic Molecules
    ANSWER 25 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Fluorohydrocarbon etchant with selectivity for doped silicon dioxide over
    undoped silicon dioxide and silicon nitride, processes which employ the
    etchant, and structures formed thereby
    PATENT NO. KIND DATE APPLICATION NO. DATE
    -----
                     ----
    WO 2002003439 A2 20020110 WO 2001-US41275
                                                           20010705
```

L4

TT

L4

PΙ

L4

TI

PΙ

L4TI

PΙ

L4

TI

PΙ

L4TI

L4

TI

PΙ

```
A3 20020606
C1 20020704
     WO 2002003439 A3
WO 2002003439 C1
         W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,
        W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, UZ, VN, YU, ZA, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM

RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW, AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG
                         A2 20030402 EP 2001-956164
                                                                   20010705
     EP 1297564
             AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
             IE, SI, LT, LV, FI, RO, MK, CY, AL, TR
                          T2 20040129 JP 2002-507425
                                                                   20010705
     JP 2004503082
     ANSWER 26 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
     Fabrication of electric circuits by reactive-gas etching of masked metal
ΤI
     layers on substrates
                                           APPLICATION NO.
     PATENT NO. KIND
                                DATE
                        ----
                                            ______
     ------
    WO 2001096955 A2
                                20011220 WO 2001-US19282 20010615
PΙ
                        A3
                                20021128
     WO 2001096955
         W: JP, US
         RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL,
             PT, SE, TR
                                                                    20010615
                          A2
                                20030312 EP 2001-946420
     EP 1290495
         R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
             IE, FI, CY, TR
                                            JP 2002-511020
                                                                    20010615
     JP 2004503829
                          T2
                                20040205
                                            US 2001-24958
                                                                    20011218
     US 2003003374
                         A1
                                20030102
L4
     ANSWER 27 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
TI
     High-density plasma etching of carbon-based low-k materials in an
     integrated circuit
                              DATE APPLICATION NO.
     PATENT NO. KIND
                                                                   -----
                        ----
                                           -----
     US 6284149
                         B1
                                20010904 US 1998-156956 19980918
PΙ
     ANSWER 28 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
     Flower-like capacitor structure for a memory cell
TI
     PATENT NO. KIND DATE APPLICATION NO. DATE
                                            -----
                         ----
                                -----
                                20010828 US 1999-249840 19990215
    US 6281542 B1
ΡI
                                19991026 US 1998-60565
     US 5973350
                         Α
     ANSWER 29 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
     Apparatus for providing ozonated process fluid and methods for using same
TI
     PATENT NO. KIND DATE APPLICATION NO. DATE
     -----
                         _ _ _ _
                                -----
                                           ______
     WO 2001040124 A1 20010607 WO 2000-US42449 WO 2001040124 C2 20020808
                                                                   20001201
PΙ
         W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,
             CR, CU, CZ, DE, DK, DM, DZ, EE, ES, FI, GB, GD, GE, GH, GM, HR,
             HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT,
             LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, PL, PT, RO, RU,
             SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, UZ, VN, YU,
             ZA, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM
         RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW, AT, BE, CH, CY,
             DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR, BF,
             BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG
    ANSWER 30 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
     Cooling agent
TI
                        KIND DATE APPLICATION NO.
     PATENT NO.
                                                                  DATE
                                            -----
                               19990827 RU 1997-120359
                         C1
                                                                   19971210
ΡI
     RU 2135541
```

- L4ANSWER 31 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- Fluoroethane etchant with selectivity for doped silicon dioxide over TI undoped silicon dioxide and silicon nitride, processes which employ the etchant, and structures formed for semiconductor devices

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	US 6117791	Α	20000912	US 1998-102152	19980622
	US 6537922	B1	20030325	US 2000-625144	20000725
	US 6875371	B1	20050405	US 2000-711324	20001113
	115 2003203639	Δ1	20031030	IIS 2003-396164	20030325

- ANSWER 32 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4
- TI Evaluation of pentafluoroethane and 1,1-difluoroethane for a dielectric etch application in an inductively coupled plasma etch tool
- ANSWER 33 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4

TI	PA.	pical TENT 1	NO.	_		KIN	D	DATE		_	APP	LICA	TION	NO.		D	ATE	
ΡI	WO	2000	0457	95		A2		2000	0810				-GB36				0000	
	WO	2000		_														
		W:											, BY,					
			-				-	-					, GH,					
					-	•						•	, LR,	•				-
													, RO,					SI,
													, UZ,					
		RW:	•	•	•	•	•	•				•	, ZW,	-	-	-		-
													, NL,		SE,	BF,	ВJ,	CF,
													, TD,					
		1866				Α		2001			IN	1999	-BO93			1:	9990	
	CA	2359	640			AA		2000	0810		CA	2000	-2359	640		2		
	ΑU	2000	0244	72		A5					AU	2000	-2447	2		2	0000	207
		7595				B2		2003										
													-7997				0000	
		1150				A2					ΕP	2000	-9027	27		2	0000	207
	EP	1150						2003										
		R:	•	•	•	•	•	•	FR,	GB,	GR	, IT	, LI,	LU,	NL,	SE,	MC,	PT,
			-	-		LV,	-											
	JP	2002	5363	19		T2		2002					-5969				0000	
	NZ	5132 2523 1150	80			A		2003					-5132			_	0000	
	AΤ	2523	80			E		2003					-9027				0000	
	PT	1150	661			T		2004					-9027				0000	
	ES	2209	812			Т3		2004			ES	2000	-9027	27		2	0000	
		6962	691			B1		2005			US	2000	-5038 -5727	43		2	0000	-
		2000						2000									0001	
		2001				Α		2001					-3815				0010	
		1042				A1		2004					-1032				0020	
	US	2004	21374	44		A1		2004	1028		US	2003	-6865	17		2	0031	016

- ANSWER 34 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4
- Synthetic lubricating oil-C1-3-hydrofluorocarbon refrigerant combinations ΤI for low-temperature phase separation in refrigeration compressor units

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	WO 2000043464	A1	20000727	WO 1999-US31118	19991228
	W: AU, CA RW: AT, BE, CH, PT, SE	CY, DE	, DK, ES, FI	, FR, GB, GR, IE, IT,	LU, MC, NL,
	US 6374629	B1	20020423	US 1999-236707	19990125

- CA 2360536 20000727 CA 1999-2360536 AA 19991228 EP 1153099 A1 20011114 B1 20040929 20011114 EP 1999-968562 19991228 EP 1153099
- R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, FI
- AU 774378 B2 20040624 AU 2000-25954 19991228
- ANSWER 35 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4
- Variable load refrigeration system particularly for cryogenic temperatures TI

	PATENT NO.		DATE		DATE
DT	110 6076373	7	20000620	US 1998-222809	19981230
ΡI	US 6076372 MX 9911766 ZA 9907869 CA 2293191 CA 2293191 TW 430733 EP 1016839	A	20000620	MX 1999-11766	19991215
	MA 9911766	A.	20000731	ZA 1999-7869	19991223
	CN 2202101	C	20000703	CA 1999-2293191	19991224
	CN 2293191	ממ	20040521	CA 1333 2233131	10001111
	TW 430733	R	20010421	TW 1999-88123007	19991227
	ED 1016839	Δ2	20010421	EP 1999-126062	
	EP 1016839	λ3	20001102	11 1999 120002	
	EP 1016839	B1	20030709		
				GB, GR, IT, LI, LU, NL,	SE, MC, PT,
	IE, SI, LT			02, 010, 11, 12, 10, 11=, 1	,,,
	JP 2000205675			JP 1999-373465	19991228
	JP 3678619	B2	20050803		
	BR 9905991 CN 1265462 AT 244860	A	20000905	BR 1999-5991	19991228
	CN 1265462	A	20000906	BR 1999-5991 CN 1999-127429	19991228
•	AT 244860	E	20030715	AT 1999-126062	19991228
	ES 2197568	T3	20040101	ES 1999-126062	19991228
	AU 9965541	A1	20000706	AU 1999-65541 US 2000-545670	19991230
	AU 753979	B2	20021031		
	US 6426019	B1	20020730	US 2000-545670	20000407
	US 2003042463	A1	20030306	US 2002-201287	20020724
			20050419		
	05 0001331				
L4	ANSWER 36 OF 214	CAPLUS	COPYRIGHT	2006 ACS on STN	
TI	A process for disp				
L4	ANSWER 37 OF 214				
TI	Determination of t	he skin	viscosity	of glass via fiber elong	ation
L4	ANSWER 38 OF 214				
TI				rodifluoromethane and	
	chlorodifluorometh	ane over	nickel c	atalwata	
	Chitotoalliaolomech	and over	HICKCI C	acaryses	
				_	
L4	ANSWER 39 OF 214	CAPLUS	COPYRIGHT	_	
L4 TI	ANSWER 39 OF 214	CAPLUS	COPYRIGHT	_	
TI	ANSWER 39 OF 214 Accidental release	CAPLUS prevent	COPYRIGHT ion	2006 ACS on STN	
TI L4	ANSWER 39 OF 214 Accidental release	CAPLUS prevent CAPLUS	COPYRIGHT ion	2006 ACS on STN	
TI	ANSWER 39 OF 214 Accidental release ANSWER 40 OF 214 Cooling agent comp	CAPLUS prevent CAPLUS osition	COPYRIGHT ion COPYRIGHT	2006 ACS on STN	DATE
TI L4	ANSWER 39 OF 214 Accidental release ANSWER 40 OF 214 Cooling agent comp PATENT NO.	CAPLUS prevent CAPLUS osition KIND	COPYRIGHT ion COPYRIGHT DATE	2006 ACS on STN  2006 ACS on STN  APPLICATION NO.	DATE
TI L4 TI	ANSWER 39 OF 214 Accidental release ANSWER 40 OF 214 Cooling agent comp PATENT NO.	CAPLUS prevent CAPLUS osition KIND	COPYRIGHT ion COPYRIGHT DATE	2006 ACS on STN  2006 ACS on STN  APPLICATION NO.	<del>-</del>
TI L4	ANSWER 39 OF 214 Accidental release  ANSWER 40 OF 214 Cooling agent comp PATENT NO	CAPLUS prevent CAPLUS osition KIND A1	COPYRIGHT ion  COPYRIGHT  DATE  19990304	2006 ACS on STN  2006 ACS on STN  APPLICATION NO.  WO 1997-RU274	<del>-</del>
TI L4 TI	ANSWER 39 OF 214 Accidental release ANSWER 40 OF 214 Cooling agent comp PATENT NO.	CAPLUS prevent CAPLUS osition KIND A1	COPYRIGHT ion  COPYRIGHT  DATE  19990304	2006 ACS on STN  2006 ACS on STN  APPLICATION NO.  WO 1997-RU274	<del>-</del>
TI L4 TI PI	ANSWER 39 OF 214 Accidental release  ANSWER 40 OF 214 Cooling agent comp PATENT NO. WO 9910447 W: BY, CZ, HU	CAPLUS prevent  CAPLUS osition KIND A1 , MD, PL	COPYRIGHT ion  COPYRIGHT  DATE 19990304 , SK, UA,	2006 ACS on STN  2006 ACS on STN  APPLICATION NO.  WO 1997-RU274 US	<del>-</del>
TI L4 TI PI L4	ANSWER 39 OF 214 Accidental release  ANSWER 40 OF 214 Cooling agent comp PATENT NO. WO 9910447 W: BY, CZ, HU  ANSWER 41 OF 214	CAPLUS  prevent  CAPLUS  osition  KIND  A1  , MD, PL  CAPLUS	COPYRIGHT ion  COPYRIGHT  DATE 19990304 , SK, UA,  COPYRIGHT	2006 ACS on STN  2006 ACS on STN  APPLICATION NO. WO 1997-RU274 US  2006 ACS on STN	<del>-</del>
TI L4 TI PI	ANSWER 39 OF 214 Accidental release  ANSWER 40 OF 214 Cooling agent comp PATENT NO. WO 9910447 W: BY, CZ, HU  ANSWER 41 OF 214 Fixative vinyl ace	CAPLUS  prevent  CAPLUS  osition  KIND  A1  , MD, PL  CAPLUS  tate tet	COPYRIGHT ion  COPYRIGHT  DATE 19990304 , SK, UA,  COPYRIGHT rapolymer	2006 ACS on STN  2006 ACS on STN  APPLICATION NO. WO 1997-RU274 US  2006 ACS on STN	19970826
TI L4 TI PI L4	ANSWER 39 OF 214 Accidental release  ANSWER 40 OF 214 Cooling agent comp PATENT NO. WO 9910447 W: BY, CZ, HU  ANSWER 41 OF 214 Fixative vinyl ace PATENT NO.	CAPLUS  prevent  CAPLUS  osition  KIND  A1  , MD, PL  CAPLUS  tate tet  KIND	COPYRIGHT ion  COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE	2006 ACS on STN  2006 ACS on STN  APPLICATION NO.  WO 1997-RU274 US  2006 ACS on STN  APPLICATION NO.	19970826 DATE
TI L4 TI PI L4 TI	ANSWER 39 OF 214 Accidental release  ANSWER 40 OF 214 Cooling agent comp PATENT NO.  WO 9910447 W: BY, CZ, HU  ANSWER 41 OF 214 Fixative vinyl ace PATENT NO.	CAPLUS prevent  CAPLUS osition KIND A1 , MD, PL  CAPLUS tate tet KIND	COPYRIGHT ion  COPYRIGHT  DATE 19990304 , SK, UA,  COPYRIGHT rapolymer DATE	2006 ACS on STN  2006 ACS on STN  APPLICATION NO. WO 1997-RU274 US  2006 ACS on STN  APPLICATION NO.	19970826 DATE
TI L4 TI PI L4	ANSWER 39 OF 214 Accidental release ANSWER 40 OF 214 Cooling agent comp PATENT NO. WO 9910447 W: BY, CZ, HU ANSWER 41 OF 214 Fixative vinyl ace PATENT NO. US 5830439	CAPLUS prevent CAPLUS osition KIND A1 , MD, PL CAPLUS tate tet KIND A	COPYRIGHT ion  COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103	2006 ACS on STN  2006 ACS on STN  APPLICATION NO. WO 1997-RU274 US  2006 ACS on STN  APPLICATION NO. US 1997-857954	DATE 19970516
TI L4 TI PI L4 TI	ANSWER 39 OF 214 Accidental release ANSWER 40 OF 214 Cooling agent comp PATENT NO. WO 9910447 W: BY, CZ, HU ANSWER 41 OF 214 Fixative vinyl ace PATENT NO. US 5830439	CAPLUS prevent CAPLUS osition KIND A1 , MD, PL CAPLUS tate tet KIND A	COPYRIGHT ion  COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103	2006 ACS on STN  2006 ACS on STN  APPLICATION NO. WO 1997-RU274 US  2006 ACS on STN  APPLICATION NO. US 1997-857954	DATE 19970516
TI L4 TI PI L4 TI	ANSWER 39 OF 214 Accidental release  ANSWER 40 OF 214 Cooling agent comp PATENT NO.  WO 9910447 W: BY, CZ, HU  ANSWER 41 OF 214 Fixative vinyl ace PATENT NO.  US 5830439 US 5972329 WO 9851266	CAPLUS prevent  CAPLUS osition KIND A1 , MD, PL  CAPLUS tate tet KIND A A A	COPYRIGHT ion  COPYRIGHT  DATE 19990304 , SK, UA,  COPYRIGHT rapolymer DATE 19981103 19991026 19981119	2006 ACS on STN  2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  S  APPLICATION NO.  US 1997-857954 US 1998-34574 WO 1998-US5318	DATE 19970516
TI L4 TI PI L4 TI	ANSWER 39 OF 214 Accidental release ANSWER 40 OF 214 Cooling agent comp PATENT NO. WO 9910447 W: BY, CZ, HU ANSWER 41 OF 214 Fixative vinyl ace PATENT NO. US 5830439 US 5972329 WO 9851266 WO 9851266	CAPLUS prevent CAPLUS osition KIND A1 , MD, PL CAPLUS tate tet KIND A A A2 A3	COPYRIGHT ion  COPYRIGHT  DATE 19990304 , SK, UA,  COPYRIGHT rapolymer DATE 19981103 19991026 19981119 19990218	2006 ACS on STN  2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  US 1997-857954 US 1998-34574 WO 1998-US5318	DATE 19970516 19980304 19980318
TI L4 TI PI L4 TI	ANSWER 39 OF 214 Accidental release  ANSWER 40 OF 214 Cooling agent comp PATENT NO.  WO 9910447 W: BY, CZ, HU  ANSWER 41 OF 214 Fixative vinyl ace PATENT NO.  US 5830439 US 5972329 WO 9851266 W: AL, AM, AT	CAPLUS prevent CAPLUS osition KIND A1 , MD, PL CAPLUS tate tet KIND A A A2 A3 , AU, AZ	COPYRIGHT ion  COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 19981119 19990218 , BA, BB,	2006 ACS on STN  APPLICATION NO. WO 1997-RU274 US  2006 ACS on STN  APPLICATION NO. US 1997-857954 US 1998-34574 WO 1998-US5318  BG, BR, BY, CA, CH, CN,	DATE 19970516 19980304 19980318 CU, CZ, DE,
TI L4 TI PI L4 TI	ANSWER 39 OF 214 Accidental release  ANSWER 40 OF 214 Cooling agent comp PATENT NO.  WO 9910447 W: BY, CZ, HU  ANSWER 41 OF 214 Fixative vinyl ace PATENT NO.  US 5830439 US 5972329 WO 9851266 W: AL, AM, AT DK, EE, ES	CAPLUS prevent  CAPLUS osition KIND A1 , MD, PL  CAPLUS tate tet KIND A A A2 A3 , AU, AZ , FI, GB	COPYRIGHT ion  COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 19981119 19990218 , BA, BB, GE, GH,	2006 ACS on STN  APPLICATION NO. WO 1997-RU274 US  2006 ACS on STN  APPLICATION NO. US 1997-857954 US 1998-34574 WO 1998-US5318  BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS,	DATE 19970516 19980304 19980318 CU, CZ, DE, JP, KE, KG,
TI L4 TI PI L4 TI	ANSWER 39 OF 214 Accidental release  ANSWER 40 OF 214 Cooling agent comp PATENT NO.  WO 9910447 W: BY, CZ, HU  ANSWER 41 OF 214 Fixative vinyl ace PATENT NO.  US 5830439 US 5972329 WO 9851266 W: AL, AM, AT DK, EE, ES KP, KR, KZ	CAPLUS prevent  CAPLUS osition KIND A1 , MD, PL  CAPLUS tate tet KIND A A A2 A3 , AU, AZ , FI, GB	COPYRIGHT ion  COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 19981119 19990218 , BA, BB, , GE, GH,	2006 ACS on STN  2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  US 1997-857954  US 1998-34574  WO 1998-US5318  BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK,	DATE 19970826  DATE 19970516 19980304 19980318  CU, CZ, DE, JP, KE, KG, MN, MW, MX,
TI L4 TI PI L4 TI	ANSWER 39 OF 214 Accidental release  ANSWER 40 OF 214 Cooling agent comp PATENT NO.  WO 9910447 W: BY, CZ, HU  ANSWER 41 OF 214 Fixative vinyl ace PATENT NO.  US 5830439 US 5972329 WO 9851266 W: AL, AM, AT DK, EE, ES KP, KR, KZ NO, NZ, PL	CAPLUS prevent  CAPLUS osition KIND A1 , MD, PL  CAPLUS tate tet KIND A A A2 A3 , AU, AZ , FI, GB , LC, LK , PT, RO	COPYRIGHT ion  COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 19981119 19990218 , BA, BB, , GE, GH, , LR, LS, , RU, SD,	2006 ACS on STN  2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  US 1997-857954  US 1998-34574  WO 1998-US5318  BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ,	DATE 19970826  DATE 19970516 19980304 19980318  CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT,
TI L4 TI PI L4 TI	ANSWER 39 OF 214 Accidental release  ANSWER 40 OF 214 Cooling agent comp PATENT NO.  WO 9910447 W: BY, CZ, HU  ANSWER 41 OF 214 Fixative vinyl ace PATENT NO.  US 5830439 US 5972329 WO 9851266 W: AL, AM, AT DK, EE, ES KP, KR, KZ NO, NZ, PL UA, UG, UZ	CAPLUS prevent  CAPLUS osition KIND A1 , MD, PL  CAPLUS tate tet KIND A A A2 A3 , AU, AZ , FI, GB , LC, LK , PT, RO , VN, YU	COPYRIGHT ion  COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 19981119 19990218 , BA, BB, GE, GH, LR, LS, RU, SD, ZW, AM,	2006 ACS on STN  2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  US 1997-857954  US 1998-34574  WO 1998-US5318  BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU,	DATE 19970826  DATE 19970516 19980304 19980318  CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM
TI L4 TI PI L4 TI	ANSWER 39 OF 214 Accidental release  ANSWER 40 OF 214 Cooling agent comp PATENT NO.  WO 9910447 W: BY, CZ, HU  ANSWER 41 OF 214 Fixative vinyl ace PATENT NO.  US 5830439 US 5972329 WO 9851266 W: AL, AM, AT DK, EE, ES KP, KR, KZ NO, NZ, PL UA, UG, UZ RW: GH, GM, KE	CAPLUS prevent  CAPLUS osition KIND A1 , MD, PL  CAPLUS tate tet KIND A A A2 A3 , AU, AZ , FI, GB , LC, LK , PT, RO , VN, YU , LS, MW	COPYRIGHT ion  COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 19981119 19990218 , BA, BB, GE, GH, LR, LS, RU, SD, ZW, AM, SD, SZ,	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274 US  2006 ACS on STN  APPLICATION NO.  US 1997-857954 US 1998-34574 WO 1998-US5318  BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU, UG, ZW, AT, BE, CH, DE,	DATE 19970826  DATE 19970516 19980304 19980318  CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI,
TI L4 TI PI L4 TI	ANSWER 39 OF 214 Accidental release  ANSWER 40 OF 214 Cooling agent comp PATENT NO.  WO 9910447 W: BY, CZ, HU  ANSWER 41 OF 214 Fixative vinyl ace PATENT NO.  US 5830439 US 5972329 WO 9851266 W: AL, AM, AT DK, EE, ES KP, KR, KZ NO, NZ, PL UA, UG, UZ RW: GH, GM, KE FR, GB, GR	CAPLUS prevent  CAPLUS osition KIND A1 , MD, PL  CAPLUS tate tet KIND A A A2 A3 , AU, AZ , FI, GB , LC, LK , PT, RO , VN, YU , LS, MW , IE, IT	COPYRIGHT ion  COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 19981119 19990218 , BA, BB, GE, GH, LR, LS, RU, SD, ZW, AM, SD, SZ, LU, MC,	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  US 1997-857954  US 1998-34574  WO 1998-US5318  BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU, UG, ZW, AT, BE, CH, DE, NL, PT, SE, BF, BJ, CF,	DATE 19970826  DATE 19970516 19980304 19980318  CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI,
TI L4 TI PI L4 TI	ANSWER 39 OF 214 Accidental release  ANSWER 40 OF 214 Cooling agent comp PATENT NO.  WO 9910447 W: BY, CZ, HU  ANSWER 41 OF 214 Fixative vinyl ace PATENT NO.  US 5830439 US 5972329 WO 9851266 W: AL, AM, AT DK, EE, ES KP, KR, KZ NO, NZ, PL UA, UG, UZ RW: GH, GM, KE FR, GB, GR GA, GN, ML	CAPLUS prevent  CAPLUS osition KIND A1 , MD, PL  CAPLUS tate tet KIND A A A2 A3 , AU, AZ , FI, GB , LC, LK , PT, RO , VN, YU , LS, MW , IE, IT , MR, NE	COPYRIGHT ion  COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 19981119 19990218 , BA, BB, GE, GH, LR, LS, RU, SD, ZW, AM, SD, SZ, LU, MC, SN, TD,	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  US 1997-857954  US 1998-34574  WO 1998-US5318  BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU, UG, ZW, AT, BE, CH, DE, NL, PT, SE, BF, BJ, CF, TG	DATE 19970826  DATE 19970516 19980304 19980318  CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI, CG, CI, CM,
TI L4 TI PI L4 TI	ANSWER 39 OF 214 Accidental release  ANSWER 40 OF 214 Cooling agent comp PATENT NO.  WO 9910447 W: BY, CZ, HU  ANSWER 41 OF 214 Fixative vinyl ace PATENT NO.  US 5830439 US 5972329 WO 9851266 W: AL, AM, AT DK, EE, ES KP, KR, KZ NO, NZ, PL UA, UG, UZ RW: GH, GM, KE FR, GB, GR	CAPLUS prevent  CAPLUS osition KIND A1 , MD, PL  CAPLUS tate tet KIND A A A2 A3 , AU, AZ , FI, GB , LC, LK , PT, RO , VN, YU , LS, MW , IE, IT , MR, NE	COPYRIGHT ion  COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 19981119 19990218 , BA, BB, GE, GH, LR, LS, RU, SD, ZW, AM, SD, SZ, LU, MC, SN, TD,	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  US 1997-857954  US 1998-34574  WO 1998-US5318  BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU, UG, ZW, AT, BE, CH, DE, NL, PT, SE, BF, BJ, CF,	DATE 19970826  DATE 19970516 19980304 19980318  CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI, CG, CI, CM,
TI L4 TI PI L7 PI	ANSWER 39 OF 214 Accidental release  ANSWER 40 OF 214 Cooling agent comp PATENT NO.  WO 9910447 W: BY, CZ, HU  ANSWER 41 OF 214 Fixative vinyl ace PATENT NO.  US 5830439 US 5972329 WO 9851266 W: AL, AM, AT DK, EE, ES KP, KR, KZ NO, NZ, PL UA, UG, UZ RW: GH, GM, KE FR, GB, GR GA, GN, ML AU 9868659	CAPLUS prevent CAPLUS osition KIND A1 , MD, PL CAPLUS tate tet KIND A A A2 A3 , AU, AZ , FI, GB , LC, LK , PT, RO , VN, YU , LS, MW , IE, IT , MR, NE A1	COPYRIGHT ion  COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 19981119 19990218 , BA, BB, , GE, GH, , LR, LS, , RU, SD, , ZW, AM, , SD, SZ, , LU, MC, , SN, TD, 19981208	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  LUS 1997-857954  US 1998-34574  WO 1998-US5318  BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, IT, LU, LV, MD, MG, MK, ISE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU, UG, ZW, AT, BE, CH, DE, INL, PT, SE, BF, BJ, CF, TG  AU 1998-68659	DATE 19970826  DATE 19970516 19980304 19980318  CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI, CG, CI, CM,
TI L4 TI PI L4 TI	ANSWER 39 OF 214 Accidental release  ANSWER 40 OF 214 Cooling agent comp PATENT NO.  WO 9910447 W: BY, CZ, HU  ANSWER 41 OF 214 Fixative vinyl ace PATENT NO.  US 5830439 US 5972329 WO 9851266 W: AL, AM, AT DK, EE, ES KP, KR, KZ NO, NZ, PL UA, UG, UZ RW: GH, GM, KE FR, GB, GR GA, GN, ML AU 9868659  ANSWER 42 OF 214	CAPLUS prevent CAPLUS osition KIND A1 , MD, PL CAPLUS tate tet KIND A A A2 A3 , AU, AZ , FI, GB , LC, LK , PT, RO , VN, YU , LS, MW , IE, IT , MR, NE A1 CAPLUS	COPYRIGHT ion  COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 19981119 19990218 , BA, BB, , GE, GH, , LR, LS, , RU, SD, , ZW, AM, , SD, SZ, , LU, MC, , SN, TD, 19981208  COPYRIGHT	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.	DATE 19970826  DATE 19970516 19980304 19980318  CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI, CG, CI, CM, 19980318
TI L4 TI PI L7 PI	ANSWER 39 OF 214 Accidental release  ANSWER 40 OF 214 Cooling agent comp PATENT NO.  WO 9910447 W: BY, CZ, HU  ANSWER 41 OF 214 Fixative vinyl ace PATENT NO.  US 5830439 US 5972329 WO 9851266 W: AL, AM, AT DK, EE, ES KP, KR, KZ NO, NZ, PL UA, UG, UZ RW: GH, GM, KE FR, GB, GR GA, GN, ML AU 9868659  ANSWER 42 OF 214 Selective etching	CAPLUS prevent CAPLUS osition KIND A1 , MD, PL CAPLUS tate tet KIND A A A2 A3 , AU, AZ , FI, GB , LC, LK , PT, RO , VN, YU , LS, MW , IE, IT , MR, NE CAPLUS of diele	COPYRIGHT ion  COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 19981119 19990218 , BA, BB, , GE, GH, , LR, LS, , RU, SD, , ZW, AM, , SD, SZ, , LU, MC, , SN, TD, 19981208  COPYRIGHT ctrics us	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  APPLICATION NO.  US 1997-857954  US 1998-34574  WO 1998-US5318  BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, IT, LU, LV, MD, MG, MK, ISE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU, UG, ZW, AT, BE, CH, DE, INL, PT, SE, BF, BJ, CF, TG  AU 1998-68659  2006 ACS on STN ing fluorohydrocarbon gas	DATE 19970826  DATE 19970516 19980304 19980318  CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI, CG, CI, CM, 19980318
TI L4 TI PI L4 TI	ANSWER 39 OF 214 Accidental release  ANSWER 40 OF 214 Cooling agent comp PATENT NO.  WO 9910447 W: BY, CZ, HU  ANSWER 41 OF 214 Fixative vinyl ace PATENT NO.  US 5830439 US 5972329 WO 9851266 W: AL, AM, AT DK, EE, ES KP, KR, KZ NO, NZ, PL UA, UG, UZ RW: GH, GM, KE FR, GB, GR GA, GN, ML AU 9868659  ANSWER 42 OF 214 Selective etching NH3-generating gas	CAPLUS prevent CAPLUS osition KIND A1 , MD, PL CAPLUS tate tet KIND A A A2 A3 , AU, AZ , FI, GB , LC, LK , PT, RO , VN, YU , LS, MW , IE, IT , MR, NE CAPLUS of diele , and ca	COPYRIGHT ion  COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 19981119 19990218 , BA, BB, GE, GH, LR, LS, RU, SD, ZW, AM, SD, SZ, LU, MC, SN, TD, 19981208  COPYRIGHT ctrics us rbon-oxyg	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.	DATE 19970826  DATE 19970516 19980304 19980318  CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI, CG, CI, CM, 19980318
TI L4 TI PI L4 TI	ANSWER 39 OF 214 Accidental release  ANSWER 40 OF 214 Cooling agent comp PATENT NO.  WO 9910447 W: BY, CZ, HU  ANSWER 41 OF 214 Fixative vinyl ace PATENT NO.  US 5830439 US 5972329 WO 9851266 W: AL, AM, AT DK, EE, ES KP, KR, KZ NO, NZ, PL UA, UG, UG, UG, UG, UG, UG, UG, UG, UG, UG	CAPLUS prevent CAPLUS osition KIND A1 , MD, PL CAPLUS tate tet KIND A A A2 A3 , AU, AZ , FI, GB , LC, LK , PT, RO , VN, YU , LS, MW , IE, IT , MR, NE CAPLUS of diele , and ca KIND	COPYRIGHT ion  COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 19981119 19990218 , BA, BB, GE, GH, LR, LS, RU, SD, ZW, AM, SD, SZ, LU, MC, SN, TD, 19981208  COPYRIGHT ctrics us rbon-oxyg DATE	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  APPLICATION NO.  US 1997-857954  US 1998-34574  WO 1998-US5318  BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, IT, LU, LV, MD, MG, MK, ISE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU, UG, ZW, AT, BE, CH, DE, INL, PT, SE, BF, BJ, CF, TG  AU 1998-68659  2006 ACS on STN ing fluorohydrocarbon gas	DATE 19970826  DATE 19970516 19980304 19980318  CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI, CG, CI, CM, 19980318

```
A 19981201 US 1996-639388
A2 19980213 JP 1997-112887
A2 19980224 JP 1997-147995
A2 19971217 EP 1997-304035
    JP 10056001
                                                            19970605
                     A2 19971217
A3 19990825
                                                            19970610
    EP 813233
    EP 813233
       R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
           IE, FI
    ANSWER 43 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Spray formulation for testing of smoke detectors
ΤI
    PATENT NO. KIND DATE APPLICATION NO. DATE
                            _____
                                       _____
                                                            -----
                      ----
    _____
                            19980728 US 1996-713058
                                                            19960912
                      Α
    US 5785891
ΡI
    ANSWER 44 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Coolant agent composition
TI
                                      APPLICATION NO.
                                                           DATE
    PATENT NO. KIND
                            DATE
                      ----
                                      ------
                                                            -----
                            _____
    -----
                            19971210 RU 1996-104188
                                                            19960301
PΙ
    RU 2098445
                      C1
    ANSWER 45 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Method and apparatus for fluorine-assisted stripping and residue removal
    PATENT NO. KIND DATE APPLICATION NO. DATE
                  A1 19980402 WO 1997-US16886 19970924
    WO 9814036
PΙ
       W: JP, KR, US
       RW: AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE
                      A1 19981007 EP 1997-944360
                                                           19970924
       R: DE, FR, GB, IT, NL
                            20000208 JP 1998-515793
20000704 US 1997-936548
                                                           19970924
    JP 2000501573 T2
                                                           19970924
    US 6082374
                       Α
L4
    ANSWER 46 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Palladium-assisted electrodehalogenation of 1,1,2-trichloro-1,2,2-
    trifluoroethane on lead cathodes combined with hydrogen diffusion anodes
    ANSWER 47 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Process for the reduction of chlorofluorocarbons and production of
ΤI
    derivatives thereof in an electrolytic cell, cell for carrying out said
    reduction and process for removing the byproducts formed within the cell
    PATENT NO. KIND DATE APPLICATION NO. DATE
                                                           -----
                            _____
                                      -----
    -----
                      ----
                     A1 19970710 WO 1996-ES248
                                                           19961226
PΙ
    WO 9724162
        W: CA, US
        RW: AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE
    ES 2103207 A1 19970816 ES 1995-2533
                                                            19951228
    ES 2103207
                      B1
                            19980401
    EP 819448
EP 819448
                            19980121 EP 1996-941667
                                                           19961226
                      A1
                           20000517
                      B1
       R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
           IE, FI
                                       AT 1996-941667
    AT 192939
                       E
                            20000615
                                                            19961226
                      T3
                            20001016
                                       ES 1996-941667
                                                           19961226
    ES 2148819
                                     US 1997-913389
                            20000530
                                                           19971104
    US 6068756
                      A
    ANSWER 48 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Large scale fluorine doped textured transparent conducting SnO2 films
TI
    deposited by atmospheric pressure chemical vapor deposition
    ANSWER 49 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Smell-added refrigerant compositions for leakage detection
TΤ
    PATENT NO. KIND DATE APPLICATION NO.
                                                           DATE
                      ----
                            -----
    -----
                      A2
                            19960924 JP 1995-51647
                                                           19950313
PΙ
    JP 08245952
    ANSWER 50 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Evaluation of critical parameters of halohydrocarbons and its quality
TI
```

19960429

19970430

Α

A2

US 5843847

codes

JP 10041274

```
ANSWER 51 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
TI
    Single-phase aerosol antiperspirant composition
    PATENT NO. KIND DATE APPLICATION NO. DATE
    WO 9618378 A2 19960620 WO 1995-US16286 19951214
PΙ
        W: AU, BR, CA, CH, CN, DE, ES, FI, GB, JP, KR, NO, NZ, PL, PT, RO,
           RU, SE, UA, VN
        RW: AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE
                            19960703 AU 1996-49618
                                                           19951214
    AU 9649618
                       A1
    ANSWER 52 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Ab initio studies of fluorinated ethanes: electronic and energetic
ΤI
    properties and reactions with hydroxyl radicals
    ANSWER 53 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Dehydrofluorination, fluorination, and decomposition of fluorohydrocarbons
TT
    with phosphate catalysts
                KIND
                            DATE APPLICATION NO.
    PATENT NO.
                     ----
                            _____
                                       ______
    ------
    JP 08104656
                      A2 19960423 JP 1994-243024
                                                            19941006
ΡI
    ANSWER 54 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Preparation of a substrate having a fluoride-doped conductive coating
TΤ
    PATENT NO. KIND DATE APPLICATION NO. DATE
    US 5496583 A 19960305 US 1994-297400 19940829
WO 9606958 A1 19960307 WO 1995-US10854 19950828
ΡI
        W: AM, AT, AU, BB, BG, BR, BY, CA, CH, CN, CZ, DE, DK, EE, ES, FI,
           GB, GE, HU, IS, JP, KE, KG, KP, KR, KZ, LK, LR, LT, LU, LV, MD,
           MG, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, TJ,
           TM, TT
        RW: KE, MW, SD, SZ, UG, AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT,
           LU, MC, NL, PT, SE, BF, BJ, CF, CG, CI, CM, GA, GN, ML, MR, NE,
           SN, TD, TG
                                       AU 1995-34959
                       A1
                            19960322
                                                            19950828
    AU 9534959
    ANSWER 55 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Four-component aerosol compositions
TI
                                      APPLICATION NO. DATE
    PATENT NO. KIND DATE
                      A1 19960111 WO 1994-US7426 19940630
                                                           -----
                      ----
    ------
    WO 9600564
PΙ
        W: AM, AT, AU, BB, BG, BR, BY, CA, CH, CN, CZ, DE, DK, ES, FI, GB,
           GE, HU, JP, KE, KG, KP, KR, KZ, LK, LU, LV, MD, MG, MN, MW, NL,
           NO, NZ, PL, PT, RO, RU, SD, SE, SI, SK, TJ, TT, UA, UZ, VN
        RW: AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE,
           BF, BJ, CF, CG, CI, CM, GA, GN, ML, MR, NE, SN, TD, TG
                      A1
                            19960125
                                     AU 1994-73206
    AU 9473206
    ANSWER 56 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
TI
    Aerosol detergent compositions with low toxicity for cleaning automotive
    brakes
                            DATE APPLICATION NO.
    PATENT NO.
                     KIND
                                                           DATE
                     ----
                                      JP 1994-126602
ΡI
    JP 07331290
                      A2
                            19951219
                                                           19940608
    ANSWER 57 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
ΤI
    Infrared photochemical properties of sensitized SO2-O2 mixtures
    ANSWER 58 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
T.4
TI
    Energy-saving binary refrigerant mixtures without ozone layer depletion
    effect
    PATENT NO.
                     KIND DATE
                                    APPLICATION NO.
                           19950125
                                      CN 1993-109083
PΙ
    CN 1097792
                      A
                                                           19930721
    ANSWER 59 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
ΤI
    Hair aerosol compositions containing polymers and dimethylether
    PATENT NO. KIND DATE APPLICATION NO. DATE
                     ----
                                       ------
```

L4

PI	EP 663203	A1		EP 1994-402874	19941213
	EP 663203	B1			
	R: AT, BE, C	H, DE, E		IT, LI, NL, SE	
	FR 2715064	A1	19950721		19940114
	FR 2715064	B1	19960209		
	AT 205698	E	20011015	AT 1994-402874	19941213
	CA 2138481	AA	19950715	CA 1994-2138481	19941219
	CA 2138481	С	20020625		
	HU 71747	A2	19960129	HU 1994-3827	19941229
	HU 218577	В	20001028		
	PL 177758	B1	20000131	PL 1994-306585	19941229
	KR 166391	B1	19990115		19941230
	BR 9500140	A	19951017		19950110
	CN 1113141	A	19951213		19950113
	CN 1113141 CN 1070358	В		CN 1999 101249	13330113
		A2	19960213	JP 1995-4323	19950113
	JP 08040847			UP 1995-4323	19950113
	JP 2834417	B2	19981209	DII 100E 100766	10050113
	RU 2124351	C1	19990110		19950113
	US 6113923	Α	20000905	US 1995-372395 ·	19950113
L4	ANSWER 60 OF 214	CAPLUS	COPYRIGHT	2006 ACS ON STN	
TI				cture of rigid foams	
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
		<del>-</del>			
ΡI	US 5391584	Α	19950221 19921230	US 1993-27533	19930308
	ZA 9201888	Α			19920313
	ZA 9201895	A	19921230		19920313
	CN 1067435	A			19920327
	KR 227876	B1	19991101	KR 1992-5064	19920327
	US 5238970	Α	19930824		19921110
	US 5240965	Α	19930831	US 1992-974352	19921110
	US 5356556	A	19941018	US 1993-61007	19930514
	US 5368769	Α	19941129	US 1993-67789	19930527
	CN 1133854	A	19961023	CN 1995-119832	19951114
	CN 1048995	В	20000202		
L4	ANSWER 61 OF 214				
$\mathtt{TI}$	Refrigerating app	aratus u	sing difluc	proethane-based refrige	rating agents
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	JP 07027431	A2	19950127	JP 1993-176804	19930716
L4	ANSWER 62 OF 214				
TI	Post treatment of	a coate	d substrate	e with a gas containing	excited halogen
	to remove residue	s			
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	WO 9502472	A1	19950126	WO 1994-US7751	19940712
	W: JP, KR, U				
			K. ES. FR.	GB, GR, IE, IT, LU, MC	NL, PT, SE
				EP 1994-922123	
	R: DE				
		Т2	19970318	JP 1994-504652	19940712
	01 02002010				
L4	ANSWER 63 OF 214	CAPLUS	COPYRIGHT	2006 ACS on STN	
TI				ive, soluble pyrrole-3-	carboxvlic acid
	ester polymers			F7	
	בא יידאיי או	KTND	DATE	APPLICATION NO.	DATE
ΡI	JP 06206986	Δ2	19940726	JP 1992-180695	19920708
	JP 3024867	B2	20000327		
	21 3021007				
L4	ANSWER 64 OF 214	CAPLUS	COPYRIGHT	2006 ACS on STN	
TI				and their manufacture	
				APPLICATION NO.	DATE
ΡI				CN 1993-119728	
	· · · · · · · · · · · · · · · · · · ·				
L4	ANSWER 65 OF 214	CAPLUS	COPYRIGHT	2006 ACS on STN	
	00 01 211		<b></b>		

TI	Substance separat gas-mixture flows	ion by t through	he action of capillaries	a pulsed IR laser radi	ation on
L4 TI	DATENT NO	ermoplas KIND	tic polyeste:	r foams by extrusion	DATE
PI	JP 06145404 JP 2801483	A2 B2	19940524 19980921	JP 1992-317764	19921102
L4 TI	dimensional stabi	tem for p lity	preparation (	006 ACS on STN of rigid polyurethane for APPLICATION NO.	
ΡI				DE 1993-4303887	
					19930210
L4 TI	ANSWER 68 OF 214 Gaseous doping of PATENT NO.	tungste	n oxide DATE	APPLICATION NO.	DATE
ΡI	US 5324537	A	19940628	US 1993-86796	19930706
L4 TI	ANSWER 69 OF 214 Hydrofluorocarbon static magnetron			006 ACS on STN licon dioxide etch in a	n axisymmetric
L4 TI	ANSWER 70 OF 214 Manufacture of ser PATENT NO.	miconduc	tor devices	APPLICATION NO.	DATE
ΡI	JP 06029263	A2	19940204	JP 1992-179993	19920707
L4 TI	ANSWER 71 OF 214 Manufacture of ser PATENT NO.	miconduc KIND	tor device by DATE	y plasma etching APPLICATION NO.	DATE
ΡI				JP 1992-174114	
L4 TI	ANSWER 72 OF 214 Manufacture of flo PATENT NO.	exible p	olyurethane :	006 ACS on STN foams having low densit APPLICATION NO.	DATE
PI	JP 05320300	A2	19931203	JP 1992-134451	
L4 TI	ANSWER 73 OF 214 Antiperspirant ae	rosol co	mposition wit	006 ACS on STN th high solid content APPLICATION NO.	DATE
ΡΙ	CA 2093781 AU 9336751 AU 671104 EP 570085	AA A1 B2 A2	19931017 19931021 19960815 19931118	CA 1993-2093781 AU 1993-36751 EP 1993-250104	19930408
	EP 570085 R: AT, BE, CI BR 9301551 ZA 9302658 US 5605682 US 5605682	H, DE, D A A A	K, ES, FR, GF 19931019 19941015 19970225	B, IE, IT, LI, LU, NL, 8 BR 1993-1551 ZA 1993-2658 US 1994-238195	SE 19930415 19930415 19940504
L4 TI		gas-chr	omatographic	006 ACS on STN retention parameters for physicochemical charact	
L4 TI	ANSWER 75 OF 214 Stabilized polyoxy PATENT NO.	yalkylen KIND	e glycols DATE	APPLICATION NO.	
PI	WO 9217563	A1	19921015	WO 1992-US2148	

```
W: AU, BB, BG, BR, CA, CS, FI, HU, JP, KP, KR, LK, MG, MN, MW, NO,
      PL, RO, RU, SD
   RW: AT, BE, BF, BJ, CF, CG, CH, CI, CM, DE, DK, ES, FR, GA, GB, GN,
      GR, IT, LU, MC, ML, MR, NL, SE, SN, TD, TG
                     19921102
                             AU 1992-17754
                                                19920318
                A1
AU 9217754
ANSWER 76 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Working fluids
                             APPLICATION NO. DATE
               KIND
                     DATE
PATENT NO.
              ---<del>-</del>
                     -----
                              -----
                                                 -----
______
                     19930514 JP 1991-281038
                                                 19911028
                A2
JP 05117646
ANSWER 77 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Working fluids
                             APPLICATION NO. DATE
PATENT NO.
               KIND
                     DATE
               ----
                                                 -----
-----
                     _____
                              ______
                             JP 1991-171032
JP 05017743
                A2
                     19930126
                                                 19910711
ANSWER 78 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Working fluids
                             APPLICATION NO. DATE
               KIND
PATENT NO.
                     DATE
               ----
                                                ------
-----
                              ______
                             JP 1991-171035
                                                 19910711
               A2
                     19930126
JP 05017746
ANSWER 79 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Working fluids
                             APPLICATION NO. DATE
PATENT NO.
               KIND
                     DATE
                              _____
                                                _____
_____
               ----
                             JP 1991-172368
                                                19910712
JP 05017748
               A2
                     19930126
ANSWER 80 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Working fluids
                             APPLICATION NO. DATE
PATENT NO.
               KIND DATE
-----
              ----
                     -----
                              _____
                                                -----
JP 05017751
               A2
                     19930126
                              JP 1991-172371
                                                 19910712
ANSWER 81 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Working fluids
                             APPLICATION NO.
PATENT NO.
               KIND DATE
                                                DATE
                              -----
              ____
                             JP 1991-172375 19910712
JP 05017755
               A2 19930126
ANSWER 82 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Working fluids
                             APPLICATION NO.
PATENT NO.
              KIND DATE
                                                DATE
              _ - - -
                     _____
                              -----
                              JP 1991-172378
JP 05017758
               A2 19930126
                                                19910712
ANSWER 83 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Prediction of refrigerant thermodynamic properties by equations of state:
vapor liquid equilibrium behavior of binary mixtures
ANSWER 84 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Crosslinked polyolefin foaming compositions
PATENT NO. KIND DATE APPLICATION NO.
                                               DATE
                     -----
_____
               ----
                              -----
                                                _____
               A2 19920602
                             JP 1990-283331
JP 04159339
                                                19901023
ANSWER 85 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Performance-oriented packaging standards; changes to classification,
hazard communication, packaging and handling requirements based on UN
standards and agency initiative
ANSWER 86 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
```

Manufacture of expandable vinylidene chloride resin particles

-----

----

PATENT NO. KIND DATE APPLICATION NO. DATE

A2 19911002 JP 1990-17733

\_\_\_\_\_\_

19900130

L4

TI

PΙ

L4

ΤI

ΡI

L4

PΙ

L4

PΤ

L4

ΤI

PΙ

L4

TI

PΙ

L4

TΙ

PΙ

T.4

ΤI

L4

TI

PΙ

L4

TI

L4

ΤI

ΡI

JP 03223346

L4 TI	ANSWER 87 OF 214 Multivariate mode haloalkanes with	ling of	the rate c	onstant of the gas-phase	e reaction of
L4 TI	ANSWER 88 OF 214 Vinylidene chlori refrigerators			2006 ACS on STN ldings for thermal insul	lators of
	PATENT NO.	KIND		APPLICATION NO.	DATE
PI				JP 1990-17732	
L4	ANSWER 89 OF 214				
TI	Preparation of the PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 03137139		19910611	JP 1989-276342	19891023
L4 TI	ANSWER 90 OF 214 Working fluids	CAPLUS	COPYRIGHT	2006 ACS on STN	
	PATENT NO.	KIND		APPLICATION NO.	DATE
ΡI	JP 03220285	A2		JP 1990-242131	
	JP 2532736	B2	19960911		
L4 TI		ering sa	afety data	2006 ACS on STN of the material pair R15 onventional refrigerants	
L4 TI	ANSWER 92 OF 214 Working fluids	CAPLUS	COPYRIGHT	2006 ACS on STN	•
11	PATENT NO.			APPLICATION NO.	DATE
ΡI	JP 03170583	A2	19910724	JP 1989-311149	19891130
	JP 03170583 US 5433879	A	19950718	US 1993-125146	19930923
L4 TI	ANSWER 93 OF 214 Working fluids	CAPLUS	COPYRIGHT	2006 ACS on STN	
	PATENT NO.			APPLICATION NO.	DATE
PI	JP 03168271	A2	19910722	JP 1989-309652	19891129
L4 TI	ANSWER 94 OF 214 Working fluids	CAPLUS	COPYRIGHT	2006 ACS on STN	
				APPLICATION NO.	
PI	JP 03170593	A2		JP 1989-311164	
L4 TI	ANSWER 95 OF 214 Working fluids	CAPLUS	COPYRIGHT	2006 ACS on STN	
	PATENT NO.	KIND		APPLICATION NO.	
ΡI	JP 03170592	A2	19910724	JP 1989-311163 US 1993-125146	19891130
L4	ANSWER 96 OF 214	CAPLUS	COPYRIGHT	2006 ACS on STN	

a

L4 TI	ANSWER 96 OF 214 Working fluids PATENT NO.	CAPLUS	COPYRIGHT	2006 ACS on STN APPLICATION NO.	DATE
PI	JP 03170590 JP 2580349	A2 B2	19910724 19970212	JP 1989-311160	19891130
	US 5304319	A	19940419	US 1992-83 <b>9700</b>	19920224
L4 TI	ANSWER 97 OF 214 Working fluids	CAPLUS	COPYRIGHT	2006 ACS on STN	
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 03170589	A2	19910724	JP 1989-311159	19891130
L4	ANSWER 98 OF 214	CAPLUS	COPYRIGHT	2006 ACS on STN	

TI	Working fluids PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 03168261	A2	19910722	JP 1989-309640	
L4 TI	ANSWER 99 OF 214 Working fluids	CAPLUS	COPYRIGHT 20	006 ACS on STN	
**	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI				JP 1989-309669	19891129
L4 TI	ANSWER 100 OF 214 Working fluids				
	PATENT NO.			APPLICATION NO.	
PI	JP 03168290	A2 .	19910722	JP 1989-309672	19891129
L4 TI				2006 ACS on STN foaming solutions witho	out ozone
	layer depletion PATENT NO.	KIND		APPLICATION NO.	
PI		A2	19910626	JP 1989-289729	
L4	ANSWER 102 OF 214				
TI	Apparatus for manu	KIND	DATE	rethane solutions APPLICATION NO.	DATE
PI	JP 03150108 JP 2706991	A2	19910626	JP 1989-289728	19891106
L4 TI	ANSWER 103 OF 214 Semiempirical calc silicon inner core	culation	of ESCA shif	ts in oxygen, nitrogen,	fluorine and
L4	ANSWER 104 OF 214				
TI	Aerosol composition PATENT NO.	KIND	DATE	APPLICATION NO.	
PI	EP 423695	A2	19910424	EP 1990-119769	19901015
	EP 423695	7.2	10011002		17701013
		_ A3	19911002	EP 1990-119769	19901013
	R: AT, BE, C	H, DE, DK	, ES, FR, GB	B, GR, IT, LI, NL, SE	
	R: AT, BE, CF AU 9064634	H, DE, DK A1	I, ES, FR, GB 19910426	3, GR, IT, LI, NL, SE AU 1990-64634	19901015
	R: AT, BE, CF AU 9064634	H, DE, DK A1	I, ES, FR, GB 19910426	3, GR, IT, LI, NL, SE AU 1990-64634	19901015
	R: AT, BE, CF AU 9064634	H, DE, DK A1	I, ES, FR, GB 19910426	3, GR, IT, LI, NL, SE AU 1990-64634	19901015
	R: AT, BE, CH AU 9064634 NO 9004492 CA 2027952 JP 03255023	H, DE, DK A1 A AA A2	<pre>E, ES, FR, GB    19910426    19910422    19910420    19911113</pre>	B, GR, IT, LI, NL, SE	19901015 19901017 19901018 19901019
L4	R: AT, BE, CH AU 9064634 NO 9004492 CA 2027952 JP 03255023 US 5378451 ANSWER 105 OF 214	H, DE, DK A1 A AA A2 A CAPLUS	C, ES, FR, GB 19910426 19910422 19910420 19911113 19950103	3, GR, IT, LI, NL, SE AU 1990-64634 NO 1990-4492 CA 1990-2027952 JP 1990-281690 US 1993-126747	19901015 19901017 19901018 19901019
L4 TI	R: AT, BE, CF AU 9064634 NO 9004492 CA 2027952 JP 03255023 US 5378451 ANSWER 105 OF 214 Etching of semicor	H, DE, DK A1 A AA A2 A CAPLUS	C, ES, FR, GB 19910426 19910422 19910420 19911113 19950103 COPYRIGHT 2	3, GR, IT, LI, NL, SE AU 1990-64634 NO 1990-4492 CA 1990-2027952 JP 1990-281690 US 1993-126747	19901015 19901017 19901018 19901019 19930927
	R: AT, BE, CH AU 9064634 NO 9004492 CA 2027952 JP 03255023 US 5378451 ANSWER 105 OF 214 Etching of semicon PATENT NO.	H, DE, DK A1 A AA A2 A CAPLUS nductor w	C, ES, FR, GB 19910426 19910422 19910420 19911113 19950103 COPYRIGHT 2	3, GR, IT, LI, NL, SE AU 1990-64634 NO 1990-4492 CA 1990-2027952 JP 1990-281690 US 1993-126747  2006 ACS on STN and hydrocarbon gas APPLICATION NO.	19901015 19901017 19901018 19901019 19930927
TI	R: AT, BE, CH AU 9064634 NO 9004492 CA 2027952 JP 03255023 US 5378451 ANSWER 105 OF 214 Etching of semicon PATENT NO.	H, DE, DK A1 A AA A2 A CAPLUS nductor w	C, ES, FR, GB 19910426 19910422 19910420 19911113 19950103 COPYRIGHT 2	3, GR, IT, LI, NL, SE AU 1990-64634 NO 1990-4492 CA 1990-2027952 JP 1990-281690 US 1993-126747  2006 ACS on STN and hydrocarbon gas APPLICATION NO.	19901015 19901017 19901018 19901019 19930927
	R: AT, BE, CH AU 9064634 NO 9004492 CA 2027952 JP 03255023 US 5378451 ANSWER 105 OF 214 Etching of semicon PATENT NO.	H, DE, DK A1 A AA A2 A CAPLUS nductor w	C, ES, FR, GB 19910426 19910422 19910420 19911113 19950103 COPYRIGHT 2	3, GR, IT, LI, NL, SE AU 1990-64634 NO 1990-4492 CA 1990-2027952 JP 1990-281690 US 1993-126747  2006 ACS on STN and hydrocarbon gas APPLICATION NO.	19901015 19901017 19901018 19901019 19930927
TI	R: AT, BE, CR AU 9064634 NO 9004492 CA 2027952 JP 03255023 US 5378451  ANSWER 105 OF 214 Etching of semicor PATENT NO.  JP 03083335 EP 497023 R: DE, FR, GR	H, DE, DK A1 A AA A2 A CAPLUS nductor w KIND A2 A1	C, ES, FR, GB 19910426 19910420 19910420 19911113 19950103 COPYRIGHT 2 ith fluoride DATE  19910409 19920805	8, GR, IT, LI, NL, SE AU 1990-64634 NO 1990-4492 CA 1990-2027952 JP 1990-281690 US 1993-126747  2006 ACS on STN and hydrocarbon gas APPLICATION NO.  JP 1989-218530 EP 1991-300793	19901015 19901017 19901018 19901019 19930927 DATE  19890828 19910131
TI	R: AT, BE, CH AU 9064634 NO 9004492 CA 2027952 JP 03255023 US 5378451 ANSWER 105 OF 214 Etching of semicor PATENT NO. 	H, DE, DK A1 A AA A2 A CAPLUS nductor w KIND A2 A1	C, ES, FR, GB 19910426 19910420 19910420 19911113 19950103 COPYRIGHT 2 ith fluoride DATE  19910409 19920805	3, GR, IT, LI, NL, SE AU 1990-64634 NO 1990-4492 CA 1990-2027952 JP 1990-281690 US 1993-126747  2006 ACS on STN and hydrocarbon gas APPLICATION NO.	19901015 19901017 19901018 19901019 19930927 DATE  19890828 19910131
TI	R: AT, BE, CR AU 9064634 NO 9004492 CA 2027952 JP 03255023 US 5378451  ANSWER 105 OF 214 Etching of semicor PATENT NO.  JP 03083335 EP 497023 R: DE, FR, GR US 5110408  ANSWER 106 OF 214 Preparation of rig PATENT NO.	H, DE, DK A1 A AA A2 A CAPLUS nductor w KIND A2 A1 B A CAPLUS gid polyu KIND	C, ES, FR, GB 19910426 19910422 19910420 19911113 19950103  COPYRIGHT 2 ith fluoride DATE 19910409 19920805  COPYRIGHT 2 COPYRIGHT 2 Arethane foam DATE	8, GR, IT, LI, NL, SE AU 1990-64634 NO 1990-4492 CA 1990-2027952 JP 1990-281690 US 1993-126747  2006 ACS on STN and hydrocarbon gas APPLICATION NO.  JP 1989-218530 EP 1991-300793  US 1991-658254  2006 ACS on STN as with low thermal cond APPLICATION NO.	19901015 19901017 19901018 19901019 19930927 DATE
TI PI L4 TI	R: AT, BE, CR AU 9064634 NO 9004492 CA 2027952 JP 03255023 US 5378451  ANSWER 105 OF 214 Etching of semicor PATENT NO.  JP 03083335 EP 497023 R: DE, FR, GR US 5110408  ANSWER 106 OF 214 Preparation of rig PATENT NO.	H, DE, DK A1 A AA A2 A CAPLUS nductor w KIND A2 A1 B A CAPLUS gid polyu KIND	C, ES, FR, GB 19910426 19910422 19910420 19911113 19950103  COPYRIGHT 2 ith fluoride DATE 19910409 19920805  COPYRIGHT 2 COPYRIGHT 2 Arethane foam DATE	8, GR, IT, LI, NL, SE AU 1990-64634 NO 1990-4492 CA 1990-2027952 JP 1990-281690 US 1993-126747  2006 ACS on STN and hydrocarbon gas APPLICATION NO.  JP 1989-218530 EP 1991-300793  US 1991-658254  2006 ACS on STN as with low thermal cond APPLICATION NO.	19901015 19901017 19901018 19901019 19930927 DATE
TI PI L4	R: AT, BE, CR AU 9064634 NO 9004492 CA 2027952 JP 03255023 US 5378451  ANSWER 105 OF 214 Etching of semicor PATENT NO.  JP 03083335 EP 497023 R: DE, FR, GR US 5110408  ANSWER 106 OF 214 Preparation of rig PATENT NO.	H, DE, DK A1 A AA A2 A CAPLUS nductor w KIND A2 A1 B A CAPLUS gid polyu KIND	C, ES, FR, GB 19910426 19910422 19910420 19911113 19950103  COPYRIGHT 2 ith fluoride DATE 19910409 19920805  COPYRIGHT 2 COPYRIGHT 2 Arethane foam DATE	8, GR, IT, LI, NL, SE AU 1990-64634 NO 1990-4492 CA 1990-2027952 JP 1990-281690 US 1993-126747  2006 ACS on STN and hydrocarbon gas APPLICATION NO.  JP 1989-218530 EP 1991-300793  US 1991-658254  2006 ACS on STN as with low thermal cond APPLICATION NO.	19901015 19901017 19901018 19901019 19930927 DATE
TI PI L4 TI	R: AT, BE, CF AU 9064634 NO 9004492 CA 2027952 JP 03255023 US 5378451  ANSWER 105 OF 214 Etching of semicor PATENT NO	H, DE, DK A1 A AA A2 A CAPLUS END A2 A1 B A CAPLUS GID CAPLUS GID CAPLUS A1 B A CAPLUS A1 B A CAPLUS A1 B A CAPLUS A1 B A A A A A A A A A A A A A A A A A	C, ES, FR, GB 19910426 19910420 19910420 19911113 19950103  COPYRIGHT 2 19910409 19920805  COPYRIGHT 2 rethane foam DATE 19910410 19910904	8, GR, IT, LI, NL, SE AU 1990-64634 NO 1990-4492 CA 1990-2027952 JP 1990-281690 US 1993-126747  2006 ACS on STN and hydrocarbon gas APPLICATION NO.  JP 1989-218530 EP 1991-300793  US 1991-658254  2006 ACS on STN as with low thermal cond	19901015 19901017 19901018 19901019 19930927 DATE
TI PI L4 TI	R: AT, BE, CR AU 9064634 NO 9004492 CA 2027952 JP 03255023 US 5378451  ANSWER 105 OF 214 Etching of semicor PATENT NO.  JP 03083335 EP 497023 R: DE, FR, GR US 5110408  ANSWER 106 OF 214 Preparation of rig PATENT NO.	H, DE, DK A1 A AA A2 A CAPLUS IND A2 A1 B A CAPLUS GID POLYU KIND A2 A1 B A CAPLUS B B B B A CAPLUS B B B B B B B B B B B B B B B B B B B	C, ES, FR, GB 19910426 19910420 19911113 19950103  COPYRIGHT 2 1910409 19920805  COPYRIGHT 2 19910409 19920805  COPYRIGHT 2 19910400 19910904 19910904 19960110	8, GR, IT, LI, NL, SE AU 1990-64634 NO 1990-4492 CA 1990-2027952 JP 1990-281690 US 1993-126747  2006 ACS on STN and hydrocarbon gas APPLICATION NO.  JP 1989-218530 EP 1991-300793  US 1991-658254  2006 ACS on STN as with low thermal cond APPLICATION NO.	19901015 19901017 19901018 19901019 19930927 DATE
TI PI L4 TI	R: AT, BE, CH AU 9064634 NO 9004492 CA 2027952 JP 03255023 US 5378451  ANSWER 105 OF 214 Etching of semicon PATENT NO.	H, DE, DK A1 A AA A2 A CAPLUS Aductor w KIND A2 A1 B A CAPLUS Gid polyu KIND A2 A3 B1 B2 H, DE, DK	C, ES, FR, GB 19910426 19910420 19911113 19950103  COPYRIGHT 2 1910409 19920805  COPYRIGHT 2 19910409 19920805  COPYRIGHT 2 19910400 19920805  COPYRIGHT 2 19910400 19910904 19960110 20020502	8, GR, IT, LI, NL, SE AU 1990-64634 NO 1990-4492 CA 1990-2027952 JP 1990-281690 US 1993-126747  2006 ACS on STN and hydrocarbon gas APPLICATION NO	19901015 19901017 19901018 19901019 19930927  DATE 19890828 19910131 19910220  Auctivity DATE 19900927
TI PI L4 TI	R: AT, BE, CH AU 9064634 NO 9004492 CA 2027952 JP 03255023 US 5378451  ANSWER 105 OF 214 Etching of semicon PATENT NO.	H, DE, DK A1 A AA A2 A CAPLUS IND A2 A1 B A CAPLUS A1 B A A A2 A1 B A A A1 B A A2 A1 B A A1 B A A2 A1 B A A1 B A A1 B A A1 B A A1 B A1 B	C, ES, FR, GB 19910426 19910420 19911113 19950103  COPYRIGHT 2 1910409 19920805  COPYRIGHT 2 19910409 19920805  COPYRIGHT 2 19910400 19920805  COPYRIGHT 2 19910410 19910904 19960110 20020502 19910411	8, GR, IT, LI, NL, SE AU 1990-64634 NO 1990-4492 CA 1990-2027952 JP 1990-281690 US 1993-126747  2006 ACS on STN and hydrocarbon gas APPLICATION NO.	19901015 19901017 19901018 19901019 19930927  DATE 19890828 19910131 19910220  Auctivity DATE 19900927

	US 5096933	A	19920317	US	1990-577174	19900904
	US 5096933 CA 2024714	B1 AA	19960326 19910407	CA	1990-2024714	19900906
	CA 2024714	C	19980623			
	AT 132882	E	19960115		1990-118532	
	ES 2081887 JP 03152160	T3 A2	19960316 19910628		1990-118532 1990-266573	
	JP 3216646	B2	20011009		1990 200373	1770100
	KR 173981	B1	19990401	KR	1990-15963	19901006
L4 TI	ANSWER 107 OF 214 Working fluid		COPYRIGHT 2	2006	ACS on STN	
	PATENT NO.	KIND	DATE		PLICATION NO.	DATE
PI	EP 430170	A1	19910605	EP	1990-122653	19901127
•	EP 430170	B1	19940803			
	R: DE, FR, GB JP 03170584	A2	19910724	qT,	1989-311153	19891130
	JP 2532695	B2	19960911	01	1707 311133	17071130
	JP 03170587	A2	19910724	JP	1989-311156	19891130
	JP 2532696	B2	19960911			
L4 TI	ANSWER 108 OF 214 Working fluid				ACS on STN	
	PATENT NO.	KIND	DATE	API	PLICATION NO.	DATE
ΡI	EP 430171	 Δ1	19910605		1990-122654	
	EP 430171 R: DE, FR, GB	B1	19931006			
			19910725	JP	1989-311166	19891130
	JP 2532697	B2	19960911			
	JP 03172386	A2	19910725	JP	1989-311168	19891130
	JP 2548412	B2	19961030			
L4 TI	ANSWER 109 OF 214				ACS on STN 3, (CFC 113, CCl2FC	71 F2)
	cacaryere nyaroace.		1011 01 11001		, (010 115, 001110	J11 <b>2</b> ,
L4	ANSWER 110 OF 214					
TI	Production of ion PATENT NO.	oeams by KIND			anced sputtering of PLICATION NO.	
	FAIBNI NO.					
PI	WO 9010303 WO 9010303		19900907 19901018	WO	1990-US677	19900206
	W: JP, KP					
					F, LU, NL, SE 1989-311504	19890214
L4	ANSWER 111 OF 214	CAPLUS	COPYRIGHT 2	2006	ACS on STN	
TI	Anti-reflective coa	ating co	mprising lig			
	PATENT NO.	KIND	DATE		PLICATION NO.	DATE
ΡI	EP 400796	A1	19901205	EP	1990-304073	19900417
	EP 400796	B1	19940316			
	R: DE, FR, GB					
	CA 2015802	AA A2	19901130	CA .TD	1990-2015802	19900501
	US 5208101	AZ A	19930504	US	1990-2015802 1990-139560 1991-723992	19910701
L4 TI	ANSWER 112 OF 214					
ΤŢ	Manufacture of flame PATENT NO.				PLICATION NO.	DATE
ΡI	JP 02123143 JP 06045719	A2 B4	19900510 19940615	JP	1988-274431	19881101
L4	ANSWER 113 OF 214	CAPLUS	COPYRIGHT 2	2006	ACS on STN	

L4 ANSWER 113 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN

TI Laser induced nonstationary processes in gaseous mixtures through porous media

L4 TI	polyurethane foam ma	agent o	with at leas ure	t one liquid reaction o	component in
				APPLICATION NO.	DATE
PI	DE 3819630 EP 345580 EP 345580	A1 A2 A3	19891214 19891213 19900926	DE 1988-3819630 EP 1989-109610	19880609 19890527
	R: AT, BE, CH, JP 02039921	A2	19900208	JP 1989-143203	19890607
L4	ANSWER 115 OF 214 C				
TI	Heat pumps with fluc	KIND	DATE	APPLICATION NO.	DATE
PI		A2	19890811	JP 1988-25011	19880204
L4 TI	aromatic compound pr	ng deac	tivated Grou on	p VIII element-zeolite	catalysts for
	PATENT NO.	KIND		APPLICATION NO.	DATE
PI	EP 316727 EP 316727	A1 B1	19890524 19920122	EP 1988-118621	
	R: BE, CH, DE,	FR, GB	, IT, LI, NL	, SE US 1988-256697	10001012
	US 4937215 CA 1317927			CA 1988-580661	
	JP 01231944			JP 1988-280348	19881108
L4 TI	ANSWER 117 OF 214 OF Pyrolytically coated PATENT NO.		glass and it		DATE
ΡI		A1		DE 1988-3823089 GB 1987-16388	
	GB 2206878 GB 2206878	B2	19910717	GB 1987-16388	198/0/11
	ES 2006972	A6 A4	19890516	ES 1988-1782 BE 1988-683	19880608
	BE 1002216	A4	19901016	BE 1988-683	19880615
	FR 2617833			FR 1988-8210	19880616
	FR 2617833 AT 8801725	B1 A	19920417	AT 1988-1725	19880704
	NL 8801713	A	19890201	NL 1988-1713	19880707
	CH 675416	Α	19900928	CH 1988-2595	19880707
	SE 8802578	Α	19890112	SE 1988-2578	19880708
	SE 465921	В	19911118		
	SE 465921 SE 465921 JP 01033033	Δ2	19920312 19890202	JP 1988-170751	19880708
L4	ANSWER 118 OF 214 C				23000.00
TI	Multilayer heat insu		and their m	anufacture	
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 63149142			JP 1986-297088	
L4 TI	ANSWER 119 OF 214 C Process for protecti aquatic environment	ng elec		006 ACS on STN sensors from biofoulin	g in an
			DATE	APPLICATION NO.	DATE
PI	US 4763537	Α	19880816	US 1986-941774	19861215
L4 TI	ANSWER 120 OF 214 C	APLUS	COPYRIGHT 2	006 ACS on STN ws through capillaries	·
Τ 4	AMENDED 101 OF 014 O	ייי זמ גי	CODVETCUM	OOF ACC CO CON	
L4 TI	ANSWER 121 OF 214 C Aerosol waterproof s PATENT NO.	unscree	en composition	ons	DATE
ΡI	US 4686099			APPLICATION NO. 	

	•				
	GB 2202740	A1	19881005	GB 1987-7617	19870331
	GB 2202740	B2	19901212		
L4 TI	ANSWER 122 OF 214 Improvement of the			2006 ACS on STN ance of bottles by surfa	ce treatment
L4	ANSWER 123 OF 214	CAPLUS	COPYRIGHT	2006 ACS on STN	
TI	Manufacture of hol	low fibe	ers		
	PATENT NO.			APPLICATION NO.	DATE
PI				JP 1985-255018	
L4 TI	ANSWER 124 OF 214 Laser action on ga			2006 ACS on STN rough metal capillaries	
L4	ANSWER 125 OF 214		COPYRIGHT	2006 ACS on STN	
TI	Silica film etchin PATENT NO.	KIND		APPLICATION NO.	DATE
PI	JP 61251138				19850430
L4 TI	ANSWER 126 OF 214 Effect of laser ra capillaries in a t	diation	on the pas	sage of resonance molecu	les through
L4	ANSWER 127 OF 214	CADITIC	COPVETCHT	2006 ACS on STN	
TI	Semiconductor devi PATENT NO.				DATE
	PAIGNI NO.				
ΡΙ	JP 60143633 JP 61004179	A2 B4		JP 1984-250543	19841129
L4	ANSWER 128 OF 214	CAPLUS	COPYRIGHT	2006 ACS on STN	
TI	Nonflammable aeros		llant micro	oemulsion system	23.00
	PATENT NO.	KIND		APPLICATION NO.	DATE
ΡI	US 4536323	A	19850820	US 1983-508643	19830628
	CA 1205349	A1	19860603	US 1983-508643 CA 1984-457246 AU 1984-33083	19840622
	AU 574715 AU 8433083	B2 A1	19880714	AU 1984-33083	19840917
	US 4655959	A		US 1985-749962	19850701
L4	ANSWER 129 OF 214	CADLIE	CODVDICUT	2006 ACC on STN	
TI	Gas and method for	selecti	ve etching	of silicon nitride	
	PATENT NO.	KIND	DATE	APPLICATION NO.  DE 1984-3420347  JP 1983-95651	DATE
·PI	DE 3420347	∸- Δ1	19841206	DE 1984-3420347	19840530
	DE 3420347 DE 3420347	C2	19870820	DE 1904 3420347	10040000
	JP 59222933	A2	19841214	JP 1983-95651	19830601
	JP 60115232	A2	19850621	JP 1983-222072	19831128
	NL 8401774	A	19850102	JP 1983-222072 NL 1984-1774 US 1984-616114	19840601
	US 4529476	A	19850/16	US 1984-616114	19840601
L4 TI	ANSWER 130 OF 214 Limit of thermal i			2006 ACS on STN c-initiated unbranched c	hain reaction
L4 TI	ANSWER 131 OF 214 Determination of particules			2006 ACS on STN nteraction potential of	polar
L4 TI	ANSWER 132 OF 214 Hydrotreating vacus compound			2006 ACS on STN atalyst and an added org	anic fluorine
	_	KIND	DATE	APPLICATION NO.	
PI				US 1981-301754 JP 1983-77342	

ANSWER 133 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN

L4

$\mathtt{TI}$	Foamed body of a	vinyl chloride-base				
	PATENT NO.	KIND DATE	APPLICATION NO.	DATE		
PΙ	GB 2110216	A1 19830615	GB 1982-32528	19821115		
	JP 58084832	A2 19830521	JP 1981-183349	19811116		
	JP 62017613	B4 19870418				
	JP 58087135	A2 19830524	JP 1981-185968	19811119		
	JP 02030341	B4 19900705				

- L4 ANSWER 134 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Solubility of vinyl chloride, trifluorochloroethylene, difluoroethane, hexafluoropropylene, and hexafluoropropylene oxide in water
- L4 ANSWER 135 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Viscosity of difluoroethane
- L4 ANSWER 136 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Specification and usage requirements for 3AL seamless, aluminum cylinders
- L4 ANSWER 137 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Fluorination of catalysts

11	FIUOTINACION OF C	acaryses			
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	GB 2024642	A	19800116	GB 1979-23338	19790704
	GB 2024642	B2	19820818		
	FR 2430263	A1	19800201	FR 1978-20182	19780706
	FR 2430263	B1	19810102		
	CA 1137062	A1	19821207	CA 1979-326392	19790426
	NL 7905206	A	19800108	NL 1979-5206	19790704
	DE 2927052	A1	19800117	DE 1979-2 <b>927052</b>	19790704
	JP 55011097	A2	19800125	JP 1979-84050	19790704
	JP 62052623	B4	19871106		

- L4 ANSWER 138 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Solvent effects on the distribution coefficients. III. The solubility of some lower fluoro- and chlorohydrocarbons in organic solvents
- L4 ANSWER 139 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Determination of gas-kinetic diameters of molecules of difluoroethane and fluoro-substituted derivatives of ethylene
- L4 ANSWER 140 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Determination of the gas-kinetic diameters of molecules of difluoroethane and fluorine-substituted derivatives of ethylene
- L4 ANSWER 141 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Effect of diffusion on absorption and saturation of infrared radiation in molecular gases
- L4 ANSWER 142 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Study of the thermal conductivity of toluene and some difluoroethanes at high pressures
- L4 ANSWER 143 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Toxicity of aerosol propellants in the respiratory and circulatory systems. VIII. Respiration and circulation in primates
- L4 ANSWER 144 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Effect of diffusion on absorption and saturation of infrared radiation in molecular gases
- L4 ANSWER 145 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Toxicity of aerosol propellants in the respiratory and circulatory systems. VI. Influence of cardiac and pulmonary vascular lesions in the rat
- L4 ANSWER 146 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Cardiopulmonary toxicity of propellants for aerosols

- L4 ANSWER 147 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Solubility of chlorine, hydrogen chloride, difluoro- and difluorochloroethanes in chloroorganic solvents
- L4 ANSWER 148 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Toxicity of aerosol propellants on the respiratory and circulatory systems. III. Influence of bronchopulmonary lesion on cardiopulmonary toxicity in the mouse
- L4 ANSWER 149 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Toxicity of aerosol propellants in the respiratory and circulatory systems. IV. Cardiotoxicity in the monkey
- L4 ANSWER 150 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Identification of absorption lines in gases used to modulate the carbon dioxide laser
- L4 ANSWER 151 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Thermal energy electron attachment rate constants for some polyatomic molecules
- L4 ANSWER 152 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN

TI Regeneration of hydrocracking catalysts

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	DE 2249892	A1	19730419	DE 1972-2249892	19721011
	US 3725244	Α	19730403	US 1971-188408	19711013

- L4 ANSWER 153 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Hydrocracking catalyst activation treatment

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	US 3673108	A	19720627	US 1969-889681	19691231

- L4 ANSWER 154 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Homopolymers and copolymers of vinylidene fluoride
  PATENT NO KIND DATE APPLICATION NO.

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
FR 1570233		19690606	FR	
DE 1770672			DE	
GB 1188889			GB	
US 3616371		19710000	US	

- L4 ANSWER 155 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Metal oxide films

ΡI

11	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	GB 1167128		19691015	GB	
	FR 1572757			FR	
	US 3477936		19690000	US	

- L4 ANSWER 156 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Gas-chromatographic analysis of aerosols by pressurized liquid sampling
- L4 ANSWER 157 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- Hair waving, two phase, quick breaking, aerosol foam TΤ PATENT NO. KIND DATE APPLICATION NO. DATE ---------\_\_\_\_\_ \_\_\_\_\_ \_\_\_\_\_ PΤ US 3433868 Α 19690318 US 1964-385467 19640727
- L4 ANSWER 158 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Concentration of sea water and brine by the gas hydration process. XIV. Pressure and temperature diagrams of mixed hydrating agents
- L4 ANSWER 159 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Careful removal of acetylene and difluroethane from vinyl fluoride
- L4 ANSWER 160 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Studies on explosions. I

```
L4
     ANSWER 161 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
ΤI
     Conversion of hydrocarbons by hydrogen
                KIND DATE APPLICATION NO.
                                                             DATE
     PATENT NO.
                              -----
                                         _____
                                                               _____
     _____
                              19640117
     FR 1349148
                                         FR
                                                               19620408
PΙ
     ANSWER 162 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Effect of anions on the electrocrystallization of zinc and cadmium
ΤI
     ANSWER 163 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
1.4
     The electrochemical fluorination of organosilicon compounds
тT
    ANSWER 164 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Refrigerant mixture of dichlorodifluoromethane and difluoroethane
ΤI
                KIND DATE APPLICATION NO. DATE
     PATENT NO.
     -----
                             19510417
    US 23358
                                         US
PΙ
    ANSWER 165 OF 214 USPATFULL on STN
L4
      Materials and methods for the conversion of hydrofluorocarbons
ΤI
      US 2005288536 A1 20051229
PI
    ANSWER 166 OF 214 USPATFULL on STN
L4
      Process for making polyurethane and polyisocyanurate foams using
TT
      mixtures of a hydrofluorocarbon and methyl formate as a blowing agent
      US 2005277701
                     A1 20051215
PΙ
    ANSWER 167 OF 214 USPATFULL on STN
L4
TΤ
      Topical spray compositions
                  B1 20051108
PΙ
      US 6962691
    ANSWER 168 OF 214 USPATFULL on STN
L4
      Heat transfer fluids and methods of making and using same
TI
      US 2005218371 A1 20051006
PΙ
    ANSWER 169 OF 214 USPATFULL on STN
L4
ΤI
      Refrigerant composition .
      US 2005109977 A1 20050526
PΙ
    ANSWER 170 OF 214 USPATFULL on STN
L4
      Closed cycle refrigeration system and mixed component refrigerant
TI
      US 2005086950 A1 20050428
PΙ
    ANSWER 171 OF 214 USPATFULL on STN
L4
      Etchant with selectivity for doped silicon dioxide over undoped silicon
TТ
      dioxide and silicon nitride, processes which employ the etchant, and
      structures formed thereby
PΙ
      US 6875371
                      B1 20050405
    ANSWER 172 OF 214 USPATFULL on STN
L4
      Heat transfer fluids and methods of making and using same
ΤI
PΤ
      US 2004227125
                     A1 20041118
    ANSWER 173 OF 214 USPATFULL on STN
L4
TI
      Topical spray compositions
PΙ
      US 2004213744
                     A1 20041028
    ANSWER 174 OF 214 USPATFULL on STN
L4
ΤI
      Formulations of mometasone and a bronchodilator for pulmonary
      administration
      US 2004198708
PΙ
                     A1 20041007
    ANSWER 175 OF 214 USPATFULL on STN
L4
TI
      Sol-gel-derived halogen-doped glass
ΡI
      US 2004194511
                      A1 20041007
    ANSWER 176 OF 214 USPATFULL on STN
L4
ΤI
      Materials and methods for the conversion of hydrofluorocarbons
```

```
PΙ
       US 2004127757
                          A1
                               20040701
1.4
     ANSWER 177 OF 214 USPATFULL on STN
       Method for plasma etching performance enhancement
TT
       US 2004072443
                               20040415
PΙ
                          A1
       US 6833325
                          B2
                                20041221
L4
     ANSWER 178 OF 214 USPATFULL on STN
       Methods for etching photolithographic reticles
ΤI
       US 2004072081
                               20040415
PΙ
                          A1
     ANSWER 179 OF 214 USPATFULL on STN
L4
ΤI
       Etchant with selectivity for doped silicon dioxide over undoped silicon
       dioxide and silicon nitride, processes which employ the etchant, and
       structures formed thereby
рT
       US 2003203639
                          A1
                               20031030
     ANSWER 180 OF 214 USPATFULL on STN
L4
       Etchant with selectivity for doped silicon dioxide over undoped silicon
TT
       dioxide and silicon nitride, processes which employ the etchant, and
       structures formed thereby
       US 6537922
                          В1
                               20030325
РΤ
     ANSWER 181 OF 214 USPATFULL on STN
L4
       Variable load refrigeration system particularly for cryogenic
TΙ
       temperatures
PΙ
       US 6426019
                          B1
                               20020730
     ANSWER 182 OF 214 USPATFULL on STN
L4
       Formulations of mometasone and a bronchodilator for pulmonary
TI
       administration
       US 2002076382
PТ
                          A1
                               20020620
     ANSWER 183 OF 214 USPATFULL on STN
L4
       Substrate cleaning apparatus and method
TI
       US 2002072016
                      A1
                               20020613
PΤ
       US 6692903
                          В2
                               20040217
     ANSWER 184 OF 214 USPATFULL on STN
L4
       Apparatus for providing ozonated process fluid and methods for using
TΙ
       same
       US 2002066717
                          A1
                               20020606
PΤ
     ANSWER 185 OF 214 USPATFULL on STN
L4
ΤI
       Lubricant refrigerant composition for hydrofluorocarbon (HFC)
       refrigerants
       US 6374629
PΙ
                          B1
                               20020423
     ANSWER 186 OF 214 USPATFULL on STN
L4
TI
       High-density plasma etching of carbon-based low-k materials in a
       integrated circuit
                          B1
PΙ
       US 6284149
                               20010904
     ANSWER 187 OF 214 USPATFULL on STN
L4
TI
       Flower-like capacitor structure for a memory cell
ΡI
       US 6281542
                          B1
                               20010828
     ANSWER 188 OF 214 USPATFULL on STN
TI
       Etchant with selectivity for doped silicon dioxide over undoped silicon
       dioxide and silicon nitride, processes which employ the etchant, and
       structures formed thereby
PΙ
       US 6117791
                               20000912
     ANSWER 189 OF 214 USPATFULL on STN
L4
       Aerosol cosmetic compositions, aerosols containing them and uses
TΙ
PΙ
       US 6113923
                               20000905
     ANSWER 190 OF 214 USPATFULL on STN
L4
       Fluorine assisted stripping and residue removal in sapphire downstream
TT
```

plasma asher PΙ US 6082374 20000704 ANSWER 191 OF 214 USPATFULL on STN L4 Variable load refrigeration system particularly for cryogenic TI temperatures 20000620 PΙ US 6076372 ANSWER 192 OF 214 USPATFULL on STN L4Process for the reduction of chlorofluorocarbons and production of TI derivatives thereof in an electrolytic cell, cell for carrying out said reduction and process for removing the by-products formed within the cell US 6068756 20000530 PΤ WO 9724162 19970410 ANSWER 193 OF 214 USPATFULL on STN L4Fixative vinyl acetate tetrapolymers TI 19981103 PT US 5830439 ANSWER 194 OF 214 USPATFULL on STN 1.4 Method for etching dielectric using fluorohydrocarbon gas, NH.sub.3 ΤI -generating gas, and carbon-oxygen gas 19980929 US 5814563 PΙ ANSWER 195 OF 214 USPATFULL on STN L4 Spray formulation for the testing of smoke detectors TI19980728 PΤ US 5785891 ANSWER 196 OF 214 USPATFULL on STN L4Antiperspirant aerosol composition with high solids content ΤI PΙ US 5605682 19970225 ANSWER 197 OF 214 USPATFULL on STN Hydrogen fluoride dopant source in the preparation of conductive coated TТ substrate PΙ US 5496583 19960305 L4ANSWER 198 OF 214 USPATFULL on STN Working fluid containing difluoroethane TI PΙ US 5433879 19950718 ANSWER 199 OF 214 USPATFULL on STN T.4 Manufacture of rigid foams and compositions therefor TΤ US 5391584 19950221 PΤ ANSWER 200 OF 214 USPATFULL on STN T.4 Topical medicinal pressurized aerosol compositions and method of TI preparation, method of use and article of manufacture thereof PΙ US 5378451 19950103 ANSWER 201 OF 214 USPATFULL on STN L4 ΤI Gaseous doping of tungsten oxide PΙ US 5324537 19940628 L4ANSWER 202 OF 214 USPATFULL on STN ΤI . Working fluid PΙ US 5304319 19940419 L4 ANSWER 203 OF 214 USPATFULL on STN TI Anti-reflective coatings comprising light metal fluorides PΤ US 5208101 19930504 ANSWER 204 OF 214 USPATFULL on STN L4ΤI Process for etching ΡI US 5110408 19920505 ANSWER 205 OF 214 USPATFULL on STN L4 TI Process for the preparation of polyurethane rigid foams having a low

thermal conductivity and their use PΙ US 5096933 ANSWER 206 OF 214 USPATFULL on STN L4Production of ion beams by chemically enhanced sputtering of solids TI 19920218 US 5089746 PΙ ANSWER 207 OF 214 USPATFULL on STN L4Process for restoring deactivated catalysts ΤI 19900626 PΙ US 4937215 ANSWER 208 OF 214 USPATFULL on STN L4 Process for protecting electrochemical sensors from biofouling in an ΤI aquatic environment 19880816 ΡI US 4763537 ANSWER 209 OF 214 USPATFULL on STN L4Aerosol waterproof sunscreen compositions TI US 4686099 19870811 PΙ ANSWER 210 OF 214 USPATFULL on STN L4Preparation of non-flammable aerosol propellant microemulsion system TI US 4655959 19870407 PΙ ANSWER 211 OF 214 USPATFULL on STN L4Non-flammable aerosol propellant microemulsion system ΤI PΙ US 4536323 19850820 ANSWER 212 OF 214 USPATFULL on STN L4Gas for selectively etching silicon nitride and process for selectively ΤI etching silicon nitride with the gas PΙ US 4529476 19850716 ANSWER 213 OF 214 USPATFULL on STN L4Hydrotreating vacuum gas oils with catalyst and added organic fluorine TIcompound PΙ US 4420388 19831213 L4ANSWER 214 OF 214 USPATFULL on STN HYDROCRACKING CATALYST ACTIVATION TREATMENT ΤI PΙ US 3673108 19720627

```
Welcome to STN International! Enter x:x
LOGINID:ssspta1751gxw
PASSWORD:
TERMINAL (ENTER 1, 2, 3, OR ?):2
 * * * * * * * *
                     Welcome to STN International
                 Web Page URLs for STN Seminar Schedule - N. America
NEWS
      1
                 "Ask CAS" for self-help around the clock
NEWS
         DEC 05 CASREACT(R) - Over 10 million reactions available
NEWS
      3
NEWS
      4
         DEC 14
                 2006 MeSH terms loaded in MEDLINE/LMEDLINE
         DEC 14 2006 MeSH terms loaded for MEDLINE file segment of TOXCENTER
NEWS 5
         DEC 14 CA/CAplus to be enhanced with updated IPC codes
NEWS 6
         DEC 21 IPC search and display fields enhanced in CA/CAplus with the
NEWS 7
                 IPC reform
         DEC 23
                 New IPC8 SEARCH, DISPLAY, and SELECT fields in USPATFULL/
NEWS
      8
                 USPAT2
                 IPC 8 searching in IFIPAT, IFIUDB, and IFICDB
NEWS 9
         JAN 13
                 New IPC 8 SEARCH, DISPLAY, and SELECT enhancements added to
NEWS 10
         JAN 13
                 INPADOC
         JAN 17
                 Pre-1988 INPI data added to MARPAT
NEWS 11
NEWS 12
         JAN 17
                 IPC 8 in the WPI family of databases including WPIFV
                 Saved answer limit increased
NEWS 13
         JAN 30
                 Monthly current-awareness alert (SDI) frequency
NEWS 14
         JAN 31
                 added to TULSA
         FEB 21 STN AnaVist, Version 1.1, lets you share your STN AnaVist
NEWS 15
                 visualization results
NEWS 16 FEB 22
                 Status of current WO (PCT) information on STN
NEWS 17 FEB 22
                 The IPC thesaurus added to additional patent databases on STN
NEWS 18 FEB 22 Updates in EPFULL; IPC 8 enhancements added
NEWS 19 FEB 27 New STN AnaVist pricing effective March 1, 2006
NEWS 20 FEB 28 MEDLINE/LMEDLINE reload improves functionality
NEWS 21 FEB 28
                 TOXCENTER reloaded with enhancements
NEWS 22
         FEB 28
                 REGISTRY/ZREGISTRY enhanced with more experimental spectral
                 property data
NEWS 23 MAR 01
                 INSPEC reloaded and enhanced
NEWS EXPRESS
             FEBRUARY 15 CURRENT VERSION FOR WINDOWS IS V8.01a,
              CURRENT MACINTOSH VERSION IS V6.0c(ENG) AND V6.0jc(jp),
              AND CURRENT DISCOVER FILE IS DATED 19 DECEMBER 2005.
              V8.0 AND V8.01 USERS CAN OBTAIN THE UPGRADE TO V8.01a AT
              http://download.cas.org/express/v8.0-Discover/
NEWS HOURS
              STN Operating Hours Plus Help Desk Availability
              General Internet Information
NEWS INTER
NEWS LOGIN
              Welcome Banner and News Items
              Direct Dial and Telecommunication Network Access to STN
NEWS PHONE
              CAS World Wide Web Site (general information)
NEWS WWW
```

Enter NEWS followed by the item number or name to see news on that specific topic.

All use of STN is subject to the provisions of the STN Customer agreement. Please note that this agreement limits use to scientific research. Use for software development or design or implementation of commercial gateways or other similar uses is prohibited and may result in loss of user privileges and other penalties.

=> s difluoroethane/cn

THIS COMMAND NOT AVAILABLE IN THE CURRENT FILE

Some commands only work in certain files. For example, the EXPAND command can only be used to look at the index in a file which has an index. Enter "HELP COMMANDS" at an arrow prompt (=>) for a list of commands which can be used in this file.

commands which can be used in this file.

=> file reg

COST IN U.S. DOLLARS

SINCE FILE TOTAL ENTRY SESSION 0.21 0.21

FULL ESTIMATED COST

FILE 'REGISTRY' ENTERED AT 11:33:07 ON 02 MAR 2006

USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.

PLEASE SEE "HELP USAGETERMS" FOR DETAILS.

COPYRIGHT (C) 2006 American Chemical Society (ACS)

Property values tagged with IC are from the ZIC/VINITI data file provided by InfoChem.

STRUCTURE FILE UPDATES: 1 MAR 2006 HIGHEST RN 875609-25-9 DICTIONARY FILE UPDATES: 1 MAR 2006 HIGHEST RN 875609-25-9

New CAS Information Use Policies, enter HELP USAGETERMS for details.

TSCA INFORMATION NOW CURRENT THROUGH January 6, 2006

Please note that search-term pricing does apply when conducting SmartSELECT searches.

\* The CA roles and document type information have been removed from \*

\* the IDE default display format and the ED field has been added,

\* effective March 20, 2005. A new display format, IDERL, is now

Structure search iteration limits have been increased. See HELP SLIMITS for details.

REGISTRY includes numerically searchable data for experimental and predicted properties as well as tags indicating availability of experimental property data in the original document. For information on property searching in REGISTRY, refer to:

http://www.cas.org/ONLINE/UG/regprops.html

=> s difluoroethane/cn

L1 1 DIFLUOROETHANE/CN

=> s trifluoromethyl iodide/cn

L2 1 TRIFLUOROMETHYL IODIDE/CN

=> file caplus, uspatful COST IN U.S. DOLLARS

SINCE FILE ENTRY

TOTAL SESSION

FULL ESTIMATED COST

9.96 10.17

FILE 'CAPLUS' ENTERED AT 11:33:34 ON 02 MAR 2006 USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT. PLEASE SEE "HELP USAGETERMS" FOR DETAILS. COPYRIGHT (C) 2006 AMERICAN CHEMICAL SOCIETY (ACS)

FILE 'USPATFULL' ENTERED AT 11:33:34 ON 02 MAR 2006
CA INDEXING COPYRIGHT (C) 2006 AMERICAN CHEMICAL SOCIETY (ACS)

```
=> s 11 and 12
1.3
            0 L1 AND L2
=> s l1
          214 L1
1.4
=> s 12
         2027 L2
L5
=> s 14 and 15
            0 L4 AND L5
=> file reg
                                              SINCE FILE
                                                              TOTAL
COST IN U.S. DOLLARS
                                                   ENTRY
                                                            SESSION
FULL ESTIMATED COST
                                                    1.97
                                                              12.14
FILE 'REGISTRY' ENTERED AT 11:34:05 ON 02 MAR 2006
USE IS SUBJECT TO THE TERMS OF YOUR STN CUSTOMER AGREEMENT.
PLEASE SEE "HELP USAGETERMS" FOR DETAILS.
COPYRIGHT (C) 2006 American Chemical Society (ACS)
Property values tagged with IC are from the ZIC/VINITI data file
provided by InfoChem.
                         1 MAR 2006 HIGHEST RN 875609-25-9
STRUCTURE FILE UPDATES:
                         1 MAR 2006 HIGHEST RN 875609-25-9
DICTIONARY FILE UPDATES:
New CAS Information Use Policies, enter HELP USAGETERMS for details.
TSCA INFORMATION NOW CURRENT THROUGH January 6, 2006
  Please note that search-term pricing does apply when
  conducting SmartSELECT searches.
* The CA roles and document type information have been removed from *
* the IDE default display format and the ED field has been added,
* effective March 20, 2005. A new display format, IDERL, is now
 available and contains the CA role and document type information.
*******************
Structure search iteration limits have been increased. See HELP SLIMITS
for details.
REGISTRY includes numerically searchable data for experimental and
predicted properties as well as tags indicating availability of
experimental property data in the original document. For information
on property searching in REGISTRY, refer to:
http://www.cas.org/ONLINE/UG/regprops.html
=> d his
     (FILE 'HOME' ENTERED AT 11:32:45 ON 02 MAR 2006)
    FILE 'REGISTRY' ENTERED AT 11:33:07 ON 02 MAR 2006
L1
             1 S DIFLUOROETHANE/CN
L2
             1 S TRIFLUOROMETHYL IODIDE/CN
    FILE 'CAPLUS, USPATFULL' ENTERED AT 11:33:34 ON 02 MAR 2006
L3
             0 S L1 AND L2
L4
           214 S L1
          2027 S L2
L5
L6
             0 S L4 AND L5
```

```
FILE 'REGISTRY' ENTERED AT 11:34:05 ON 02 MAR 2006
=> d l1
     ANSWER 1 OF 1 REGISTRY COPYRIGHT 2006 ACS on STN
Ь1
     25497-28-3 REGISTRY
RN
     Entered STN: 16 Nov 1984
ED
     Ethane, difluoro- (6CI, 7CI, 8CI, 9CI) (CA INDEX NAME)
CN
OTHER NAMES:
    Difluoroethane
CN
     C2 H4 F2
MF
     IDS, COM
CI
                  BIOSIS, CA, CAOLD, CAPLUS, CASREACT, CHEMLIST, CIN, DETHERM*,
     STN Files:
LC
       ENCOMPLIT, ENCOMPLIT2, ENCOMPPAT, ENCOMPPAT2, IFICDB, IFIPAT, IFIUDB,
       NIOSHTIC, PDLCOM*, PIRA, PROMT, TOXCENTER, TULSA, USPAT2, USPATFULL, VTB
         (*File contains numerically searchable property data)
1/2 H<sub>3</sub>C-CH<sub>3</sub>
     D1-F
**PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT**
             164 REFERENCES IN FILE CA (1907 TO DATE)
             164 REFERENCES IN FILE CAPLUS (1907 TO DATE)
               3 REFERENCES IN FILE CAOLD (PRIOR TO 1967)
=> d 12
     ANSWER 1 OF 1 REGISTRY COPYRIGHT 2006 ACS on STN
     2314-97-8 REGISTRY
     Entered STN: 16 Nov 1984
     Methane, trifluoroiodo- (6CI, 8CI, 9CI) (CA INDEX NAME)
OTHER NAMES:
CN
    Freon 13I1
    Iodotrifluoromethane
CN
CN
    Monoiodotrifluoromethane
    Perfluoromethyl iodide
CN
CN
    R 13I1
    Trifluoroiodomethane
CN
CN
    Trifluoromethyl iodide
FS
     3D CONCORD
DR
     263005-66-9
MF
     C F3 I
CI
     COM
                  BEILSTEIN*, BIOSIS, CA, CAOLD, CAPLUS, CASREACT, CHEMCATS,
LC
     STN Files:
       CHEMINFORMRX, CHEMLIST, CHEMSAFE, CIN, CSCHEM, CSNB, DETHERM*, DIPPR*,
       GMELIN*, IFICDB, IFIPAT, IFIUDB, MEDLINE, MSDS-OHS, PROMT, PS, RTECS*,
       SPECINFO, TOXCENTER, ULIDAT, USPATZ, USPATFULL, VTB
         (*File contains numerically searchable property data)
```

EINECS\*\*, NDSL\*\*, TSCA\*\*

(\*\*Enter CHEMLIST File for up-to-date regulatory information)

Other Sources:

- 1837 REFERENCES IN FILE CA (1907 TO DATE)
  - 12 REFERENCES TO NON-SPECIFIC DERIVATIVES IN FILE CA
- 1839 REFERENCES IN FILE CAPLUS (1907 TO DATE)
  - 88 REFERENCES IN FILE CAOLD (PRIOR TO 1967)

#### => d his

L1

L3

(FILE 'HOME' ENTERED AT 11:32:45 ON 02 MAR 2006)

FILE 'REGISTRY' ENTERED AT 11:33:07 ON 02 MAR 2006

1 S DIFLUOROETHANE/CN

L2 1 S TRIFLUOROMETHYL IODIDE/CN

FILE 'CAPLUS, USPATFULL' ENTERED AT 11:33:34 ON 02 MAR 2006

0 S L1 AND L2

L4 214 S L1

L5 2027 S L2

L6 0 S L4 AND L5

FILE 'REGISTRY' ENTERED AT 11:34:05 ON 02 MAR 2006

## => d 14 ti,pi

YOU HAVE REQUESTED DATA FROM FILE 'CAPLUS, USPATFULL' - CONTINUE? (Y) /N:y

L4 ANSWER 1 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN

TI Making polyurethane and polyisocyanurate foams, mixtures of a hydrofluorocarbon and methyl formate as a blowing agent, polyol premix of reduced vapor pressure

	PATENT NO.						KIND DATE			APPLICATION NO.						DATE			
ΡI	US	2005	 2777	01		A1	A1 20051215				US 2	004-		20040615					
	WO	2006	0020	43		A1		2006	0105	5 WO 2005-US20929						20050614			
		W:	ΑE,	AG,	AL,	AM,	AT,	AU,	AZ,	BA,	BB,	BG,	BR,	BW,	BY,	BZ,	CA,	CH,	
			CN,	co,	CR,	CU,	CZ,	DE,	DK,	DM,	DZ,	EC,	EE,	EG,	ES,	FI,	GB,	GD,	
			GE,	GH,	GM,	HR,	HU,	ID,	IL,	IN,	IS,	JP,	KE,	KG,	KM,	KP,	KR,	KZ,	
			LC,	LK,	LR,	LS,	LT,	LU,	LV,	MA,	MD,	MG,	MK,	MN,	MW,	MX,	MZ,	NA,	
			NG,	NI,	NO,	NZ,	OM,	PG,	PH,	PL,	PT,	RO,	RU,	SC,	SD,	SE,	SG,	SK,	
			SL,	SM,	SY,	TJ,	TM,	TN,	TR,	TT,	TZ,	UA,	UG,	US,	UZ,	VC,	VN,	YU,	
				ZM,															
		RW:	AT,	BE,	BG,	CH,	CY,	CZ,	DE,	DK,	EE,	ES,	FI,	FR,	GB,	GR,	HU,	ΙE,	
			IS,	IT,	LT,	LU,	MC,	NL,	PL,	PT,	RO,	SE,	SI,	SK,	TR,	BF,	ВJ,	CF,	
			CG,	CI,	CM,	GA,	GN,	GQ,	GW,	ML,	MR,	NE,	SN,	TD,	TG,	BW,	GH,	GM,	
			KE,	LS,	MW,	MZ,	NA,	SD,	SL,	SZ,	TZ,	UG,	ZM,	ZW,	AM,	AZ,	BY,	KG,	
			KZ,	MD,	RU,	TJ,	TM												

=> d 14 ti,pi 1-

YOU HAVE REQUESTED DATA FROM FILE 'CAPLUS, USPATFULL' - CONTINUE? (Y)/N:y

YOU HAVE REQUESTED DATA FROM 214 ANSWERS - CONTINUE? Y/(N):y

- L4 ANSWER 1 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Making polyurethane and polyisocyanurate foams, mixtures of a hydrofluorocarbon and methyl formate as a blowing agent, polyol premix of reduced vapor pressure

	PATENT NO.					KIND		DATE		APPLICATION NO.						DATE			
ΡI	US 2005277701			A1 20051215				,	US 2004-868400						20040615				
	WO 2006002043			A1 20060105			WO 2005-US20929						20050614						
	Ţ	V: AE	, AG,	AL,	AM,	ΑT,	AU,	ΑZ,	BA,	BB,	BG,	BR,	BW,	BY,	BZ,	CA,	CH,		
		CN	, CO,	CR,	CU,	CZ,	DΕ,	DK,	DM,	DZ,	EC,	EE,	EG,	ES,	FI,	GB,	GD,		
		GE	, GH,	GM,	HR,	HU,	ID,	IL,	IN,	IS,	JP,	KE,	KG,	KM,	ΚP,	KR,	KZ,		
		LC	, LK,	LR,	LS,	LT,	LU,	LV,	MA,	MD,	MG,	MK,	MN,	MW,	MX,	ΜZ,	NA,		

```
SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU,
            ZA, ZM, ZW
        RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE,
            IS, IT, LT, LU, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF,
            CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM,
            KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG,
            KZ, MD, RU, TJ, TM
    ANSWER 2 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Procedure for processing hollow glassware, particularly a bottle
ΤI
                       KIND DATE
                                     APPLICATION NO.
    PATENT NO.
                       ----
                              -----
                                         _______
                                                               _____
                        A5
                              20040615
                                         AT 2003-941
                                                               20030617
PΙ
    AT 200300941
    AT 412341
                        В
                              20050125
    ANSWER 3 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
ΤI
    Preparation method and equipment of difluorochloroethane
                       KIND DATE APPLICATION NO.
                                                               DATE
    PATENT NO.
                                         -----
     -----
                       ----
                              -----
                              20041222 CN 2004-10015778
    CN 1556083
                        Α
                                                               20040109
PΙ
    ANSWER 4 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Refrigerant composition with lubricant
TI
    PATENT NO. KIND DATE APPLICATION NO.
                                                              DATE
                            -----
                              20050512 WO 2004-US34724
                      . ____
     _____
    WO 2005042679 · A1
                                                              20041020
PΙ
        W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH,
            CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD,
            GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC,
            LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI,
            NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY,
            TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW
        RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM,
            AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK,
            EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE,
            SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE,
            SN, TD, TG
    US 2005109977
                              20050526
                                         US 2004-969621
                        A1
                                                               20041020
    ANSWER 5 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Closed cycle refrigeration system and mixed component refrigerant
ΤI
    PATENT NO.
                       KIND DATE APPLICATION NO. DATE
    ------
                       _ _ _ _
                              -----
                                         ______
                                                               -----
PΙ
    US 2005086950
                        A1
                              20050428
                                         US 2003-694699
                                                               20031028
    ANSWER 6 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Improvements in or relating to aerosol formulations comprising formoterol
TI
    fumarate dihydrate
                       KIND
                             DATE
                                       APPLICATION NO.
                                                              DATE
                             -----
    ------------
                       ----
                                         -----
    WO 2005034927
ΡI
                       A2
                              20050421
                                        WO 2004-IB3465
                                                               20041008
                       A3
                             20050602
    WO 2005034927
           AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH,
            CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD,
            GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC,
            LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NI,
            NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY,
            TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW
        RW: BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM,
            AZ, BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK,
            EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PL, PT, RO, SE,
            SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE,
            SN, TD, TG
L4
    ANSWER 7 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Consolidation heat treating atmospheres for manufacture of sol-gel-derived
ΤI
    halogen-doped optical glass
    PATENT NO.
                       KIND
                             DATE
                                         APPLICATION NO.
                                                               DATE
```

NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK,

```
ΡI
    US 2004194511 A1
                               20041007
                                           US 2004-771176
                                                                  20040203
                        A1
    US 2003147605
                               20030807
                                           US 2002-62748
                                                                  20020201
                        B2
    US 6928220
                               20050809
                                           US 2002-215162
                                                                  20020807
                        A1
                               20030807
    US 2003147606
    ANSWER 8 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
     Polyol compositions containing polyether or polyester polyols and
ΤI
     polyisocyanate-based foams prepared therefrom
     PATENT NO. KIND DATE APPLICATION NO.
    EP 1435366 A1 20040707 EP 2003-250046
                                                                 20030103
PΙ
        R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
             IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK
                               20040729 CA 2003-2511811 20031223
20040729 WO 2003-US41607 20031223
                        AA
     CA 2511811
                              20040729
     WO 2004063243
                        A1
        W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,
            CO, CR, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM,
            HR, HU, ID, IL, IN, IS, JP, KE, KG, KR, KZ, LC, LK, LR, LS, LT,
            LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, OM, PH, PL, PT,
            RO, RU, SD, SE, SG, SK, SL, TJ, TM, TN, TR, TT, TZ, UA, UG, US,
            UZ, YU, ZA, ZM, ZW
        RW: BW, GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ,
            BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE,
             ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK,
             TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG
     BR 2003017211
                        Α
                               20051101 BR 2003-17211
                                                                 20031223
    ANSWER 9 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Materials and methods for the conversion of hydrofluorocarbons to
ΤI
     fluoromonomers
                       KIND DATE APPLICATION NO.
    US 2004127757 A1 20040701 US 2002-331821 20021230 CA 2511887 AA 20040722 CA 2003-2511887 20031230 WO 2004060842 A1 20040722 WO 2003-US41851 20031230 WO 2004060842 C1 20041021
ΡI
        W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,
            CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH,
            GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR,
            LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NI, NO, NZ, OM,
            PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN,
            TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW
         RW: BW, GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ,
            BY, KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE,
            ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK,
            TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD,
                        A1 20051005 EP 2003-815021
                                                                 20031230
    EP 1581468
            AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
             IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK
                               20051229 US 2005-218055
                                                                  20050831
     US 2005288536
                         A1
    ANSWER 10 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
     Plasma device and procedure for anisotropic etching in of structures in a
TI
     substrate
                      KIND DATE APPLICATION NO.
     PATENT NO.
    DE 10247913
                       ----
                                           ______
                       A1 20040422
A2 20040429
A3 20040722
                               20040422 DE 2002-10247913 20021014
PΙ
     WO 2004036627
                                           WO 2003-DE2971
                                                                 20030909
                               20040429
     WO 2004036627
        W: JP, US
        RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE,
            IT, LU, MC, NL, PT, RO, SE, SI, SK, TR
                         A2 20050720 EP 2003-753277
    EP 1554747
            AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
             IE, SI, FI, RO, CY, TR, BG, CZ, EE, HU, SK
                               20060126 JP 2004-543938
                                                                 20030909
                         T2
     JP 2006503425
```

-----

L4

```
Procedure for the plasma anisotropic etching of a silicon substrate
     PATENT NO. KIND DATE APPLICATION NO.
     -----
                        ----
                               -----
                                          ______
                                                                 _____
                               20040422 DE 2002-10246063
                                                                 20021002
PΙ
     DE 10246063
                         A1
     ANSWER 12 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
     Method for plasma etching performance enhancement in semiconductor device
TI
     fabrication
                      KIND DATE APPLICATION NO.
                                                                 DATE
     PATENT NO.
    US 2004072443 A1 20040415 US 2002-295601 20021114 US 6833325 B2 20041221 US 2004072430 A1 20040415 US 2003-674675 20030929 WO 2004034445 A2 20040422 WO 2003-US31712 20031006 WO 2004034445 A3 20040812 WO 2004034445 B1 20040930
PΙ
        W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,
            CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH,
            GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR,
            LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NI, NO, NZ, OM,
            PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN,
            TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW
        RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY,
            KG, KZ, MD, RU, TJ, TM, AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES,
            FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR,
            BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG
    AU 2003282718 A1 20040504 AU 2003-282718 20031006
EP 1550153 A2 20050706 EP 2003-774602 20031006
            AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
            IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, SK
                                          US 2004-946181
     US 2005037624
                         A1
                               20050217
                                                                 20040920
L4
    ANSWER 13 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
TТ
     Method for etching photolithographic reticles
    PATENT NO. KIND DATE APPLICATION NO.
                                                               DATE
                                         -----
                                                                 -----
     -----
                       ---- ------
    JP 2004038154 A2 20040205 JP 2003-136222 20030514
PΙ
                        A1 20040415 US 2003-437729
     US 2004072081
    ANSWER 14 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
     Safety tires having good durability and riding comfort
ΤI
     PATENT NO. KIND DATE APPLICATION NO.
                                          _____
                        ----
                               -----
                               20030423 JP 2002-94474
PI
    JP 2003118311
                        A2
                                                                 20020329
    ANSWER 15 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
TI
     Silicon dioxide etching yield measurements with inductively coupled
     fluorocarbon plasmas
L4
    ANSWER 16 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
     Speed-of-sound, ideal-gas heat capacity, and second acoustic virial
TI
     coefficient for mixing refrigerant difluoroethane (HFC152a) +
     difluoromethane (HCFC22)
    ANSWER 17 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
TI
    Resistive plate chambers for muon detection at LHC
    ANSWER 18 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
TI
    Heat transfer fluids useable for cooling items, such as optical fibers
    PATENT NO. KIND DATE APPLICATION NO. DATE
    WO 2002074709
                        A1 20020926 WO 2002-EP3030
PΙ
                                                                20020314
        W: AU, BR, CN, IN, JP
        RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL,
            PT, SE, TR
    EP 1373153
                             20040102
                                         EP 2002-753572
                        A1
           AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
            IE, FI, CY, TR
                                                                 20020314
                                         CN 2002-806445
    CN 1496340
                        Α
                               20040512
```

TI

```
US 2004-874079
                                                            20040622
                       A1
                             20041118
    US 2004227125
                                       US 2005-130331
                                                             20050517
                       A1
                             20051006
    US 2005218371
    ANSWER 19 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Algorithmically Compressed Data and the Topological Conjecture for the
ΤI
    Inner-Core Electrons
    ANSWER 20 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Substrate cleaning apparatus and method
TT
                   KIND DATE APPLICATION NO.
                                                           DATE
                           -----
                     ----
                                       _____
    -----
    US 2002072016 A1 20020613 US 2000-737373
                                                            20001213
PI
    WO 2002049078 A2
WO 2002049078 A3
    US 6692903
                      B2 20040217
                             20020620 WO 2001-US48273
                                                            20011210
                      A3 20021024
        W: CN, JP, KR, SG
        RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL,
            PT, SE, TR
    ANSWER 21 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Hydrocarbon-based refrigerant mixture composition for replacing R-12 and
TI
    R-22 refrigerants
    PATENT NO.
                      KIND
                            DATE
                                     APPLICATION NO.
                                                           DATE
    ______
                      ----
                            -----
                                       -----
                                                            _____
                             20000705 KR 2000-17251
    KR 2000036953
                      Α
                                                            20000403
PΙ
    ANSWER 22 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
ΤI
    Formulations of mometasone and a bronchodilator for pulmonary
    administration
                                     APPLICATION NO.
                     KIND DATE
    PATENT NO.
                                                           -----
                     ----
                                       ______
    WO 2002011711
                      A2 20020214 WO 2001-US24093
                                                           20010801
PΙ
                      A3 20030227
B1 20040422
    WO 2002011711
WO 2002011711
        W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,
            CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH,
            GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR,
            LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, PL, PT,
            RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, UZ,
            VN, YU, ZA, ZW
        RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW, AM, AZ, BY, KG,
            KZ, MD, RU, TJ, TM, AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR,
            IE, IT, LU, MC, NL, PT, SE, TR, BF, BJ, CF, CG, CI, CM, GA, GN,
           GQ, GW, ML, MR, NE, SN, TD, TG
                AA 20020214
    CA 2417973
                                       CA 2001-2417973
                                                           20010801
    AU 2001078115
                      A5
                             20020218
                                      AU 2001-78115
                                                           20010801
                      A1 20020620 US 2001-920340
A2 20030521 EP 2001-956079
    US 2002076382
                      A1
    EP 1311294
           AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
            IE, SI, LT, LV, FI, RO, MK, CY, AL, TR
    US 2004198708
                       A1
                            20041007
                                     US 2004-824711
                                                           20040414
    ANSWER 23 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Detection of fluorine containing gas compounds
TI
    PATENT NO. KIND DATE APPLICATION NO.
    -----
                      ----
                                       -----
    JP 2002022725
                      A2
                            20020123 JP 2000-209708
                                                           20000711
PΤ
    JP 3640601
                       B2
                            20050420
    ANSWER 24 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
T.4
ΤI
    Additivity of the Correlation Energy in Some 3D Organic Molecules
L4
    ANSWER 25 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Fluorohydrocarbon etchant with selectivity for doped silicon dioxide over
TI
    undoped silicon dioxide and silicon nitride, processes which employ the
    etchant, and structures formed thereby
    PATENT NO. KIND DATE APPLICATION NO.
                                       -----
                                                            -----
    WO 2002003439
                      A2
                            20020110 WO 2001-US41275
PΙ
                                                            20010705
```

```
... 2002003439
WO 2002003439
                     A3
                            20020606
                     A3 20020606
C1 20020704
    W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,
    W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, UZ, VN, YU, ZA, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM

RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW, AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG
                     A2 20030402 EP 2001-956164
EP 1297564
                                                                20010705
        AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO, MK, CY, AL, TR
JP 2004503082
                      T2
                            20040129
                                      JP 2002-507425
                                                                 20010705
ANSWER 26 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Fabrication of electric circuits by reactive-gas etching of masked metal
layers on substrates
                                       APPLICATION NO.
PATENT NO. KIND
                            DATE
------
                   ----
                                         ______
                                                                 -----
WO 2001096955 A2 20011220 WO 2001-US19282
                                                                20010615
WO 2001096955
                    A3 20021128
    W: JP, US
    RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL,
        PT, SE, TR
                      A2 20030312 EP 2001-946420
EP 1290495
                                                                20010615
    R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
        IE, FI, CY, TR
                                      JP 2002-511020
US 2001-24958
JP 2004503829 T2
                            20040205
                                                                20010615
                    A1
US 2003003374
                            20030102
                                                                20011218
ANSWER 27 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
High-density plasma etching of carbon-based low-k materials in an
integrated circuit
PATENT NO. KIND
                            DATE APPLICATION NO.
                                                                DATE
-----
                    ----
                            -----
                                        _____
US 6284149
                    B1
                            20010904 US 1998-156956
                                                                19980918
ANSWER 28 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Flower-like capacitor structure for a memory cell
PATENT NO. KIND DATE APPLICATION NO.
                                                                DATE
                   ----
-----
                            _____
                                        -----
                                                                -----
US 6281542 B1 20010828 US 1999-249840 19990215
US 5973350 A 19991026 US 1998-60565 19980414
ANSWER 29 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Apparatus for providing ozonated process fluid and methods for using same
PATENT NO. KIND DATE APPLICATION NO. DATE
                   ----
-----
                                       -----
WO 2001040124 A1 20010607 WO 2000-US42449 20001201 WO 2001040124 C2 20020808
    W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN,
        CR, CU, CZ, DE, DK, DM, DZ, EE, ES, FI, GB, GD, GE, GH, GM, HR,
        HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT,
        LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NO, NZ, PL, PT, RO, RU,
        SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, UZ, VN, YU,
        ZA, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM
    RW: GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZW, AT, BE, CH, CY,
        DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, TR, BF,
        BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG
                            20020606 US 2000-727661 20001201
US 2002066717
                     A1
TW 490757
                     В
                            20020611
                                      TW 2000-89125686
                                                                20010108
ANSWER 30 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
Cooling agent
                                   APPLICATION NO. DATE
PATENT NO.
                   KIND DATE
-----
                   ----
                            -----
                                       ______
RU 2135541
                    C1
                            19990827 RU 1997-120359 19971210
```

L4 TI

PT

L4

TI

PΤ

L4

ΤI

PΙ

L4 TI

PΙ

L4

ΤI

ΡI

ANSWER 31 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4 Fluoroethane etchant with selectivity for doped silicon dioxide over TI undoped silicon dioxide and silicon nitride, processes which employ the etchant, and structures formed for semiconductor devices KIND DATE APPLICATION NO. PATENT NO. \_ \_ \_ \_ -----\_\_\_\_\_\_ \_\_\_\_\_\_ Α 20000912 US 1998-102152 19980622 PΙ US 6117791 B1 20030325 US 2000-625144 20000725 US 6537922 B1 20050405 US 2000-711324 20001113 US 6875371 20031030 US 2003-396164 20030325 **A1** US 2003203639 ANSWER 32 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4Evaluation of pentafluoroethane and 1,1-difluoroethane for a dielectric ΤI etch application in an inductively coupled plasma etch tool ANSWER 33 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN L4Topical sprays containing film-forming polymers TI PATENT NO. KIND DATE APPLICATION NO. DATE \_\_\_\_\_ ----------\_\_\_\_\_ \_ \_ \_ \_ 20000810 WO 2000-GB366 20000207 WO 2000045795 A2 PΙ 20010809 WO 2000045795 A3 W: AE, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CA, CH, CN, CR, CU, CZ, DE, DK, DM, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, TZ, UA, UG, US, UZ, VN, YU, ZA, ZW RW: GH, GM, KE, LS, MW, SD, SL, SZ, TZ, UG, ZW, AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE, BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG 20011020 IN 1999-B093 19990205 IN 186668 Α CA 2359640 AA 20000810 CA 2000-2359640 20000207 AU 2000024472 A5 20000825 AU 2000-24472 20000207 AU 759515 B2 20030417 BR 2000007997 Α 20011030 BR 2000-7997 20000207 20011107 EP 2000-902727 EP 1150661 A2 20000207 B1 20031022 EP 1150661 AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, SI, LT, LV, FI, RO T220021029 JP 2000-596915 20000207 JP 2002536319 NZ 2000-513208 20000207 NZ 513208 Α 20030530 E AT 2000-902**727** 20000207 AT 252380 20031115 Т 20040227 PT 2000-902**727** 20000207 PT 1150661 Т3 ES 2209812 20040701 ES 2000-902**727** 20000207

L4 ANSWER 34 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
TI Synthetic lubricating oil-Cl-3-hydrofluorocarbon refrigerant combinations
for low-temperature phase separation in refrigeration compressor units

20051108

20001221

20011002

20040408

20041028

B1

Α

Α

A1

A1

US 6962691

HK 1042043

PΙ

L4

ZA 2000005727

US 2004213744

NO 2001003815

US 2000-503843

ZA 2000-5727

NO 2001-3815

HK 2002-103295

US 2003-686517

20001017

20010803

20020502

20031016

PATENT NO. KIND DATE APPLICATION NO. DATE ---------WO 1999-US31118 WO 2000043464 A1 20000727 19991228 W: AU, CA RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE US 1999-236707 US 6374629 B1 20020423 19990125 CA 2360536 AA 20000727 CA 1999-2360536 19991228 EP 1153099 Α1 20011114 EP 1999-968**562** 19991228 EP 1153099 20040929 B1 AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, IE, FI AU 774378 20040624 AU 2000-25954 19991228 B2

ANSWER 35 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN

TI Variable load refrigeration system particularly for cryogenic temperatures

	PATENT NO.		DATE		
ΡI	US 6076372		20000620 20000731		19981230
	US 6076372 MX 9911766 ZA 9907869	Α	20000731	MX 1999-11766	19991215
	ZA 9907869	A	20000705	ZA 1999-7869	19991223
	CA 2293191 CA 2293191 TW 430733 EP 1016839	C	20040921	CA 1999-2293191	19991224
	CA 2293191	AA B	20000630	TW 1999-88123007	19991227
	EP 1016839	A2	20010421	EP 1999-126062	
	EP 1016839	A3	20001102		
	EP 1016839	B1	20030709		
				GB, GR, IT, LI, LU, NL,	SE, MC, PT,
	IE, SI, L JP 2000205675	T, LV, FI		JP 1999-373465	19991228
	TD 2679619	<b>B</b> 2	20050803		13331220
	BR 9905991	A A E	20000905	BR 1999-5991	19991228
	CN 1265462	Α	20000906	CN 1999-127429	19991228
	AT 244860	E	20030715	AT 1999-126062	19991228
	ES 2197568	T3	20040101	ES 1999-126062	19991228
	AU 9965541 Au 753979	B2	20000700	AU 1999-65541 US 2000-545670	10001200
	US 6426019	B1	20020730	US 2000-545670	20000407
	US 2003042463	A1	20030306	US 2002-2012 <b>87</b>	20020724
	US 6881354	B2	20050419		
L4 TI	ANSWER 36 OF 214 A process for dis	CAPLUS posal of	COPYRIGHT Halon 130	2006 ACS on STN 1 (CBrF3)	
L4	ANSWER 37 OF 214	CAPLUS	COPYRIGHT	2006 ACS on STN	
ΤĮ	Determination of	the skin	viscosity	of glass via fiber elon	gation
		~~~~			
L4 TI	ANSWER 38 OF 214 Conversion under chlorodifluoromet	hydrogen	of dichlo	rodifluoromethane and	
τ 4	ANCHED 20 OF 214	CADITIC	CODVDICUM	0006 700 - CMM	
L4				2006 ACS on STN	
TI				2006 ACS ON STN	
		e prevent	ion		
TI	Accidental releas  ANSWER 40 OF 214  Cooling agent com	e prevent CAPLUS position	ion COPYRIGHT	2006 ACS on STN	
TI L4	Accidental releas	e prevent CAPLUS position	ion COPYRIGHT		DATE
TI L4 TI	Accidental releas ANSWER 40 OF 214 Cooling agent com PATENT NO.	e prevent  CAPLUS  position  KIND	ion COPYRIGHT DATE	2006 ACS on STN  APPLICATION NO.	
TI L4	Accidental releas  ANSWER 40 OF 214 Cooling agent com PATENT NO WO 9910447	CAPLUS  CAPLUS  CAPLUS  CAPLUS  KIND  A1	ion COPYRIGHT DATE 19990304	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274	
TI L4 TI	Accidental releas  ANSWER 40 OF 214 Cooling agent com PATENT NO WO 9910447	e prevent  CAPLUS  position  KIND	ion COPYRIGHT DATE 19990304	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274	
TI L4 TI PI L4	Accidental release  ANSWER 40 OF 214 Cooling agent compatent No. WO 9910447 W: BY, CZ, H  ANSWER 41 OF 214	CAPLUS  Sposition  KIND  A1  SU, MD, PL  CAPLUS	ion  COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT	2006 ACS on STN  APPLICATION NO. WO 1997-RU274 US  2006 ACS on STN	
TI L4 TI PI	Accidental release  ANSWER 40 OF 214 Cooling agent compatent No. WO 9910447 W: BY, CZ, H  ANSWER 41 OF 214 Fixative vinyl acceptable	CAPLUS  MODERATE TO THE TENT OF THE TENT O	ion  COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274 US  2006 ACS on STN	19970826
TI L4 TI PI L4	Accidental release  ANSWER 40 OF 214 Cooling agent compatent No. WO 9910447 W: BY, CZ, H  ANSWER 41 OF 214 Fixative vinyl accepatent No.	CAPLUS  MODERATE TO THE TOTAL TO THE TOTAL	ion  COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274 US  2006 ACS on STN S  APPLICATION NO.	19970826 DATE
TI L4 TI PI L4 TI	Accidental release  ANSWER 40 OF 214 Cooling agent compatent NO. WO 9910447 W: BY, CZ, H  ANSWER 41 OF 214 Fixative vinyl accepatent NO.	CAPLUS DOSITION KIND A1 TU, MD, PL CAPLUS Setate tet KIND	ion  COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274 US  2006 ACS on STN S  APPLICATION NO.	19970826 DATE
TI L4 TI PI L4	Accidental release  ANSWER 40 OF 214 Cooling agent compatent NO. WO 9910447 W: BY, CZ, H  ANSWER 41 OF 214 Fixative vinyl accepatent NO. US 5830439 US 5872329	CAPLUS  ADDITION  CAPLUS	COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT  rapolymer  DATE  19981103	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  US 1997-857954  US 1998-34574	DATE 19970516
TI L4 TI PI L4 TI	Accidental release  ANSWER 40 OF 214 Cooling agent compatent NO. WO 9910447 W: BY, CZ, H  ANSWER 41 OF 214 Fixative vinyl accepatent NO. WO 5830439 US 5972329 WO 9851266	CAPLUS DOSITION KIND A1 TU, MD, PL CAPLUS DETAILS	DATE 19990304 , SK, UA, COPYRIGHT rapolymer DATE 19981103 19991026 19981119	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274 US  2006 ACS on STN  APPLICATION NO.  US 1997-857954 US 1998-34574 WO 1998-US5318	DATE 19970516
TI L4 TI PI L4 TI	Accidental release  ANSWER 40 OF 214 Cooling agent compatent NO. WO 9910447 W: BY, CZ, H  ANSWER 41 OF 214 Fixative vinyl accepatent No. WS 5830439 US 5972329 WO 9851266 WO 9851266	CAPLUS DOSITION KIND A1 TU, MD, PL CAPLUS DETAILS THE TENTY CAPLUS DETAILS TO A A A A A2 A3	DATE 19990304 , SK, UA, COPYRIGHT rapolymer DATE 19981103 19991026 19981119 19990218	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  US 1997-857954  US 1998-34574  WO 1998-US5318	DATE 19970516 19980304 19980318
TI L4 TI PI L4 TI	Accidental release  ANSWER 40 OF 214 Cooling agent compatent NO. WO 9910447 W: BY, CZ, H  ANSWER 41 OF 214 Fixative vinyl accepatent No. S830439 US 5972329 WO 9851266 WO 9851266 W: AL, AM, AM	CAPLUS DOSITION KIND A1 TU, MD, PL CAPLUS DETAILS	DATE 19990304 , SK, UA, COPYRIGHT rapolymer DATE 19981103 19991026 19981119 19990218 , BA, BB,	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  US 1997-857954  US 1998-34574  WO 1998-US5318  BG, BR, BY, CA, CH, CN,	DATE 19970516 19980304 19980318 CU, CZ, DE,
TI L4 TI PI L4 TI	Accidental release  ANSWER 40 OF 214 Cooling agent compatent NO. WO 9910447 W: BY, CZ, H  ANSWER 41 OF 214 Fixative vinyl accepatent No. US 5830439 US 5972329 WO 9851266 W: AL, AM, ADK, EE, E	CAPLUS DOSITION KIND A1 TU, MD, PL CAPLUS DETAILS BETTE TELL KIND A A A2 A3 AT, AU, AZ SS, FI, GB	DATE 19990304 , SK, UA, COPYRIGHT rapolymer DATE 19981103 19991026 19981119 19990218 , BA, BB, , GE, GH,	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  US 1997-857954  US 1998-34574  WO 1998-US5318  BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS,	DATE 19970516 19980304 19980318 CU, CZ, DE, JP, KE, KG,
TI L4 TI PI L4 TI	Accidental release  ANSWER 40 OF 214 Cooling agent compatent NO. WO 9910447 W: BY, CZ, H  ANSWER 41 OF 214 Fixative vinyl accepatent No. US 5830439 US 5972329 WO 9851266 W: AL, AM, ADK, EE, EKP, KR, K	CAPLUS DOSITION KIND A1 TU, MD, PL CAPLUS DETAILS BETTE TELL KIND A A A2 A3 A7, AU, AZ SS, FI, GB CZ, LC, LK	COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 19981119 19990218 , BA, BB, , GE, GH, , LR, LS,	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  US 1997-857954  US 1998-34574  WO 1998-US5318  BG, BR, BY, CA, CH, CN,	DATE 19970516 19980304 19980318 CU, CZ, DE, JP, KE, KG, MN, MW, MX,
TI L4 TI PI L4 TI	Accidental release  ANSWER 40 OF 214 Cooling agent compatent NO	CAPLUS  position  KIND   A1  TU, MD, PL  CAPLUS  etate tet  KIND   A  A  A  A2  A3  A7, AU, AZ  SS, FI, GB  EZ, LC, LK  DL, PT, RO  EZ, VN, YU	COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 19981119 19990218 , BA, BB, , GE, GH, , LR, LS, , RU, SD, , ZW, AM,	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  US 1997-857954  US 1998-34574  WO 1998-US5318  BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU,	DATE 19970826  DATE 19970516 19980304 19980318  CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM
TI L4 TI PI L4 TI	Accidental release  ANSWER 40 OF 214 Cooling agent compatent NO	CAPLUS  position  KIND   A1  TU, MD, PL  CAPLUS  etate tet  KIND   A  A  A2  A3  A7, AU, AZ  SS, FI, GB  CZ, LC, LK  PT, RO  IZ, VN, YU  EE, LS, MW	COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 19981119 19990218 , BA, BB, , GE, GH, , LR, LS, , RU, SD, , ZW, AM, , SD, SZ,	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  US 1997-857954  US 1998-34574  WO 1998-US5318  BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU, UG, ZW, AT, BE, CH, DE,	DATE 19970826  DATE 19970516 19980304 19980318  CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI,
TI L4 TI PI L4 TI	Accidental release  ANSWER 40 OF 214 Cooling agent compatent NO	CAPLUS  position  KIND   A1  TU, MD, PL  CAPLUS  etate tet  KIND   A  A  A2  A3  A7, AU, AZ  SS, FI, GB  EZ, LC, LK  PT, RO  IZ, VN, YU  EE, LS, MW  ER, IE, IT	COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 1998119 19990218 , BA, BB, , GE, GH, , LR, LS, , RU, SD, , ZW, AM, , SD, SZ, , LU, MC,	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  US 1997-857954  US 1998-34574  WO 1998-US5318  BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU, UG, ZW, AT, BE, CH, DE, NL, PT, SE, BF, BJ, CF,	DATE 19970826  DATE 19970516 19980304 19980318  CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI,
TI L4 TI PI L4 TI	Accidental release  ANSWER 40 OF 214 Cooling agent compatent NO	CAPLUS  position  KIND   A1  TU, MD, PL  CAPLUS  etate tet  KIND   A  A  A2  A3  A7, AU, AZ  SS, FI, GB  EZ, LC, LK  PT, RO  IZ, VN, YU  EE, LS, MW  ER, IE, IT  IL, MR, NE	DATE 19990304 , SK, UA, COPYRIGHT rapolymer DATE 19981103 19991026 1998119 19990218 , BA, BB, , GE, GH, , LR, LS, , RU, SD, , ZW, AM, , SD, SZ, , LU, MC, , SN, TD,	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  US 1997-857954  US 1998-34574  WO 1998-US5318  BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU, UG, ZW, AT, BE, CH, DE, NL, PT, SE, BF, BJ, CF, TG	DATE 19970826  19970826  19970516 19980304 19980318  CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI, CG, CI, CM,
TI L4 TI PI L4 TI	Accidental release  ANSWER 40 OF 214 Cooling agent compatent No	CAPLUS  position  KIND   A1  TU, MD, PL  CAPLUS  etate tet  KIND   A  A  A2  A3  A7, AU, AZ  SS, FI, GB  EZ, LC, LK  PT, RO  IZ, VN, YU  EE, LS, MW  ER, IE, IT  IL, MR, NE	DATE 19990304 , SK, UA, COPYRIGHT rapolymer DATE 19981103 19991026 1998119 19990218 , BA, BB, , GE, GH, , LR, LS, , RU, SD, , ZW, AM, , SD, SZ, , LU, MC, , SN, TD,	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  US 1997-857954  US 1998-34574  WO 1998-US5318  BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU, UG, ZW, AT, BE, CH, DE, NL, PT, SE, BF, BJ, CF,	DATE 19970826  19970826  19970516 19980304 19980318  CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI, CG, CI, CM,
TI L4 TI PI L4 TI .	Accidental release  ANSWER 40 OF 214 Cooling agent compatent No	CAPLUS  CAPLUS  A1  TU, MD, PL  CAPLUS	COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 1998119 19990218 , BA, BB, , GE, GH, , LR, LS, , RU, SD, , ZW, AM, , SD, SZ, , LU, MC, , SN, TD, 19981208  COPYRIGHT	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  US 1997-857954  US 1998-34574  WO 1998-US5318  BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU, UG, ZW, AT, BE, CH, DE, NL, PT, SE, BF, BJ, CF, TG  AU 1998-68659  2006 ACS on STN	DATE 19970826  DATE 19970516 19980304 19980318  CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI, CG, CI, CM, 19980318
TI L4 TI PI L4 TI .	Accidental release  ANSWER 40 OF 214 Cooling agent compatent No	CAPLUS CA	COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 19981119 19990218 , BA, BB, , GE, GH, , LR, LS, , RU, SD, , ZW, AM, , SD, SZ, , LU, MC, , SN, TD, 19981208  COPYRIGHT ctrics us	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  LIS 1997-857954  US 1998-34574  WO 1998-US5318  BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU, UG, ZW, AT, BE, CH, DE, NL, PT, SE, BF, BJ, CF, TG  AU 1998-68659  2006 ACS on STN ing fluorohydrocarbon ga	DATE 19970826  DATE 19970516 19980304 19980318  CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI, CG, CI, CM, 19980318
TI L4 TI PI L4 TI .	Accidental release  ANSWER 40 OF 214 Cooling agent compatent NO	CAPLUS CA	COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 19981103 19991026 1998119 19990218 , BA, BB, , GE, GH, , LR, LS, , RU, SD, , ZW, AM, , SD, SZ, , LU, MC, , SN, TD, 19981208  COPYRIGHT ctrics us rbon-oxyge	2006 ACS on STN  APPLICATION NO.  WO 1997-RU274  US  2006 ACS on STN  APPLICATION NO.  US 1997-857954  US 1998-34574  WO 1998-US5318  BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU, UG, ZW, AT, BE, CH, DE, NL, PT, SE, BF, BJ, CF, TG  AU 1998-68659  2006 ACS on STN ing fluorohydrocarbon gaen gas	DATE 19970826  DATE 19970516 19980304 19980318  CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI, CG, CI, CM, 19980318
TI L4 TI PI L4 TI .	Accidental release  ANSWER 40 OF 214 Cooling agent compatent No	CAPLUS CA	COPYRIGHT  DATE  19990304 , SK, UA,  COPYRIGHT rapolymer DATE  19981103 19991026 1998119 19990218 , BA, BB, , GE, GH, , LR, LS, , RU, SD, , ZW, AM, , SD, SZ, , LU, MC, , SN, TD, 19981208  COPYRIGHT ctrics us rbon-oxyge DATE	APPLICATION NO.  APPLICATION NO.  WO 1997-RU274  US  2006 ACS ON STN  APPLICATION NO.  US 1997-857954  US 1998-34574  WO 1998-US5318  BG, BR, BY, CA, CH, CN, GM, GW, HU, ID, IL, IS, LT, LU, LV, MD, MG, MK, SE, SG, SI, SK, SL, TJ, AZ, BY, KG, KZ, MD, RU, UG, ZW, AT, BE, CH, DE, NL, PT, SE, BF, BJ, CF, TG  AU 1998-68659  2006 ACS ON STN ing fluorohydrocarbon gaen gas  APPLICATION NO.	DATE 19970826  DATE 19970516 19980304 19980318  CU, CZ, DE, JP, KE, KG, MN, MW, MX, TM, TR, TT, TJ, TM DK, ES, FI, CG, CI, CM, 19980318  s, DATE

```
19980224 JP 1997-19971217 EP 1997-304035
                      A2
    JP 10056001
                                                           19970605
                     A2
                                                           19970610
    EP 813233
                      A3
    EP 813233
       R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
           IE, FI
    ANSWER 43 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Spray formulation for testing of smoke detectors
ΤI
    PATENT NO. KIND DATE APPLICATION NO. DATE
                     ----
                            _____
                                      ______
                                                           _____
    -----
                            19980728 US 1996-713058
    US 5785891
                                                           19960912
                      Α
PΙ
    ANSWER 44 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
TI
    Coolant agent composition
    PATENT NO. KIND DATE
                                     APPLICATION NO.
                                                          DATE
                           _____
                                      -----
                                                           _____
    _____
                     ____
                            19971210 RU 1996-104188
                                                           19960301
PΙ
    RU 2098445
                      C1
    ANSWER 45 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Method and apparatus for fluorine-assisted stripping and residue removal
TT
    PATENT NO. KIND DATE APPLICATION NO. DATE
                     --'--
                                     _____
                                                           _____
    -----
                     A1 19980402 WO 1997-US16886
                                                           19970924
PΙ
    WO 9814036
       W: JP, KR, US
       RW: AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE
                     A1 19981007 EP 1997-944360
                                                          19970924
       R: DE, FR, GB, IT, NL
                            20000208 JP 1998-515793
                      T2
                                                           19970924
    JP 2000501573
                                      US 1997-936548
                                                           19970924
    US 6082374
                      Α
                            20000704
    ANSWER 46 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
TI
    Palladium-assisted electrodehalogenation of 1,1,2-trichloro-1,2,2-
    trifluoroethane on lead cathodes combined with hydrogen diffusion anodes
    ANSWER 47 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Process for the reduction of chlorofluorocarbons and production of
    derivatives thereof in an electrolytic cell, cell for carrying out said
    reduction and process for removing the byproducts formed within the cell
    PATENT NO. KIND DATE APPLICATION NO. DATE
                            -----
                                      ______
                                                          _____
                     ----
                     A1 19970710 WO 1996-ES248
                                                          19961226
PΙ
    WO 9724162
       W: CA, US
       RW: AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE
    ES 2103207
                  A1 19970816 ES 1995-2533
                                                           19951228
    ES 2103207
                      B1
                            19980401
    EP 819448
EP 819448
                     A1
                            19980121
                                     EP 1996-941667
                                                           19961226
                      B1
                            20000517
       R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT,
           IE, FI
                            20000615
                                      AT 1996-941667
                                                           19961226
    AT 192939
                      E
                      T3
                            20001016
                                      ES 1996-941667
                                                          19961226
    ES 2148819
                                      US 1997-913389
    US 6068756
                          20000530
                                                          19971104
                      A
    ANSWER 48 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Large scale fluorine doped textured transparent conducting SnO2 films
ΤТ
    deposited by atmospheric pressure chemical vapor deposition
    ANSWER 49 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Smell-added refrigerant compositions for leakage detection
TТ
    PATENT NO. KIND DATE APPLICATION NO.
                                                          DATE
                     _ _ _ _
                            -----
    JP 08245952
                      A2
                            19960924 JP 1995-51647
                                                          19950313
PΙ
    ANSWER 50 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Evaluation of critical parameters of halohydrocarbons and its quality
TI
```

19981201

Α A2

US 5843847

codes

JP 10041274

US 1996-639388

19980213 JP 1997-112887

19960429

19970430

```
ANSWER 51 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
ΤI
    Single-phase aerosol antiperspirant composition
    PATENT NO. KIND DATE APPLICATION NO. DATE
WO 9618378 A2 19960620 WO 1995-US16286 19951214
                                                             -----
ΡI
        W: AU, BR, CA, CH, CN, DE, ES, FI, GB, JP, KR, NO, NZ, PL, PT, RO,
           RU, SE, UA, VN
        RW: AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE
                   A1 19960703 AU 1996-49618
    AU 9649618
    ANSWER 52 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Ab initio studies of fluorinated ethanes: electronic and energetic
ΤI
    properties and reactions with hydroxyl radicals
    ANSWER 53 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Dehydrofluorination, fluorination, and decomposition of fluorohydrocarbons
TI
    with phosphate catalysts
                KIND DATE APPLICATION NO.
                                                            DATE
    PATENT NO.
                                       -----
                     ----
    -----
    JP 08104656 A2 19960423 JP 1994-243024
                                                            19941006
PΙ
    ANSWER 54 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Preparation of a substrate having a fluoride-doped conductive coating
TI
                KIND DATE APPLICATION NO. DATE
    PATENT NO.
    US 5496583 A 19960305 US 1994-297400 19940829 WO 9606958 A1 19960307 WO 1995-US10854 19950828
ΡI
        W: AM, AT, AU, BB, BG, BR, BY, CA, CH, CN, CZ, DE, DK, EE, ES, FI,
            GB, GE, HU, IS, JP, KE, KG, KP, KR, KZ, LK, LR, LT, LU, LV, MD,
            MG, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, TJ,
            TM, TT
        RW: KE, MW, SD, SZ, UG, AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT,
            LU, MC, NL, PT, SE, BF, BJ, CF, CG, CI, CM, GA, GN, ML, MR, NE,
            SN, TD, TG
                             19960322
                                        AU 1995-34959
                                                             19950828
    AU 9534959
                       A1
    ANSWER 55 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Four-component aerosol compositions
TΙ
                                       APPLICATION NO. DATE
    PATENT NO. KIND DATE
                      A1 19960111 WO 1994-US7426 19940630
                      ----
    _____
    WO 9600564
PΙ
        W: AM, AT, AU, BB, BG, BR, BY, CA, CH, CN, CZ, DE, DK, ES, FI, GB,
            GE, HU, JP, KE, KG, KP, KR, KZ, LK, LU, LV, MD, MG, MN, MW, NL,
            NO, NZ, PL, PT, RO, RU, SD, SE, SI, SK, TJ, TT, UA, UZ, VN
        RW: AT, BE, CH, DE, DK, ES, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE,
            BF, BJ, CF, CG, CI, CM, GA, GN, ML, MR, NE, SN, TD, TG
                       A1
                            19960125 AU 1994-73206
    AU 9473206
    ANSWER 56 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
TI
    Aerosol detergent compositions with low toxicity for cleaning automotive
    brakes
                     KIND DATE APPLICATION NO.
    PATENT NO.
                     ----
                      A2
                             19951219 JP 1994-126602
PΙ
    JP 07331290
                                                            19940608
    ANSWER 57 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Infrared photochemical properties of sensitized SO2-O2 mixtures
ΤI
L4
    ANSWER 58 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
TI
    Energy-saving binary refrigerant mixtures without ozone layer depletion
    effect
    PATENT NO.
                     KIND DATE
                                     APPLICATION NO.
                            19950125 CN 1993-109083
PΙ
    CN 1097792
                      A
                                                            19930721
L4
    ANSWER 59 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
    Hair aerosol compositions containing polymers and dimethylether
ΤI
    PATENT NO. KIND DATE APPLICATION NO. DATE
                     ----
```

PI					
	EP 663203		·	EP 1994-4028 <b>7</b> 4	19941213
	EP 663203		010919		
	R: AT, BE, CH,				
	FR 2715064	A1 199		FR 1994-367	19940114
	FR 2715064	B1 199	960209		
	AT 205698	E 200		AT 1994-4028 <b>74</b>	19941213
	CA 2138481	AA 199	950715	CA 1994-2138481	19941219
	CA 2138481	C 200	20625		
	HU 71747			HU 1994-3827	19941229
	HU 218577		001028		
	PL 177758			PL 1994-306585	19941229
				KR 1994-40216	19941230
	KR 166391				
	BR 9500140			BR 1995-140	19950110
	CN 1113141			CN 1995-101243	19950113
	CN 1070358		10905		
	JP 08040847	A2 199	960213	JP 1995-4323	19950113
	JP 2834417	B2 199	981209		
	RU 2124351	C1 199	990110	RU 1995-100766	19950113
	US 6113923		00905	US 1995-3723 <b>95</b>	19950113
	00 01107-0				
L4	ANSWER 60 OF 214 C	ים חם פונום מי	/PTGHT 200	6 ACS on STN	
TI	Compositions and me				
11				APPLICATION NO.	DATE
	PATENT NO.			APPLICATION NO.	DAIL
ΡI	US 5391584			US 1993-275 <b>33</b>	19930308
	ZA 9201888	A 199	921230	ZA 1992-188 <b>8</b>	19920313
	ZA 9201895	A 199	921230	ZA 1992-189 <b>5</b>	19920313
	CN 1067435	A 199	21230	CN 1992-102 <b>958</b>	19920327
	KR 227876			KR 1992-5064	19920327
	US 5238970			US 1992-974353	19921110
	US 5240965			US 1992-974352	19921110
				US 1993-61007	19930514
	US 5356556				
	US 5368769			US 1993-67789	19930527
	CN 1133854			CN 1995-119832	19951114
	CN 1048995	B 200	000202		
L4	ANSWER 61 OF 214 C			6 ACS on STN	
L4 TI				6 ACS on STN thane-based refrigerat:	ing agents
			difluoroe		ing agents DATE
	Refrigerating appar	atus using KIND DAT	difluoroe	thane-based refrigerat:	
	Refrigerating appar PATENT NO.	atus using KIND DAT	difluoroe	thane-based refrigerat:	
TI	Refrigerating appar PATENT NO.	atus using KIND DAT	difluoroe	thane-based refrigerat: APPLICATION NO.	DATE
TI PI	Refrigerating appar PATENT NO.  JP 07027431	atus using KIND DAT  A2 199	difluoroe E  950127	thane-based refrigerat: APPLICATION NO	DATE
TI PI L4	Refrigerating appar PATENT NO.  JP 07027431  ANSWER 62 OF 214 C	Tatus using KIND DAT A2 199	difluoroe TE 950127 CRIGHT 200	thane-based refrigerat: APPLICATION NO	DATE  19930716
TI PI	Refrigerating appar PATENT NO. JP 07027431  ANSWER 62 OF 214 C Post treatment of a	ATUS USING KIND DAT A2 199 APLUS COPY COAted sub	difluoroe TE 950127 CRIGHT 200	thane-based refrigerat: APPLICATION NO	DATE  19930716
TI PI L4	Refrigerating appar PATENT NO.  JP 07027431  ANSWER 62 OF 214 Const treatment of a to remove residues	ATUS USING KIND DAT A2 199 APLUS COPY COATED SUB	difluoroe TE 250127 CRIGHT 200 Ostrate wi	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing except	DATE 19930716 cited halogen
TI PI L4	Refrigerating appar PATENT NO.  JP 07027431  ANSWER 62 OF 214 Const treatment of a to remove residues	ATUS USING KIND DAT A2 199 APLUS COPY COATED SUB	difluoroe TE 250127 CRIGHT 200 Ostrate wi	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc	DATE 19930716 cited halogen
TI PI L4 TI	Refrigerating appar PATENT NO.  JP 07027431  ANSWER 62 OF 214 OF Post treatment of a to remove residues PATENT NO.	AZ 199 CAPLUS COPY Coated sub	difluoroe TE 250127 RIGHT 200 Ostrate wi	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exception	DATE 19930716 cited halogen DATE
TI PI L4	Refrigerating appar PATENT NO.  JP 07027431  ANSWER 62 OF 214 OF	AZ 199 CAPLUS COPY Coated sub	difluoroe TE 250127 RIGHT 200 Ostrate wi	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc	DATE 19930716 cited halogen DATE
TI PI L4 TI	Refrigerating appart PATENT NO.  JP 07027431  ANSWER 62 OF 214 Composed to remove residues PATENT NO.  WO 9502472 W: JP, KR, US	ATUS USING KIND DAT A2 199 CAPLUS COPY COATED DAT A1 199	difluoroe TE 250127 RIGHT 200 estrate wi	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc APPLICATION NO.  WO 1994-US7751	DATE 19930716 cited halogen DATE 19940712
TI PI L4 TI	Refrigerating appar PATENT NO.  JP 07027431  ANSWER 62 OF 214 C Post treatment of a to remove residues PATENT NO.  WO 9502472 W: JP, KR, US RW: AT, BE, CH,	Atus using KIND DAT A2 199 CAPLUS COPY Coated sub KIND DAT A1 199 DE, DK, ES	difluoroe TE 250127 RIGHT 200 estrate wi TE 250126	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc APPLICATION NO.  WO 1994-US7751  GR, IE, IT, LU, MC, NI	DATE 19930716  cited halogen  DATE 19940712  G, PT, SE
TI PI L4 TI	Refrigerating appart PATENT NO.  JP 07027431  ANSWER 62 OF 214 Composed to remove residues PATENT NO.  WO 9502472 W: JP, KR, US RW: AT, BE, CH,	Atus using KIND DAT A2 199 CAPLUS COPY Coated sub KIND DAT A1 199 DE, DK, ES	difluoroe TE 250127 RIGHT 200 estrate wi TE 250126	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc APPLICATION NO.  WO 1994-US7751  GR, IE, IT, LU, MC, NI	DATE 19930716  cited halogen  DATE 19940712  G, PT, SE
TI PI L4 TI	Refrigerating appart PATENT NO.  JP 07027431  ANSWER 62 OF 214 Composed to remove residues PATENT NO.  WO 9502472 W: JP, KR, US RW: AT, BE, CH,	Atus using KIND DAT A2 199 CAPLUS COPY Coated sub KIND DAT A1 199 DE, DK, ES	difluoroe TE 250127 RIGHT 200 estrate wi TE 250126	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc APPLICATION NO.  WO 1994-US7751  GR, IE, IT, LU, MC, NI	DATE 19930716  cited halogen  DATE 19940712  G, PT, SE
TI PI L4 TI	Refrigerating appart PATENT NO.  JP 07027431  ANSWER 62 OF 214 Composed to remove residues PATENT NO.  WO 9502472 W: JP, KR, US RW: AT, BE, CH, EP 710161 R: DE	CAPLUS COPY COATED DATE  A2 199 CAPLUS COPY COATED DATE  KIND DATE  A1 199  DE, DK, ES  A1 199	difluoroe TE 250127 RIGHT 200 estrate wi TE 250126 S, FR, GB,	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc  APPLICATION NO.  WO 1994-US7751  GR, IE, IT, LU, MC, NI EP 1994-922123	DATE 19930716  cited halogen  DATE 19940712  G, PT, SE 19940712
TI PI L4 TI	Refrigerating appart PATENT NO.  JP 07027431  ANSWER 62 OF 214 Composed to remove residues PATENT NO.  WO 9502472 W: JP, KR, US RW: AT, BE, CH, EP 710161 R: DE	CAPLUS COPY COATED DATE  A2 199 CAPLUS COPY COATED DATE  KIND DATE  A1 199  DE, DK, ES  A1 199	difluoroe TE 250127 RIGHT 200 estrate wi TE 250126 S, FR, GB,	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc  APPLICATION NO.  WO 1994-US7751  GR, IE, IT, LU, MC, NI	DATE 19930716  cited halogen  DATE 19940712  G, PT, SE 19940712
PI L4 TI	Refrigerating appart PATENT NO.  JP 07027431  ANSWER 62 OF 214 Composed to remove residues PATENT NO.  WO 9502472 W: JP, KR, US RW: AT, BE, CH, EP 710161 R: DE JP 09502646	TATUS USING KIND DATE A2 199 CAPLUS COPY COATED SUB KIND DATE A1 199 DE, DK, ES A1 199 T2 199	difluoroe TE  950127 (RIGHT 200 estrate wi TE  950126 (3, FR, GB, 960508	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc  APPLICATION NO.  WO 1994-US7751  GR, IE, IT, LU, MC, NI EP 1994-922123  JP 1994-504652	DATE 19930716  cited halogen  DATE 19940712  G, PT, SE 19940712
TI PI L4 TI PI	Refrigerating appart PATENT NO.  JP 07027431  ANSWER 62 OF 214 Composed to remove residues PATENT NO.  WO 9502472 W: JP, KR, US RW: AT, BE, CH, EP 710161 R: DE JP 09502646  ANSWER 63 OF 214 Composed to the patent of the patent	TATUS USING KIND DATE A2 199 CAPLUS COPY COATED SUB KIND DATE A1 199 DE, DK, ES A1 199 T2 199	difluoroe TE  950127 (RIGHT 200 sstrate wi TE  950126 (S, FR, GB, 960508	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc  APPLICATION NO.  WO 1994-US7751  GR, IE, IT, LU, MC, NI EP 1994-922123  JP 1994-504652  6 ACS on STN	DATE 19930716  cited halogen  DATE 19940712  19940712
PI L4 TI	Refrigerating appart PATENT NO.  JP 07027431  ANSWER 62 OF 214 OF	TATUS USING KIND DATE A2 199 CAPLUS COPY COATED SUB KIND DATE A1 199 DE, DK, ES A1 199 T2 199	difluoroe TE  950127 (RIGHT 200 sstrate wi TE  950126 (S, FR, GB, 960508	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc  APPLICATION NO.  WO 1994-US7751  GR, IE, IT, LU, MC, NI EP 1994-922123  JP 1994-504652	DATE 19930716  cited halogen  DATE 19940712  19940712
TI PI L4 TI PI	Refrigerating appart PATENT NO.  JP 07027431  ANSWER 62 OF 214 OF	TAPLUS COPY TAPLUS COPY A1 199 TAPLUS COPY A1 199 TAPLUS COPY A1 199 TAPLUS COPY TAPLUS COPY TAPLUS COPY TAPLUS COPY	difluoroe TE 250127 (RIGHT 200) Strate wi TE 250126 S, FR, GB, 260508 (RIGHT 200) Onductive,	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc  APPLICATION NO.  WO 1994-US7751  GR, IE, IT, LU, MC, NI EP 1994-922123  JP 1994-504652  6 ACS on STN soluble pyrrole-3-cark	DATE 19930716  cited halogen  DATE 19940712  c, PT, SE 19940712  19940712  coxylic acid
TI PI L4 TI PI	Refrigerating appart PATENT NO.  JP 07027431  ANSWER 62 OF 214 OF	Tatus using KIND DAT A2 199 CAPLUS COPY COATED SUB KIND DAT A1 199 DE, DK, ES A1 199 T2 199 CAPLUS COPY CTICALLY CO	difluoroe TE 250127 RIGHT 200 estrate wi TE 250126 S, FR, GB, 260508 270318 RIGHT 200 enductive,	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc  APPLICATION NO.  WO 1994-US7751  GR, IE, IT, LU, MC, NI EP 1994-922123  JP 1994-504652  6 ACS on STN soluble pyrrole-3-cark  APPLICATION NO.	DATE 19930716  cited halogen  DATE 19940712  19940712  19940712  DOXYlic acid  DATE
TI PI L4 TI PI	Refrigerating appart PATENT NO.  JP 07027431  ANSWER 62 OF 214 OF	Tatus using KIND DAT A2 199 CAPLUS COPY COATED SUB KIND DAT A1 199 DE, DK, ES A1 199 T2 199 CAPLUS COPY CTICALLY CO	difluoroe TE 250127 RIGHT 200 estrate wi TE 250126 S, FR, GB, 260508 270318 RIGHT 200 enductive,	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc  APPLICATION NO.  WO 1994-US7751  GR, IE, IT, LU, MC, NI EP 1994-922123  JP 1994-504652  6 ACS on STN soluble pyrrole-3-cark  APPLICATION NO.	DATE 19930716  cited halogen  DATE 19940712  19940712  19940712  DOXYlic acid  DATE
TI PI L4 TI PI	Refrigerating appart PATENT NO.  JP 07027431  ANSWER 62 OF 214 OF	Tatus using KIND DAT A2 199 CAPLUS COPY COATED SUB KIND DAT A1 199 DE, DK, ES A1 199 T2 199 CAPLUS COPY CTICALLY CO	difluoroe TE 250127 RIGHT 200 estrate wi TE 250126 S, FR, GB, 260508 270318 RIGHT 200 enductive,	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc  APPLICATION NO.  WO 1994-US7751  GR, IE, IT, LU, MC, NI EP 1994-922123  JP 1994-504652  6 ACS on STN soluble pyrrole-3-cark  APPLICATION NO.	DATE 19930716  cited halogen  DATE 19940712  19940712  19940712  DOXYlic acid  DATE
PI L4 TI PI	Refrigerating appart PATENT NO.  JP 07027431  ANSWER 62 OF 214 OF	Tatus using KIND DAT A2 199 CAPLUS COPY COATED SUB KIND DAT A1 199 DE, DK, ES A1 199 T2 199 CAPLUS COPY CTICALLY CO	difluoroe TE 250127 RIGHT 200 estrate wi TE 250126 S, FR, GB, 260508 270318 RIGHT 200 enductive,	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc  APPLICATION NO.  WO 1994-US7751  GR, IE, IT, LU, MC, NI EP 1994-922123  JP 1994-504652  6 ACS on STN soluble pyrrole-3-cark  APPLICATION NO.	DATE 19930716  cited halogen  DATE 19940712  19940712  19940712  DOXYlic acid  DATE
PI L4 TI PI	Refrigerating appart PATENT NO.  JP 07027431  ANSWER 62 OF 214 OF	Tatus using KIND DAT A2 199 CAPLUS COPY COATED SUB KIND DAT A1 199 DE, DK, ES A1 199 T2 199 CAPLUS COPY CTICALLY CO	difluoroe TE 250127 RIGHT 200 estrate wi TE 250126 S, FR, GB, 260508 270318 RIGHT 200 enductive,	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc  APPLICATION NO.  WO 1994-US7751  GR, IE, IT, LU, MC, NI EP 1994-922123  JP 1994-504652  6 ACS on STN soluble pyrrole-3-cark	DATE 19930716  cited halogen  DATE 19940712  19940712  19940712  DOXYlic acid  DATE
PI L4 TI PI	Refrigerating appart PATENT NO.  JP 07027431  ANSWER 62 OF 214 OF	TATUS USING KIND DATE A2 199 CAPLUS COPY COATED SUB KIND DATE A1 199 DE, DK, ES A1 199 T2 199 CAPLUS COPY CTICALLY	difluoroe TE  950127 (RIGHT 200 strate wi TE  950126 3, FR, GB, 960508 970318 (RIGHT 200 onductive, TE 	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc  APPLICATION NO.  WO 1994-US7751  GR, IE, IT, LU, MC, NI EP 1994-922123  JP 1994-504652  6 ACS on STN soluble pyrrole-3-cark  APPLICATION NO.  JP 1992-180695	DATE 19930716  cited halogen  DATE 19940712  19940712  19940712  DOXYlic acid  DATE
PI L4 TI PI L4 TI	Refrigerating appart PATENT NO.  JP 07027431  ANSWER 62 OF 214 OF POST TREATMENT OF A TO THE PROPERTY OF THE P	TATUS USING KIND DATE A2 199 CAPLUS COPY COATED SUB KIND DATE A1 199 DE, DK, ES A1 199 T2 199 CAPLUS COPY CITICALLY COPY CAPLUS COPY	difluoroe TE  950127 (RIGHT 200 strate wi TE  950126 3, FR, GB, 960508 (RIGHT 200 onductive, TE  940726 (00327 (RIGHT 200)	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc  APPLICATION NO.  WO 1994-US7751  GR, IE, IT, LU, MC, NI EP 1994-922123  JP 1994-504652  6 ACS on STN soluble pyrrole-3-cark  APPLICATION NO.  JP 1992-180695  6 ACS on STN	DATE 19930716  cited halogen  DATE 19940712  19940712  19940712  DOXYlic acid  DATE
PI L4 TI PI L4 TI	Refrigerating appart PATENT NO.  JP 07027431  ANSWER 62 OF 214 OF POST TREATMENT OF THE PROPERTY NO.  WO 9502472  W: JP, KR, US  RW: AT, BE, CH, EP 710161  R: DE  JP 09502646  ANSWER 63 OF 214 OF Manufacture of elected ester polymers PATENT NO.  JP 06206986  JP 3024867  ANSWER 64 OF 214 OF TESTING agents for	ALUS COPY TAPLUS COPY TAPLUS COPY ALL 199  ALL 1	difluoroe TE 250127 (RIGHT 200) Strate wi TE 250126 S, FR, GB, 260508 (RIGHT 200) Onductive, TE 240726 (200327 (RIGHT 200) Strate wi	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc  APPLICATION NO.  WO 1994-US7751  GR, IE, IT, LU, MC, NI EP 1994-922123  JP 1994-504652  6 ACS on STN soluble pyrrole-3-cark  APPLICATION NO.  JP 1992-180695  6 ACS on STN their manufacture	DATE 19930716  cited halogen  DATE 19940712  c, PT, SE 19940712  19940712  coxylic acid  DATE 19920708
PI L4 TI PI L4 TI	Refrigerating appart PATENT NO.  JP 07027431  ANSWER 62 OF 214 OF	TAPLUS COPY TAPLUS COPY A1 199 TAPLUS COPY A1 199 TAPLUS COPY A1 199 TAPLUS COPY TAPLUS CO	difluoroe TE 950127  (RIGHT 200 estrate wi TE 950126  G, FR, GB, 960508  (RIGHT 200 enductive, TE 940726 00327  (RIGHT 200 etors and TE	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc  APPLICATION NO.  WO 1994-US7751  GR, IE, IT, LU, MC, NI EP 1994-922123  JP 1994-504652  6 ACS on STN soluble pyrrole-3-cark  APPLICATION NO.  JP 1992-180695  6 ACS on STN their manufacture APPLICATION NO.	DATE 19930716  cited halogen  DATE 19940712  c, PT, SE 19940712  19940712  coxylic acid  DATE 19920708
PI L4 TI PI L4 TI PI L4 TI	Refrigerating appart PATENT NO.  JP 07027431  ANSWER 62 OF 214 OF POST TREATMENT OF ATTENT NO.  WO 9502472  W: JP, KR, US  RW: AT, BE, CH, EP 710161  R: DE  JP 09502646  ANSWER 63 OF 214 OF ATTENT NO.  JP 06206986  JP 3024867  ANSWER 64 OF 214 OF ATTENT NO.  PATENT NO.  PATENT NO.  PATENT NO.  PATENT NO.	TATUS USING KIND DATE A2 199 CAPLUS COPY COATED SWA KIND DATE A1 199 DE, DK, ES A1 199 T2 199 CAPLUS COPY CTICALLY COPY STORY COPY S	difluoroe EE 250127 (RIGHT 200 strate wi EE 250126 S, FR, GB, 260508 (RIGHT 200 onductive, EE 240726 000327 (RIGHT 200 stors and EE	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc  APPLICATION NO.  WO 1994-US7751  GR, IE, IT, LU, MC, NI EP 1994-922123  JP 1994-504652  6 ACS on STN soluble pyrrole-3-cark  APPLICATION NO.  JP 1992-180695  6 ACS on STN their manufacture APPLICATION NO.	DATE 19930716  cited halogen  DATE 19940712  c, PT, SE 19940712  19940712  coxylic acid  DATE 19920708
PI L4 TI PI L4 TI	Refrigerating appart PATENT NO.  JP 07027431  ANSWER 62 OF 214 OF POST TREATMENT OF ATTENT NO.  WO 9502472  W: JP, KR, US  RW: AT, BE, CH, EP 710161  R: DE  JP 09502646  ANSWER 63 OF 214 OF ATTENT NO.  JP 06206986  JP 3024867  ANSWER 64 OF 214 OF ATTENT NO.  PATENT NO.  PATENT NO.  PATENT NO.  PATENT NO.	TATUS USING KIND DATE A2 199 CAPLUS COPY COATED SWA KIND DATE A1 199 DE, DK, ES A1 199 T2 199 CAPLUS COPY CTICALLY COPY STORY COPY S	difluoroe EE 250127 (RIGHT 200 strate wi EE 250126 S, FR, GB, 260508 (RIGHT 200 onductive, EE 240726 000327 (RIGHT 200 stors and EE	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc  APPLICATION NO.  WO 1994-US7751  GR, IE, IT, LU, MC, NI EP 1994-922123  JP 1994-504652  6 ACS on STN soluble pyrrole-3-cark  APPLICATION NO.  JP 1992-180695  6 ACS on STN their manufacture APPLICATION NO.	DATE 19930716  cited halogen  DATE 19940712  c, PT, SE 19940712  19940712  coxylic acid  DATE 19920708
PI L4 TI PI L4 TI PI L4 TI	Refrigerating appart PATENT NO.  JP 07027431  ANSWER 62 OF 214 OF POST TREATMENT OF ATTENT NO.  WO 9502472  W: JP, KR, US  RW: AT, BE, CH, EP 710161  R: DE  JP 09502646  ANSWER 63 OF 214 OF ATTENT NO.  JP 06206986  JP 3024867  ANSWER 64 OF 214 OF ATTENT NO.  PATENT NO.  PATENT NO.  PATENT NO.  PATENT NO.	TATUS USING KIND DATE A2 199 CAPLUS COPY COATED SWA KIND DATE A1 199 DE, DK, ES A1 199 T2 199 CAPLUS COPY CTICALLY COPY STORY COPY S	difluoroe EE 250127 (RIGHT 200 strate wi EE 250126 G, FR, GB, 260508 (RIGHT 200 onductive, EE 240726 (200327 (RIGHT 200) stors and EE 240323	thane-based refrigerat: APPLICATION NO.  JP 1993-176804  6 ACS on STN th a gas containing exc  APPLICATION NO.  WO 1994-US7751  GR, IE, IT, LU, MC, NI EP 1994-922123  JP 1994-504652  6 ACS on STN soluble pyrrole-3-cark  APPLICATION NO.  JP 1992-180695  6 ACS on STN their manufacture APPLICATION NO.  CN 1993-119728	DATE 19930716  cited halogen  DATE 19940712  c, PT, SE 19940712  19940712  coxylic acid  DATE 19920708

TI	Substance separation gas-mixture flows			a pulsed IR laser radia	ation on
L4 TI	ANSWER 66 OF 214 Manufacture of the PATENT NO.	rmonlact	ic polyecter	forme by extrusion	DATE
ΡI	JP 06145404 JP 2801483	A2 B2	19940524 19980921	APPLICATION NO.  JP 1992-317764	19921102
L4 TI	dimensional stabil	em for p ity KIND	preparation o	f rigid polyurethane for APPLICATION NO.	DATE
ΡI	DE 4303887	A1	19940421	DE 1993-4303887	19930210
L4 TI	ANSWER 68 OF 214 Gaseous doping of PATENT NO.	tungster	n oxide	06 ACS on STN APPLICATION NO.	DATE
PI	US 5324537	A	19940628	US 1993-86796	19930706
L4 TI	ANSWER 69 OF 214 (Hydrofluorocarbon static magnetron			06 ACS on STN icon dioxide etch in a	n axisymmetric
L4 TI	ANSWER 70 OF 214 Manufacture of semi PATENT NO.	iconduct KIND	or devices DATE	06 ACS on STN APPLICATION NO.	DATE
ΡI				JP 1992-1799 <b>93</b>	
L4 TI	ANSWER 71 OF 214 OMANUFACTURE OF SEM	iconduct KIND	cor device by DATE	plasma etching APPLICATION NO.	DATE
ΡI	JP 06021016	A2	19940128	JP 1992-174114	19920701
L4 TI	ANSWER 72 OF 214 (Manufacture of flem PATENT NO.	xible po KIND	olyurethane f DATE	06 ACS on STN oams having low density APPLICATION NO.	DATE
PI				JP 1992-134451	
L4 TI	PATENT NO.	osol com KIND	mposition wit DATE	h high solid content APPLICATION NO.	DATE
PI	CA 2093781 AU 9336751 AU 671104 EP 570085	AA A1 B2 A2	19931017 19931021 19960815 19931118	CA 1993-2093781 AU 1993-36751 EP 1993-250104	19930408 19930406
	BR 9301551 ZA 9302658	, DE, DE A A A	19931019 19941015 19970225	, IE, IT, LI, <b>LU, NL,</b> 8 BR 1993-1551 ZA 1993-2658 US 1994-2381 <b>95</b>	19930415 19930415
L4 TI		gas-chro	omatographic	06 ACS on STN retention parameters for physicochemical charact	
L4 TI	ANSWER 75 OF 214 O Stabilized polyoxyo PATENT NO.	alkylene	glycols	06 ACS on STN APPLICATION NO.	DATE
ΡI	WO 9217563	A1	19921015	WO 1992-US2148	19920318

```
PL, RO, RU, SD
       RW: AT, BE, BF, BJ, CF, CG, CH, CI, CM, DE, DK, ES, FR, GA, GB, GN,
          GR, IT, LU, MC, ML, MR, NL, SE, SN, TD, TG
                                AU 1992-17754
                                                  19920318
                       19921102
                    A1
   AU 9217754
   ANSWER 76 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
   Working fluids
TT
                                APPLICATION NO. DATE
    PATENT NO.
                   KIND DATE
                  ----
                                 ______
                                                   -----
    -----
    JP 05117646
                   A2
                        19930514 JP 1991-281038 19911028
PΙ
   ANSWER 77 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
   Working fluids
ΤI
                                APPLICATION NO. DATE
    PATENT NO.
                   KIND DATE
                  ----
                                 _____
    _____
                        19930126 JP 1991-171032
   JP 05017743
                   A2
                                                   19910711
PΤ
   ANSWER 78 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
   Working fluids
TI
                                APPLICATION NO. DATE
                   KIND DATE
    PATENT NO.
                                 -----
                                                   -----
    -----
                  ----
                   A2 19930126 JP 1991-171035 19910711
   JP 05017746
PΙ
   ANSWER 79 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Working fluids
TI
                                APPLICATION NO. DATE
    PATENT NO.
                   KIND DATE
                                 _____
                                                   -----
    ----<del>-----</del>
                  ____
                   A2 19930126 JP 1991-172368 19910712
PΙ
   JP 05017748
   ANSWER 80 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
   Working fluids
TT
                               APPLICATION NO. DATE
   PATENT NO.
                  KIND DATE
                                                  -----
                                _____
    ______
                  ----
                   A2 19930126 JP 1991-172371
   JP 05017751
                                                  19910712
PΙ
   ANSWER 81 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
   Working fluids
TI
                                APPLICATION NO. DATE
   PATENT NO.
                  KIND DATE
                  ----
                                 -----
                                                   _____
   JP 05017755
                   A2 19930126 JP 1991-172375
                                                  19910712
PΙ
   ANSWER 82 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
   Working fluids PATENT NO.
ΤI
                  KIND DATE APPLICATION NO. DATE
                                                   -----
                  ----
                                 ______
PI JP 05017758
                   A2 19930126 JP 1991-172378
                                                  19910712
   ANSWER 83 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
T.4
   Prediction of refrigerant thermodynamic properties by equations of state:
TI
   vapor liquid equilibrium behavior of binary mixtures
   ANSWER 84 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
   Crosslinked polyolefin foaming compositions
TI
   PATENT NO. KIND DATE APPLICATION NO. DATE
                                 -----
                  ----
                   A2 19920602 JP 1990-283331
ΡI
   JP 04159339
                                                  19901023
   ANSWER 85 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
T.4
TΤ
   Performance-oriented packaging standards; changes to classification,
   hazard communication, packaging and handling requirements based on UN
   standards and agency initiative
   ANSWER 86 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
   Manufacture of expandable vinylidene chloride resin particles
TI
   PATENT NO. KIND DATE APPLICATION NO. DATE
                  ----
                  A2 19911002 JP 1990-17733 19900130
ΡI
   JP 03223346
```

W: AU, BB, BG, BR, CA, CS, FI, HU, JP, KP, KR, LK, MG, MN, MW, NO,

L4 TI	ANSWER 87 OF 214 Multivariate mode haloalkanes with	ling of	the rate co	onstant of the gas-phase	e reaction of
L4 TI		CAPLUS de polyt	COPYRIGHT	2006 ACS on STN ldings for thermal insu	lators of
	refrigerators PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI				JP 1990-17732	
L4 TI	ANSWER 89 OF 214 Preparation of the PATENT NO.	ermally KIND	insulating DATE	urethane foams APPLICATION NO.	DATE
ΡI	JP 03137139	A2	1 <b>9</b> 910611	JP 1989-276342	19891023
L4	ANSWER 90 OF 214	CAPLUS	COPYRIGHT	2006 ACS on STN	
TI	Working fluids PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI		A2	19910927	JP 1990-242 <b>13</b> 1	
L4 TI		ering sa	afety data	2006 ACS on STN of the material pair R1: onventional refrigerants	
L4 TI	ANSWER 92 OF 214 Working fluids				
	PATENT NO.	KIND		APPLICATION NO.	
ΡI	JP 03170583 US 5433879	A2 A	19910724 19950718	JP 1989-311149 US 1993-125146	19891130 19930923
L4 TI	ANSWER 93 OF 214 Working fluids			_	
	PATENT NO.		DATE	APPLICATION NO.	
ΡI	JP 03168271	A2	19910722	JP 1989-3096 <b>52</b>	19891129
L4 TI	ANSWER 94 OF 214 Working fluids				
	PATENT NO.	KIND		APPLICATION NO.	
PI	JP 03170593	A2	<b>19</b> 910724	JP 1989-311164	19891130
L4 TI	ANSWER 95 OF 214 Working fluids	CAPLUS	COPYRIGHT	2006 ACS on STN	
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE 
PI		A2	19910724	JP 1989-3111 <b>63</b> US 1993-1251 <b>46</b>	
L4 TI	ANSWER 96 OF 214 Working fluids	CAPLUS	COPYRIGHT	2006 ACS on STN	
11	PATENT NO.	KIND		APPLICATION NO.	
PI	JP 03170590 JP 2580349 US 5304319	A2 B2	19910724 19970212	JP 1989-311160 US 1992-839700	19891130 19920224
T 4					17720227
L4 TI	ANSWER 97 OF 214 Working fluids PATENT NO.				DATE
DΤ					

PI JP 03170589 A2 19910724 JP 1989-311159 19891130

ANSWER 98 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN

L4

а

TI	Working fluids PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 03168261		19910722	JP 1989-309640	19891129
L4 TI	ANSWER 99 OF 214 Working fluids	CAPLUS	COPYRIGHT 2	006 ACS on STN	
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI				JP 1989-309669	
L4 TI	ANSWER 100 OF 214 Working fluids			2006 ACS on STN	
	PATENT NO.			APPLICATION NO.	DATE
PI				JP 1989-3096 <b>72</b>	19891129
L4 TI	ANSWER 101 OF 214 Apparatus for preplayer depletion			2006 ACS on STN foaming solutions with	out ozone
	PATENT NO.	KIND 		APPLICATION NO.	
ΡI		A2	19910626	JP 1989-289729	19891106
L4	ANSWER 102 OF 214				
TI	Apparatus for many PATENT NO.			urethane solutions APPLICATION NO.	DATE
ΡI	JP 03150108 JP 2706991	A2 B2	19910626 19980128	JP 1989-289728	19891106
L4 TI	ANSWER 103 OF 214 Semiempirical calc silicon inner core	culation	of ESCA shi	fts in oxygen, nitrogen	, fluorine and
L4 TI	ANSWER 104 OF 214 Aerosol composition				
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE 
PI	EP 423695 EP 423695	A2 A3	19910424 19911002	EP 1990-119769	19901015
	R: AT, BE, CI	H, DE, DE	C, ES, FR, G	B, GR, IT, LI, NL, SE	
				AU 1990-64634	19901015
	NO 9004492 CA 2027952	A NN	19910422		19901017 19901018
	JP 03255023	A2	19911113	JP 1990-281690	19901019
	US 5378451	A	19950103	CA 1990-2027 <b>952</b> JP 1990-281690 US 1993-126747	19930927
L4	ANSWER 105 OF 214				
TI	PATENT NO.	KIND	DATE		DATE
DT				TD 1000 210520	
ΡI	EP 497023	A1	19910409	JP 1989-218530 EP 1991-3007 <b>93</b>	19910131
	R: DE, FR, GI US 5110408		19920505	US 1991-6582 <b>54</b>	19910220
L4 TI	PATENT NO.	gid polyu KIND	rethane foar DATE	ms with low th <mark>ermal con</mark> d	DATE
PI	EP 421269 EP 421269 EP 421269 EP 421269	A2 A3 B1 B2	19910410 19910904 19960110 20020502	EP 1990-118532	19900927
	R: AT, BE, CI DE 3933335	A, DE, DK Al		B, IT, LI, NL, <b>SE</b> DE 1989-3933 <b>335</b>	

	US 5096933	Α	19920317	US 1990-5771 <b>74</b>	19900904
	US 5096933		19960326		
	CA 2024714	AA	19910407	CA 1990-2024 <b>714</b>	19900906
	CA 2024714	C E	19980623	3	1000000
	AT 132882	E T3	19960115	AT 1990-118532	
			19960316	ES 1990-118532	
	JP 03152160	A2	19910628 20011009	JP 1990-2665 <b>73</b>	19901005
	JP 3216646 KR 173981	B2 B1		KR 1990-15963	19901006
	KR 173901	БI	19990401	IX 1990-19909	13301000
L4	ANSWER 107 OF 214	CAPLUS	COPYRIGHT	2006 ACS on STN	
TI	Working fluid				
	PATENT NO.	KIND	DATE		DATE
ΡI			19910605	EP 1990-122653	19901127
		B1	19940803		
	R: DE, FR, GB	7.7	19910724	JP 1989-311153	19891130
	JP 03170584 JP 2532695	A2 B2	19910724	JP 1989-311153	19091130
	JP 03170587			JP 1989-311156	19891130
	JP 2532696		19960911	01 1909 311130	15051150
	01 2332030	22	10000011		
L4	ANSWER 108 OF 214	CAPLUS	COPYRIGHT	2006 ACS on STN	
TI	Working fluid				
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	EP 430171			EP 1990-122654	19901127
	EP 430171	B1	19931006		
	R: DE, FR, GB		10010705	TD 1000 211166	10001120
	JP 03172384 JP 2532697	A2 B2	19910725 19960911	JP 1989-3111 <b>66</b>	19891130
	JP 03172386	A2	19910725	JP 1989-311168	19891130
	JP 2548412		19961030	OF 1909-311100	19891130
	01 2010112		1330100		
L4	ANSWER 109 OF 214	CAPLUS	COPYRIGHT	2006 ACS on STN	
TI	Catalytic hydrodec	nlorinat	ion of fred	on 113, (CFC 113, CCl2FC	ClF2)
L4	ANSWER 110 OF 214				
TI				enhanced sputtering of	
	PATENT NO.	KIND		APPLICATION NO.	
ΡI	WO 9010303			WO 1990-US677	
	WO 9010303		19901018		13300200
	W: JP, KP				
	RW: AT, BE, CH	, DE, DK	, ES, FR, C	BB, IT, LU, NL, SE	
	US 5089746	Α	19920218	US 1989-3115 <b>04</b>	19890214
L4	ANSWER 111 OF 214				
TI				ight metal fluorides	D
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	EP 400796	71	19901205	EP 1990-304073	19900417
PI	BB 400506	R1	19901205	EP 1990-304073	19900417
	R: DE. FR. GB	51	10040010		
	CA 2015802	AA	19901130	CA 1990-2015 <b>802</b>	19900501
	JP 03017601	A2	19910125	JP 1990-139560	19900529
	US 5208101	Α	19930504	CA 1990-2015802 JP 1990-139560 US 1991-723992	19910701
L4					
TI				ne resin laminar foams	
	PATENT NO.	KIND		APPLICATION NO.	
דמ			19900510		
ΡI	JP 06045719	AZ RA	19940616	JP 1988-2744 <b>31</b>	12881101
	OF 00043/13	73.4	エンンゼロロエコ		
L4	ANSWER 113 OF 214	CAPLUS	COPYRIGHT	2006 ACS on STN	
11·4	121011211 110 01 211			2000 11CD OII DIN	

ANSWER 113 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN Laser induced nonstationary processes in gaseous mixtures through porous media

L4	ANSWER 114 OF 214	CAPLUS	COPYRIGHT 2	2006 ACS on STN	
TI	Combining a blowin polyurethane foam			st one liquid reaction	component in
	PATENT NO.	KIND	DATE	APPLICATION NO.	
ΡI	DE 3819630	A1	19891214	DE 1988-3819630	19880609
	EP 345580	A2	19891213	DE 1988-3819630 EP 1989-109610	19890527
	EP 345580	A3	19900926		
	R: AT, BE, CH	, DE, ES	, FR, GB, IT	r, LI, NL, SE	
	JP 02039921	A2	19900208	JP 1989-143203	19890607
L4	ANSWER 115 OF 214				
$\mathtt{TI}$	Heat pumps with fl				
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	JP 01200153	A2	19890811	JP 1988-25011	19880204
L4	ANSWER 116 OF 214	CADLIIG	COPVETCHT 2	2006 ACS on STN	
TI				up VIII element-zeolite	catalvsts for
	aromatic compound			r / I I I I I I I I I I I I I I I I I I	7
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
DΤ				ED 1000 110621	
ΡI	EP 316727 EP 316727		19890524	EP 1988-118621	19881109
	R: BE, CH, DE			. SE	
	US 4937215	, 1R, OD A	19900626	US 1988-2566 <b>97</b>	19881012
				CA 1988-580661	
				JP 1988-28 <b>0348</b>	
L4	ANSWER 117 OF 214				
TI	Pyrolytically coat PATENT NO.	ed piate KIND	glass and it DATE	a DDITCATION NO	DATE
	PATENT NO.	KIND	DAIE	APPLICATION NO.	DAIL
ΡI	DE 3823089	A1		DE 1988-3823089	19880707
	GB 2206878	A1	19890118	GB 1987-16388	19870711
	GB 2206878		19910717		
	ES 2006972	A6	19890516	ES 1988-1782 BE 1988-683	19880608
	BE 1002216	A4	19901016	BE 1988-683	19880615
				FR 1988-8210	19880616
	FR 2617833 AT 8801725	A BI	19920417	AT 1988-1725	19880704
		A		NL 1988-1713	19880707
	CH 675416	A	19900928	CH 1988-2595	19880707
	SE 8802578	A	19890112	SE 1988-25 <b>78</b>	19880708
	SE 465921	В	19911118		
	SE 8802578 SE 465921 SE 465921	C	19920312		
	JP 01033033	A2	19890202	JP 1988-170751	19880708
L4	ANSWER 118 OF 214	CAPLUS	COPYRIGHT 2	2006 ACS on STN	
TI	Multilayer heat in				
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI				JP 1986-297088	
	01 00117110	112	17000011	01 1300 13700	17001111
L4	ANSWER 119 OF 214				
ΤΙ	aquatic environmen		ctrochemical	sensors from biofouli	ng in an
			DATE	APPLICATION NO	DATE
	PATENT NO.			APPLICATION NO.	
ΡI	US 4763537	Α	19880816	US 1986-941 <b>774</b>	19861215
L4	ANSWER 120 OF 214	CAPLITE	СОБЛЕТСНА 3	2006 ACS on STN	•
ΤI				ows through capillaries	
L4	ANSWER 121 OF 214			006 ACS on STN	
TI	Aerosol waterproof				22.55
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡĪ				US 1985-807 <b>488</b>	

	GB 2202740	המ	19881005	GB 1987-7617	19870331
	GB 2202740			GB 1707 7017	15070331
T 4	AVOURD 100 OF 014	CA DI IIO	CODVIDENT	OOOC ACC on CON	
L4 TI	ANSWER 122 OF 214 Improvement of the			nce of bottles by su	rface treatment
	_				
L4 TI	ANSWER 123 OF 214 Manufacture of hol			2006 ACS on STN	
11	PATENT NO.	KIND	DATE	APPLICATION NO.	
DT		7.7		JP 1985-255018	
ΡI	UP 6211/613	AZ	19870329	GP 1903-255010	17031113
L4	ANSWER 124 OF 214				
TI	Laser action on ga	s mixtur	re flows thr	ough metal capillari	es
L4	ANSWER 125 OF 214		COPYRIGHT	2006 ACS on STN	
TI	Silica film etchin PATENT NO.		DATE	APPLICATION NO.	DATE
ΡI	JP 61251138	A2	19861108	JP 1985-93024	19850430
L4	ANSWER 126 OF 214				
TI	Effect of laser ra capillaries in a t			age of resonan <mark>ce mol</mark> e	ecules through
	•		Ā		
L4	ANSWER 127 OF 214 Semiconductor devi		COPYRIGHT	2006 ACS on STN	
TI		KIND	DATE	APPLICATION NO.	DATE
				TD 1004 050542	10041100
ΡI	JP 60143633 JP 61004179	A2 B4	19850729 19860207	JP 1984-250543	19841129
L4 TI	ANSWER 128 OF 214 Nonflammable aeros				
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PI	US 4536323	 2		US 1983-5086 <b>43</b>	
	CA 1205349	A1	19860603	CA 1984-457246 AU 1984-33083	19840622
					19840917
	AU 8433083			US 1985-749 <b>962</b>	19850701
					13030.01
L4 TI				2006 ACS on STN of silicon nitride	
11	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
D.T.	DD 3400345		10041006	DE 1984-3420347  JP 1983-95651	10040530
ΡI	DE 3420347 DE 3420347	C2	19841206	DE 1984-3420 <b>34</b> 7	19840530
	JP 59222933	A2	19841214	JP 1983-956 <b>51</b>	19830601
	JP 60115232	A2	19850621	JP 1983-222 <b>072</b>	19831128
	NL 8401774	A	19850102	NL 1984-1774 US 1984-616 <b>114</b>	19840601
	US 4529476	A	19850716	US 1984-616114	19840601
L4					
TI	Limit of thermal i	gnition	for a light	-initiated unbranched	d chain reaction
L4	ANSWER 131 OF 214				
TI	Determination of particular molecules	arameter	s of the in	teraction potential o	of polar
	MOTECUTER				
L4	ANSWER 132 OF 214				
TI	Hydrotreating vacus compound	um gas o	ils with ca	talyst and an added o	organic fluorine
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	IIC 4420200		10021212	US 1981-301 <b>754</b>	10010014
L.T.	JP 59202291	A2	19841116	JP 1983-77342	19830430

L4 ANSWER 133 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN

TI	Foamed body of a	resin composition			
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	GB 2110216	A1	19830615	CB 1982-32528	19821115
	JP 58084832	A2	19830521	JP 1981-183349	19811116
	JP 62017613	B4	19870418		
	JP 58087135	A2	19830524	JP 1981-1859 <b>68</b>	19811119
	JP 02030341	B4	19900705		

- L4 ANSWER 134 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Solubility of vinyl chloride, trifluorochloroethylene, difluoroethane, hexafluoropropylene, and hexafluoropropylene oxide in water
- L4 ANSWER 135 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Viscosity of difluoroethane
- L4 ANSWER 136 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Specification and usage requirements for 3AL seamless, aluminum cylinders
- L4 ANSWER 137 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN

11	riddinacion of cac	aryses			
	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	GB 2024642	Α	19800116	GB 19 <b>7</b> 9-2333 <b>8</b>	19790704
	GB 2024642	B2	19820818		
	FR 2430263	A1	19800201	FR 1978-2018 <b>2</b>	19780706
	FR 2430263	B1	19810102		
	CA 1137062	A1	19821207	CA 1979-3263 <b>9</b> 2	19790426
	NL 7905206	A	19800108	NL 1979-5206	19790704
	DE 2927052	A1	19800117	DE 1979-292 <b>7052</b>	19790704
	JP 55011097	A2	19800125	JP 1979-84050	19790704
	JP 62052623	B4	19871106		

- L4 ANSWER 138 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Solvent effects on the distribution coefficients. III. The solubility of some lower fluoro- and chlorohydrocarbons in organic solvents
- L4 ANSWER 139 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Determination of gas-kinetic diameters of molecules of difluoroethane and fluoro-substituted derivatives of ethylene
- L4 ANSWER 140 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Determination of the gas-kinetic diameters of molecules of difluoroethane and fluorine-substituted derivatives of ethylene
- L4 ANSWER 141 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Effect of diffusion on absorption and saturation of infrared radiation in molecular gases
- L4 ANSWER 142 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Study of the thermal conductivity of toluene and some difluoroethanes at high pressures
- L4 ANSWER 143 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Toxicity of aerosol propellants in the respiratory and circulatory systems. VIII. Respiration and circulation in primates
- L4 ANSWER 144 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Effect of diffusion on absorption and saturation of infrared radiation in molecular gases
- L4 ANSWER 145 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Toxicity of aerosol propellants in the respiratory and circulatory systems. VI. Influence of cardiac and pulmonary vascular lesions in the rat
- L4 ANSWER 146 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Cardiopulmonary toxicity of propellants for aerosols

- L4 ANSWER 147 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Solubility of chlorine, hydrogen chloride, difluoro- and difluorochloroethanes in chloroorganic solvents
- L4 ANSWER 148 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Toxicity of aerosol propellants on the respiratory and circulatory systems. III. Influence of bronchopulmonary lesion on cardiopulmonary toxicity in the mouse
- L4 ANSWER 149 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Toxicity of aerosol propellants in the respiratory and circulatory systems. IV. Cardiotoxicity in the monkey
- L4 ANSWER 150 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Identification of absorption lines in gases used to modulate the carbon dioxide laser
- L4 ANSWER 151 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Thermal energy electron attachment rate constants for some polyatomic molecules
- L4 ANSWER 152 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Regeneration of hydrocracking catalysts

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
		<del>-</del>			
ΡI	DE 2249892	A1	19730419	DE 1972-2249892	19721011
	US 3725244	Α	19730403	US 1971-188408	19711013

- L4 ANSWER 153 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Hydrocracking catalyst activation treatment

	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
PΙ	US 3673108	Α	19720627	US 1969-8896 <b>81</b>	19691231

- L4 ANSWER 154 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- II Homopolymers and copolymers of vinylidene fluoride

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
FR 1570233		19690606	FR	
DE 1770672			DE	
GB 1188889			GB	
US 3616371		19710000	US	

---

19640727

- L4 ANSWER 155 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TT Metal oxide films

US 3433868

PΙ

PΙ

11	PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
ΡI	GB 1167128		19691015	GB	
	FR 1572757			FR	
	US 3477936		19690000	US	

- L4 ANSWER 156 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Gas-chromatographic analysis of aerosols by pressurized liquid sampling
- L4 ANSWER 157 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Hair waving, two phase, quick breaking, aerosol foam
  PATENT NO. KIND DATE APPLICATION NO. DATE
- L4 ANSWER 158 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN

Α

TI Concentration of sea water and brine by the gas hydration process. XIV. Pressure and temperature diagrams of mixed hydrating agents

19690318 US 1964-3854**67** 

- L4 ANSWER 159 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Careful removal of acetylene and difluroethane from vinyl fluoride
- L4 ANSWER 160 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
- TI Studies on explosions. I

```
ANSWER 161 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Conversion of hydrocarbons by hydrogen
TI
                                    APPLICATION NO.
                KIND DATE
    PATENT NO.
                                                             DATE
                             -----
                                        -----
                                                              _____
    -----
                             19640117
                                                              19620408
PΙ
    FR 1349148
    ANSWER 162 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Effect of anions on the electrocrystallization of zinc and cadmium
TI
    ANSWER 163 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    The electrochemical fluorination of organosilicon compounds
TT
    ANSWER 164 OF 214 CAPLUS COPYRIGHT 2006 ACS on STN
L4
    Refrigerant mixture of dichlorodifluoromethane and difluoroethane
ΤI
               KIND DATE APPLICATION NO. DATE
    PATENT NO.
                     ----
                             -----
                                        ______
    -----
                            19510417 US
    US 23358
PΙ
    ANSWER 165 OF 214 USPATFULL on STN
L4
      Materials and methods for the conversion of hydrofluorocarbons
TΤ
      US 2005288536 A1 20051229
PI
    ANSWER 166 OF 214 USPATFULL on STN
L4
      Process for making polyurethane and polyisocyanurate foams using
ΤI
      mixtures of a hydrofluorocarbon and methyl formate as a blowing agent
PI
      US 2005277701
                     A1 20051215
    ANSWER 167 OF 214 USPATFULL on STN
L4
ΤI
      Topical spray compositions
                  B1 20051108
PΙ
      US 6962691
    ANSWER 168 OF 214 USPATFULL on STN
L4
      Heat transfer fluids and methods of making and using same
ΤI
PΙ
      US 2005218371 A1 20051006
    ANSWER 169 OF 214 USPATFULL on STN
L4
      Refrigerant composition
TI
PΙ
      US 2005109977 A1 20050526
    ANSWER 170 OF 214 USPATFULL on STN
1.4
      Closed cycle refrigeration system and mixed component refrigerant
ΤI
      US 2005086950
                     A1 20050428
ΡI
    ANSWER 171 OF 214 USPATFULL on STN
L4
      Etchant with selectivity for doped silicon dioxide over undoped silicon
ΤI
      dioxide and silicon nitride, processes which employ the etchant, and
      structures formed thereby
PΙ
      US 6875371
                      B1 20050405
    ANSWER 172 OF 214 USPATFULL on STN
L4
      Heat transfer fluids and methods of making and using same
TI
PI .
      US 2004227125 A1 20041118
   ANSWER 173 OF 214 USPATFULL on STN
L4
TI
      Topical spray compositions
                     A1 20041028
PΙ
      US 2004213744
    ANSWER 174 OF 214 USPATFULL on STN
T.4
TI
      Formulations of mometasone and a bronchodilator for pulmonary
      administration
                      A1 20041007
PΙ
      US 2004198708
    ANSWER 175 OF 214 USPATFULL on STN
L4
ΤI
      Sol-gel-derived halogen-doped glass
PΙ
      US 2004194511 A1 20041007
    ANSWER 176 OF 214 USPATFULL on STN
L4
ΤI
      Materials and methods for the conversion of hydrofluorocarbons
```

```
20040701
PΙ
       US 2004127757
                         Δ1
     ANSWER 177 OF 214 USPATFULL on STN
L4
       Method for plasma etching performance enhancement
TΙ
       US 2004072443 A1
                              20040415
PΙ
                         B2
                               20041221
       US 6833325
     ANSWER 178 OF 214 USPATFULL on STN
L4
       Methods for etching photolithographic reticles
TI
                       A1
                               20040415
       US 2004072081
PΙ
     ANSWER 179 OF 214 USPATFULL on STN
L4
       Etchant with selectivity for doped silicon dioxide over undoped silicon
ΤI
       dioxide and silicon nitride, processes which employ the etchant, and
       structures formed thereby
                               20031030
PΙ
       US 2003203639
                         A1
     ANSWER 180 OF 214 USPATFULL on STN
L4
       Etchant with selectivity for doped silicon dioxide over undoped silicon
TТ
       dioxide and silicon nitride, processes which employ the etchant, and
       structures formed thereby
                               20030325
PΙ
       US 6537922
                         B1
     ANSWER 181 OF 214 USPATFULL on STN
L4
       Variable load refrigeration system particularly for cryogenic
TI
       temperatures
PΙ
       US 6426019
                          B1
                               20020730
     ANSWER 182 OF 214 USPATFULL on STN
T.4
       Formulations of mometasone and a bronchodilator for pulmonary
TI
       administration
       US 2002076382
                        A1 20020620
PΙ
     ANSWER 183 OF 214 USPATFULL on STN
T.4
       Substrate cleaning apparatus and method
ΤI
                       A1
       US 2002072016
                              20020613
PΙ
       US 6692903
                         B2
                               20040217
L4
     ANSWER 184 OF 214 USPATFULL on STN
       Apparatus for providing ozonated process fluid and methods for using
TI
       same
                        A1 20020606
PΙ
      US 2002066717
L4
     ANSWER 185 OF 214 USPATFULL on STN
       Lubricant refrigerant composition for hydrofluorocarbon (HFC)
ΤI
       refrigerants
       US 6374629
PΙ
                         B1
                               20020423
     ANSWER 186 OF 214 USPATFULL on STN
L4
       High-density plasma etching of carbon-based low-k materials in a
TI
       integrated circuit
PΙ
      US 6284149
                         B1 20010904
     ANSWER 187 OF 214 USPATFULL on STN
T.4
       Flower-like capacitor structure for a memory cell
TΤ
PΤ
       US 6281542
                        B1 20010828
     ANSWER 188 OF 214 USPATFULL on STN
T.4
       Etchant with selectivity for doped silicon dioxide over undoped silicon
TI
       dioxide and silicon nitride, processes which employ the etchant, and
       structures formed thereby
ΡI
      US 6117791
                               20000912
     ANSWER 189 OF 214 USPATFULL on STN
L4
ΤI
      Aerosol cosmetic compositions, aerosols containing them and uses
PI
      US 6113923
                              20000905
    ANSWER 190 OF 214 USPATFULL on STN
T.4
ΤI
       Fluorine assisted stripping and residue removal in sapphire downstream
```

plasma asher PΙ US 6082374 20000704 ANSWER 191 OF 214 USPATFULL on STN L4Variable load refrigeration system particularly for cryogenic TI temperatures 20000620 PΤ US 6076372 ANSWER 192 OF 214 USPATFULL on STN L4Process for the reduction of chlorofluorocarbons and production of TI derivatives thereof in an electrolytic cell, cell for carrying out said reduction and process for removing the by-products formed within the cell US 6068756 20000530 PΤ WO 9724162 19970410 ANSWER 193 OF 214 USPATFULL on STN L4Fixative vinyl acetate tetrapolymers TΙ US 5830439 19981103 PΙ ANSWER 194 OF 214 USPATFULL on STN L4 Method for etching dielectric using fluorohydrocarbon gas, NH.sub.3 TI -generating gas, and carbon-oxygen gas 19980929 US 5814563 PΙ ANSWER 195 OF 214 USPATFULL on STN L4 Spray formulation for the testing of smoke detectors ΤI 19980728 US 5785891 PΙ ANSWER 196 OF 214 USPATFULL on STN L4Antiperspirant aerosol composition with high solids content ΤI PΙ US 5605682 19970225 ANSWER 197 OF 214 USPATFULL on STN L4 Hydrogen fluoride dopant source in the preparation of conductive coated TI substrate US 5496583 19960305 PΙ ANSWER 198 OF 214 USPATFULL on STN L4ΤI Working fluid containing difluoroethane PΤ US 5433879 19950718 ANSWER 199 OF 214 USPATFULL on STN L4TI Manufacture of rigid foams and compositions therefor PΙ US 5391584 19950221 ANSWER 200 OF 214 USPATFULL on STN 1.4 Topical medicinal pressurized aerosol compositions and method of ΤI preparation, method of use and article of manufacture thereof PΙ US 5378451 19950103 ANSWER 201 OF 214 USPATFULL on STN Gaseous doping of tungsten oxide TI PΙ US 5324537 19940628 ANSWER 202 OF 214 USPATFULL on STN T.4 TIWorking fluid PΤ US 5304319 19940419 ANSWER 203 OF 214 USPATFULL on STN TI Anti-reflective coatings comprising light metal fluorides US 5208101 19930504 PΙ ANSWER 204 OF 214 USPATFULL on STN L4Process for etching TI ΡI US 5110408 19920505 ANSWER 205 OF 214 USPATFULL on STN L4 TT Process for the preparation of polyurethane rigid foams having a low

thermal conductivity and their use PΙ US 5096933 19920317 ANSWER 206 OF 214 USPATFULL on STN L4 Production of ion beams by chemically enhanced sputtering of solids TIUS 5089746 19920218 PΙ ANSWER 207 OF 214 USPATFULL on STN L4 Process for restoring deactivated catalysts ΤI 19900626 US 4937215 PΙ ANSWER 208 OF 214 USPATFULL on STN L4Process for protecting electrochemical sensors from biofouling in an ŢΙ aquatic environment US 4763537 19880816 ΡI ANSWER 209 OF 214 USPATFULL on STN L4Aerosol waterproof sunscreen compositions TI US 4686099 19870811 PΙ ANSWER 210 OF 214 USPATFULL on STN L4 Preparation of non-flammable aerosol propellant microemulsion system TI 19870407 US 4655959 PΙ ANSWER 211 OF 214 USPATFULL on STN L4Non-flammable aerosol propellant microemulsion system TI 19850820 US 4536323 PΙ ANSWER 212 OF 214 USPATFULL on STN L4Gas for selectively etching silicon nitride and process for selectively TI etching silicon nitride with the gas 19850716 PΙ US 4529476 ANSWER 213 OF 214 USPATFULL on STN **L4** Hydrotreating vacuum gas oils with catalyst and added organic fluorine TI compound US 4420388 19831213 PΙ ANSWER 214 OF 214 USPATFULL on STN L4HYDROCRACKING CATALYST ACTIVATION TREATMENT ΤI

19720627

PΙ

US 3673108